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Rochester Institute of Technology

**A SIMULATION STUDY OF DISPATCHING RULES AND REWORK STRATEGIES IN
SEMICONDUCTOR MANUFACTURING**

A Thesis

**Submitted in partial fulfillment of the
requirements for the degree of
Master of Science in Industrial Engineering**

in the

**Department of Industrial & Systems Engineering
Kate Gleason College of Engineering**

by

Gregory R. Laubisch

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KATE GLEASON COLLEGE OF ENGINEERING
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Master of Science degree

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A Simulation Study of Dispatching Rules and Rework Strategies in Semiconductor Manufacturing

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ABSTRACT

The semiconductor industry is fast paced and on the cutting edge of technology, resulting in very short life spans of semiconductor products. In order to stay competitive, manufacturers must be able to quickly adapt to produce new products, and they must achieve a high level of productivity. Two major operational components of semiconductor fabrication plants (fabs) that effect productivity are dispatching rules and rework strategies. Although prior research has been conducted independently on these two issues, the hypothesis is that the interrelationship between the dispatching rules and rework strategies has a significant effect on the productivity of the fab. Moreover, the goal is to determine which combination of widely-used dispatching rules and new and existing rework strategies results in the highest level of fab productivity. To test this hypothesis, the significance of rework is evalutated, and a four-factor experiment is conducted to determine the effect of dispatching rules, rework strategies, fab types, and rework levels on key fab performance measures. Five dispatching rules are combined with three previously studied rework strategies and the first bottleneck strategy which is developed in this study. The treatment combinations are compared based on fab performance measures including cycle time, percentage on time, work-in-process, and the XTheoretical value. Simulation models based on actual fab data are constructed to carry out the experiments. The detailed results of the experiment show that combinations of dispatching rules and rework strategies have a significant impact on fab performance measures at each rework level in both fab types. In general, two dispatching rules, rework priority and first-in-first-out, in combination with the first bottleneck rework strategy perform the best. Further analysis concludes that the rework priority dispatching rule and the first bottleneck rework strategy result in the highest level of fab performance and are most robust over alterative fab configurations.

TABLE OF CONTENTS

1. INTRODUCTION	1
2. PROBLEM STATEMENT	3
3. LITERATURE REVIEW	6
3.1 Semiconductor versus Traditional Manufacturing.....	7
3.2 Overview of Semiconductor Fabrication Processes	8
3.3 Semiconductor Research Using Simulation.....	13
3.3.1 Rework Strategies	14
3.3.2 Dispatching Rules	18
3.3.3 Order Release and Dispatching Rules.....	29
3.3.4 Order Release and Dispatching Rules with Rework.....	32
4. THE SIGNIFICANCE OF REWORK.....	34
4.1 Fab Description	34
4.2 Simulation Model.....	37
4.3 Verification and Validation.....	38
4.4 Analysis Methodology	39
4.5 Experimentation and Analysis	39
4.6 Summary	40
5. A STUDY OF DISPATCHING RULES AND REWORK STRATEGIES	41
5.1 Methodology	42
5.1.1 Experimental Design.....	42
5.1.2 Performance Measures.....	46
5.1.3 Simulation Modeling	48
5.1.3.2 Modeling the Make-to-Stock Fab	49
5.1.4 Statistical Analysis Methods.....	53
5.2 Analysis of Results	57
5.2.1 Split Strategy Results.....	57
5.2.2 Percent Idle Performance Measure	58
5.2.3 Four Factor Analysis.....	59
5.2.4 Analysis of the Make-to-Order Fab	59
5.2.5 Analysis of the Make-to-Stock Fab	63
5.3 Performance of the CR, EDD, and SPT Dispatching Rules	66
5.4 Analysis of Robust Strategies	68
5.4.1 Two Factor Analysis to Determine Robust Strategy in Each Fab Type	68
5.4.2 Two Factor Analysis to Determine Robust Strategy Overall	69
5.5 Summary	71

6. CONCLUSIONS & RECOMMENDATIONS FOR FUTURE RESEARCH	73
6.1 Conclusions.....	73
6.2 Recommendations for Future Research.....	74
6.2.1 Discrimination between Top Strategies.....	74
6.2.2 New Methods for Determining First Bottleneck	75
6.2.3 Alternative Dispatching Rules	75
6.2.4 First Bottleneck Validation.....	76
REFERENCES	77
APPENDECIES.....	80
Appendix A. Results of Rework Strategy.....	80
Appendix B. Experimental Data	81
Appendix C. Four Factor ANOVA Results	83
Appendix D. MTO Three Factor ANOVA Tables	86
Appendix E. MTO Two Factor ANOVA and Tukey Pairwise Comparison Results	88
Appendix F. MTS Three Factor ANOVA Tables.....	98
Appendix G. MTS Two Factor ANOVA and Tukey Pairwise Comparison Results	100
Appendix H. Two Factor MTO ANOVA Tables: Determination of Robust Strategies.....	110
Appendix I. Two Factor MTS ANOVA Tables: Determination of Robust Strategies.....	112
Appendix J. Two Factor ANOVA and Tukey Analysis to Determine Robust Strategies Overall.....	114
Appendix K. Fab Description	117

1. INTRODUCTION

Semiconductor manufacturing refers to the production of integrated circuits, or devices. These devices have many functions, from simple transistors to memory chips and processors. Nearly everyone relies on such devices every day, whether they realize it or not. Some common places semiconductor devices are found are in computers, cellular phones, and automobiles.

Semiconductor devices are manufactured on silicon substrate material commonly referred to as a wafer. On the surface of each wafer are the integrated circuits (chips) that are formed during production. There can be hundreds of chips on a single wafer. These wafers travel through the semiconductor fabrication plant (fab) in lots, typically made up of 25 or 50 wafers.

Typically, the amount of processing that the device endures increases as the circuit design becomes more complex, and it is common for a wafer to go through three hundred or more processes during production. During this time, wafers may enter the same process, such as lithography, thirty or more times. The idea of going through the same process multiple times is referred to as re-entrant flow. Also, because of the high level of precision that the processes must adhere to, mistakes can be made and some wafers must be reworked, adding to the complexity of the fab. Therefore, there can be multiple products at various stages of fabrication (that is, at different masking layers) and wafers needing rework all waiting in the same queue. Furthermore, some stations process wafers individually, some process entire lots, and some process several lots simultaneously (batching). All of these things make the study and analysis of fabs very difficult.

For semiconductor manufacturers to stay competitive, they must be able to properly make decisions. Making these proper decisions allows them to quickly adapt to produce new products in a profitable manner, as the technology governing this industry changes daily. The importance

making the proper decisions is apparent when considering that the value of a finished wafer is at least \$10,000 (Berkeley 2003). If the decisions used allow the fab to produce even one more lot per day, that would increase daily revenue by \$240,000 - \$500,000.

Two decisions that must be made in semiconductor manufacturing are what dispatching rule and rework strategy to use. Dispatching rules determine which lot is processed next from a queue when there is more than one lot waiting. Rework strategies define the relationship between the wafers from the lot that need rework, and those that do not need rework, as usually rework is not required for the entire lot. The term mother lot refers to the portion of the lot that does not need rework, and the term child lot refers to the portion of the lot that needs rework. An example of a rework strategy is to hold the mother lot while the child lot is being reworked, and then combine the two lots for all further processing (Zargar 1995).

There are many different dispatching rules and rework strategies that are used in fabs throughout the world. Fabs choose dispatching rules and rework strategies based on how they effect key performance measures, such as throughput, cycle time and its variability, and on time delivery. Much research has been undertaken focusing on dispatching rules and rework strategies independently. The result of these studies shows that choosing appropriate dispatching rules and rework strategies can greatly effect the performance of a fab and are essential for efficient and profitable production (Sheng-Yuan et al. 2001). This research focuses on how the interaction of dispatching rules and rework strategies effect performance measures. As small improvements in fab performance can have a large economic impact, an optimal combination of a dispatching rule and a rework strategy would be of great value to the semiconductor industry.

2. PROBLEM STATEMENT

Modern day fabs must be able to manufacture semiconductor devices in an efficient manner to stay competitive. In order to do this, proper decisions must be made to maximize the productivity of the fab. Simulation has been the main tool used in research to test different operational decisions in fabs. The goal of such studies has been to develop rules and strategies that can be implemented in a full production fab. In order to validate these rules and strategies for such a purpose, all components of a realistic production fab must be accurately modeled. One of these components is rework. Reworking wafers adversely affects the performance of a fab, but is necessary because of the high costs associated with scrapping a wafer. However, the importance of including rework in simulation modeling has been inconclusive.

Since rework is present in fabs, determining how significant of an effect that rework has on the performance of a fab is important. If the presence of rework is shown to make significant differences in the performance of a fab, ways to lessen the detrimental effects that rework causes should be explored. Two major operational decisions that previous research has targeted are dispatching rules and rework strategies. Past research has explored these two decisions independently and has shown that choosing effective dispatching rules and rework strategies can lessen the adverse impact of rework in fabs. Therefore, these rules and strategies become important to the overall productivity (and thus profitability) of the fab.

The goal of this thesis is to determine if the presence of rework significantly affects the performance of a fab, and consequently to investigate how a combination of a rework strategy and dispatching rule at different rework levels and in different fab types affect key fab performance measures. Moreover, it is of interest to determine if there is a combination of a

rework strategy and a dispatching rule that is robust or if not, which combinations are best for various fab types and rework levels.

Simulation is used to execute a four-factor experiment, using dispatching rules, rework strategies, rework levels, and fab types as the factors. Realistic fab data is used to construct the simulation models and conclusions are formed based on detailed statistical analysis of the experimental results. One of the fab setups represents a make-to-order fab and the second fab represents a make-to-stock manufacturing environment. The rework data for each fab is set to three levels; one, five, and ten percent at all steps containing rework. Dispatching rules that are used include first-in-first-out (FIFO), shortest processing time (SPT), earliest due date (EDD), critical ratio (CR), and rework priority (RWK).

Four rework strategies are tested. The wait strategy holds the mother lot at the rework step until the child lot has gone through all rework steps, then the mother lot and child lot are combined for all further processing (Zargar 1995). The second strategy, the split strategy, permanently splits the mother lot and the child lot, therefore allowing the mother lot to continue processing while the child lot is being reworked (Zargar 1995). The next rework strategy that is tested is the rendezvous strategy, which splits the mother lot and the child lot, allowing the mother lot to go through the next processing step. After the mother lot goes through the next processing step, it is held there until the child lot has been reworked and goes through the next processing step, at which point they are combined for all further processing (Sha et al. 2001).

The last strategy, named the first bottleneck strategy, is developed in this research and splits the mother lot and child lot when rework occurs. The mother lot then goes thorough all processing stations until it reaches the first bottleneck station. The mother lot then waits to be processed at this bottleneck station until the child lot catches up to it, then the two are combined

for all further processing. The rework strategies and dispatching rules are evaluated based on fab performance measures including average cycle time, standard deviation of cycle time, percentage on time, percent idle, average work in process (WIP), and average XTheoretical (XT) value.

3. LITERATURE REVIEW

The semiconductor industry is an extremely fast paced, technology driven industry that is always changing. Currently it is at another major turning point in an attempt to take its technology to a new level when many companies increase their wafer size from 200mm to 300mm (sizes refer to the diameter of the wafer). This move should immensely improve the throughput for manufacturers, as a 300mm wafer can have more than twice the number of chips as a 200mm wafer (Aalund and Mathia 2001). Two of the main determinants of success in a fab are the ability to rapidly change to newer technologies and keep deliveries on time (Mittler and Schoemig 1999). The ability to do these things are closely related to being able to keep cycle times low which in turn keeps the fab more flexible to the volatile industry. This is magnified as the average life cycle of semiconductor product is roughly six months (Qi and Tang 2002).

In the semiconductor industry it is important to understand the relationships between WIP, utilization, yield, and time in the system. It is obvious that the more WIP a fab has the higher its machine utilization is as there are always lots waiting to be processed at each machine. This may seem like a good thing, but by overloading the system with WIP, for a given throughput rate (λ) the cycle time (w) is increased proportionally to the increase in WIP (L) as proven by Little's Law (Hopp 2001):

$$L = \lambda w .$$

This causes the fab to be rather inflexible to changes in demand and technology, as it takes a long time to get lots through the system. This is also major problem in the semiconductor industry because cycle time directly affects the quality of the wafer. The longer a wafer is on the floor, the more chance it has to become contaminated and consequently scrapped or sent for rework (Miller 1990).

3.1 Semiconductor versus Traditional Manufacturing

Semiconductor manufacturing deals mostly with high volume, low product mix production. This sort of mass production is traditionally characterized by an assembly line setup in a manufacturing plant where a station carries out the same process on the same or similar product all the time (Hopp 2001). Also, in a traditional assembly line, material moves down the line, therefore once it has gone through a certain station, it most likely will not return to that station for processing again. This is not at all the case in semiconductor manufacturing.

Fabs are much more complex than the traditional manufacturing plant. The greatest difference comes with the idea of re-entrant flow. A typical wafer must go through over three hundred process steps at a relatively small number of process stations before it becomes a finished product. This means that the lots enter the same process many times and are also moving about the manufacturing floor in a rather chaotic manner. To add to the difficulty, lots are batched in some operations to gain efficiencies in scale (i.e. oxidation), yet go through some processes, such as photolithography, as single wafers. A further cause of difficulty is the large number of different products that a fab produces simultaneously. The setup for the same machine can be different for each product and performing the setups can be time consuming and costly.

Another main reason for fab complexity is the cutting edge nature of the silicon wafer industry. New state-of-the-art machines are frequently being tried out in the line to test their capabilities and can disrupt the normal production flow. Also, because of the demanding nature of wafer specifications, machine downtime for adjustment and calibration is high. Resulting from these tight specifications is the need for some wafers to be reworked or even scrapped.

It is also important point to understand the extreme cleanliness that all of the processes must adhere to. Clean rooms are held to standards 1000 times more exacting than those of hospital rooms (Microelectronics 101 2002), and a single particle of smoke can ruin an entire wafer. Highly automated material handling systems minimize the need for human hands to interact with wafers during the process, and some fabs are now almost completely automated.

Lastly, the short product life of a wafer is a main contributor to the difficulty of wafer fabrication. Because of the intense pace of the industry, better components and processes are introduced quite often and this leads to changes in the product flow, routings, and also to the manufacturing equipment itself. As a result of the rapid development of wafer technology, in some fabs, research and development wafers with a high priority are sent through the manufacturing line and tie up resources that would otherwise be working on production wafers. In addition, much of the time it is hard to predict what the demand for a product will be at some period in the future. Therefore, it is not wise to build up large quantities of stock in such a volatile industry.

3.2 Overview of Semiconductor Fabrication Processes

This section gives an overview of the basic processes that are used in the production of silicon wafers. Unless specified otherwise, the primary source of this information was gathered from Jaeger (1993).

Silicon is the main material used for the production of integrated circuits, which are built on thin, circular frames called wafers. Currently, most wafers are being produced at 200mm (~8in.) in diameter and some companies are now in full production with 300mm (~12in.) fabs.

Wafers cycle through a set of processes many times in order to reach their finished state. These processes include:

- Oxidation
- Photolithography
- Etching
- Diffusion/Ion Implantation
- Chemical Vapor Deposition (CVD)/Evaporation/Sputtering
- Epitaxy

Oxidation is generally the first step in the wafer production. It involves the heating of a wafer in an oven at high temperatures to form a silicon dioxide layer on the surface of the wafer. To accomplish this, wafers are baked in either pure oxygen or water vapor, which act as the reactants that form the layer of silicon dioxide. Wafers are placed in the oven in batches to maximize the efficiency of this operation.

Photolithography (see Figure 3.1), next in the process, is the term used to describe all of the steps involved in transferring a pattern from a mask to the surface of the silicon wafer. After the silicon dioxide layer is formed, the wafer is thoroughly cleaned with an agent such as deionized water or hydrofluoric acid to remove any surface impurities. A photoresist is then applied and uniformity of thickness is achieved by spinning the wafer at high speeds in a process called coating. The wafer then goes through a soft baking process whose purpose is to improve photoresist adhesion to the silicon dioxide.

After the photoresist is applied, a photomask is placed onto the surface of the wafer. The photomask is used as a means of showing the future integrated circuit pattern. The photoresist that is not covered by the mask is exposed to high intensity ultra violet light in a stepper tool.

Next is a hard bake step to improve the adhesion between the unexposed photoresist and the silicon dioxide below it. The last step is called the developing step where the exposed photoresist is removed with a developing agent. Each time wafers go through photolithography, a new layer is formed. The amount of layers that are necessary for semiconductor devices varies greatly with the complexity of the device, as each layer plays an integral role in its functionality.

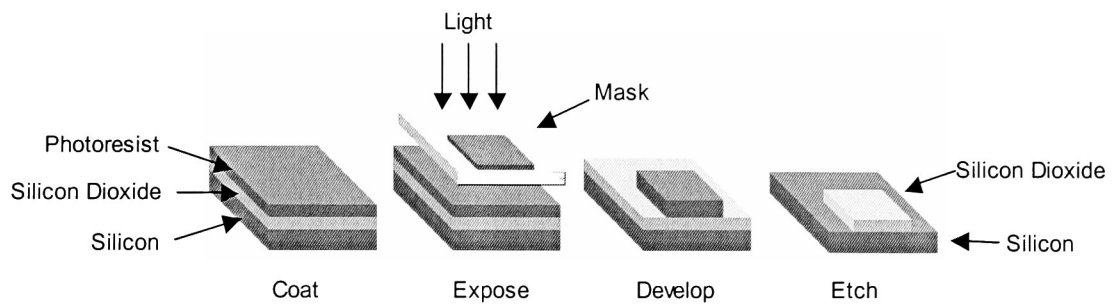


Figure 3.1. The Steps of Photolithography (www.ece.gatech.edu)

Following photolithography is an etching process that removes the silicon dioxide not protected by the photoresist. A couple different methods of etching are available, but the main techniques are wet and dry etching. Wet etching uses a chemical, which, when at room temperature, attacks and removes the silicon dioxide much faster than it attacks the exposed photoresist. Dry etching uses gases to remove the silicon dioxide while leaving the exposed photoresist still adhered to the silicon dioxide. After the etching is completed, an ashing step is carried out in which the remaining photoresist is removed leaving a silicon dioxide pattern and the rest of the silicon wafer exposed.

The next step for the wafer is a diffusion process that introduces conductive material (dopants) into the silicon lattice to change the electrical characteristics of the wafer's layers. The dopants that are commonly used are boron and phosphorous. There are two common ways that this process is carried out; by a spin-on dopant, or by a gaseous dopant. With the spin-on

method, the dopant is applied and the wafers are spun at high speeds to ensure uniformity across the wafer. The wafer is then heated at high temperatures to diffuse the impurities to a desired depth into the wafers surface. The gaseous method is similar, but instead of using a spin-on dopant, the wafer is placed in an oven with the dopant being an ambient gas flowing through the oven. The heating causes the impurities, which are in a gaseous form, to diffuse into the wafer's silicon crystal structure. Diffusion is a temperature dependent process, and therefore can occur at many different rates, but slow rate diffusion offers the most control and repeatability of the process.

Ion implantation can be used to perform the same function as diffusion. In ion implantation, the impurity atoms are shot into the surface of the wafer with a particle accelerator. There are some disadvantages of ion implantation. Wafers can only be implanted one at a time, while diffusion can process a batch of wafers simultaneously. Also, ion implantation causes damage to the lattice structure of the silicon and a subsequent annealing step must be done to repair the damage. Ion implantation is advantageous over diffusion as it allows for more precise doping through the control of the particle accelerator beam. Another advantage is that this process is done at low temperatures, preventing the undesired spreading of the impurity.

Thin film deposition refers to various materials that are required to be deposited on the wafer in many steps of wafer fabrication. Two of the methods of deposition are evaporation and chemical vapor deposition (CVD). Evaporation involves materials being heated to the point of vaporization, and are then evaporated on the wafer's surface. CVD is quite a bit different, as it forms the layer by directly applying the desired material from its gaseous state to a solid. Another form of deposition is sputtering, where the wafer's surface is bombarded with chosen ions. Sputtering is commonly used to form the gate and the source and drain contacts.

The last process to be discussed is epitaxy, which is the growth of a silicon crystal layer that is the same as the underlying lattice structure. This is done to create an ultra pure, contaminate free crystalline layer to enhance the performance of complex devices. This layer is deposited with a specific thickness and resistivity based on the customer demands (Epitaxy 2003).

The processes that are used in wafer manufacturing must be monitored closely to ensure that they meet the tight specifications placed upon them. When something goes wrong during processing, the effected wafers must be considered for rework, as scrapping them is extremely costly to the manufacturer, especially when they are far into production. While some defective wafers must be scrapped, most of the time defects caused at photolithography stations can be reworked. These defects are mainly caused by coating problems, focus and exposure defects, developer defects, edge-bead removal problems, contamination, and scratches (Ashkenaz 2002). When a wafer needs rework at the photolithography stations, it must go through an etch process to remove the resist, and then go through the photolithography steps again. This series of steps is commonly referred to as a rework loop (see Figure 3.2).

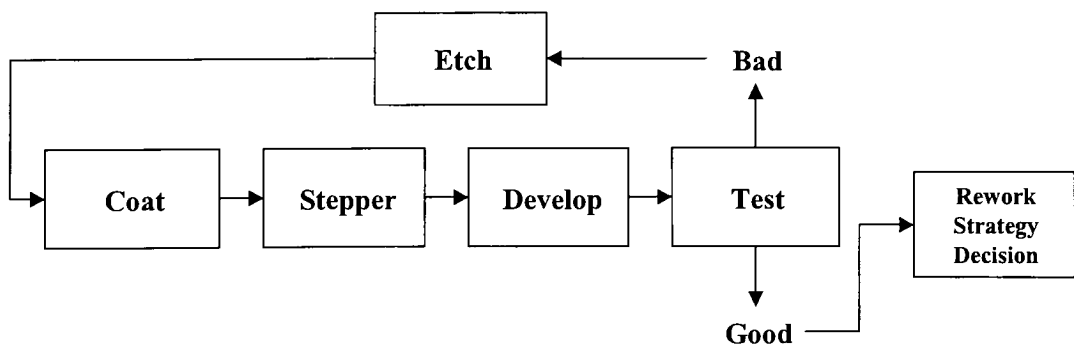


Figure 3.2. Typical Lithography Rework Loop

The presence of rework intuitively increases the cycle time and processing costs for not only the wafers being reworked, but for all of the wafers in the fab. Those increases must be

compared with the increased yield due to reworking nonconforming wafers. Since wafers are very expensive and each processing step adds value to the wafer, it is usually beneficial to rework wafers when possible. Also, many fabs produce wafers to order, therefore if a wafer has to be scrapped during production, a new wafer must be started and go through processing as a small lot, decreasing efficiencies gained by producing full lots.

3.3 Semiconductor Research Using Simulation

There are enormous amounts of rules and decision-making techniques that can govern the way that a manufacturing operation controls its floor. As stated in “The Goal” by Goldratt, the overall goal of any manufacturing operation is to make money; therefore key decision rules should developed around this specific goal. There are no closed form solutions to decide what dispatching rule or rework strategy to use in a particular fab because of the complexity and variability of the fabrication process. Simulation is the main tool used to compare and contrast these rules and strategies, as its main purpose is to analyze complex systems that contain variability. This makes simulation a great tool to use to test different rules in various scenarios and draw valid conclusions from the resulting data. Much research has been conducted that utilizes simulation in the semiconductor area, mainly dealing with dispatching rules, order release rules, and rework strategies.

Dispatching rules are decisions that determine the order that product will be processed from a queue. The purpose of these rules is to promote the efficient and profitable flow of product. Simple examples of dispatching rules are FIFO and SPT. FIFO dictates lots to beprocessed in order of their arrival while the SPT rule sends the product that has the shortest processing time on that given machine to the front of the queue. Other common dispatching rules

are based on: order of entry into the queue, how long a product has been in queue, when the product's due date is, how much processing time the product has left, how the tool is currently setup, etc. The method of determining what will be processed next from the queue can greatly alter key performance measures governing the overall efficiency of the fab and should be closely analyzed.

A literature review of relevant research done in the area of dispatching rules and rework strategies is conducted. Much of the early literature on dispatching and order release rules (rules governing when to release product into the fab) does not include rework in the modeling. Unfortunately there are not many reasons given to substantiate these claims. For instance, Collins, Torsina, and Balgemann (1999) assume that rework and scrap are not significant and are therefore omitted in their study. More recent research has included rework and has determined that rework does have an effect on some key performance measures in fabs. A study done by Grewal et al. (1999) focusing on validating cycle times discusses how sensitive the simulation results are to the rework level. The following literature review is divided into the following four areas:

1. Wafer Rework Strategies;
2. Dispatching Rules;
3. Order Release and Dispatching Rules; and
4. Order Release and Dispatching Rules with Rework.

3.3.1 Rework Strategies

As discussed previously, wafer rework strategies decide the relationship between rework wafers (child lot) and rest of the lot (mother lot) when rework occurs. Zargar (1995) researches

ways to deal with rework in the queue with respect to cycle time. The following four ways of dealing with rework are discussed:

1. Hold the mother lot while the child lot is reworked, and combine the two lots before moving it to the next processing station. The child lot gets priority in the rework loop.
2. Move the mother lot on, and send the child lot through the rework loop. The child lot does not have priority in queue, and then the child lot becomes a mother lot when the rework is completed.
3. Move the mother lot on, and introduce a new lot composed of numerous child lots when a predefined number of wafers have accumulated. These combined child lots then become a single mother lot.
4. Move the mother lot on, and add the child lot to the next mother lot of the same product at the tool.

There are positive and negative points concerning each of the strategies. The first strategy is favorable to management for tracking reasons, as the wafers continue on the same boat with the same lot throughout processing. The obvious downside is that the mother lot loses processing time while the wafers are reworked, and the cycle time of all lots will increase when queuing priority is given to the child lot in the rework loop. The second strategy allows the mother lot to continue processing, and since priority is not given to the child lot, the cycle time of other lots is effected to a lesser extent than with the first strategy. However, with this strategy, small lots are created and efficiencies associated with large lot sizes cannot be exploited. This strategy also makes tracing lots difficult.

The third strategy is like the second, except the efficiencies are not lost. However, the cycle time of the child lot is dramatically increased, as it must wait for a certain amount of

wafers of the same product type and at the same lithography step to accumulate before it can be processed. Tracking lots also becomes extremely difficult as wafers from many different lots are being combined. The fourth strategy attempts to balance the pros and cons of the previous strategies as efficiencies in scale are not lost and child lots should not have to wait very long before being joined with a mother lot. However, as Zargar points out, this strategy is not practical for use in the semiconductor industry. The main reason for this is that wafers travel in “boats” in the fab that are usually full, therefore there is no extra space for reworked wafers to join a mother lot. Leaving extra space in a boat in hope that the lot will pick up reworked wafers during processing is very risky, as throughput is lost if there is extra space at the end of processing. Tracing wafers is also difficult with this strategy.

This research uses a fairly simple fab model with three products, all of which have the same process flow and processing times. However, they cannot be processed together. Also, with the fourth strategy, lot size was not used as a constraint when adding the reworked wafers to the mother lot. Lastly, there were no machine failures allowed.

From the study, even in a small fab, it is shown that the rework strategy chosen can greatly alter the products cycle time. The conclusion drawn is that the fourth strategy decreases the average cycle time the most. While this is a significant conclusion, as previously discussed, this strategy is difficult to implement in a fab.

Sha et al. (2001) attempt to critique the work done by Zargar (1995) by highlighting the disadvantages of his strategies and also introduce two alternative strategies to deal with rework. Five strategies, three from Zargar (1995) and the two new strategies, are evaluated with respect to total cycle time, the quantity of WIP, machine utilization, and queue length at photolithography stations. Zargar’s strategies that are used are the first, second, and fourth (see

above). The two new strategies that are introduced are the lot staging strategy and the rendezvous strategy. The lot staging strategy is similar to Zargar's third strategy except the child lots are reworked, and then wait for a certain number to accumulate before moving on. Child lots are not given priority in queue with this strategy. With the rendezvous strategy, the mother lot goes on for processing at the next station, then waits there for the child lot to be reworked and processed at the next station. The child lot is given priority, or "hot lot" status during the rework steps. The mother and child lot are then combined for all further processing. This strategy aims to lessen the amount of time that the mother lot waits for the child lot to be reworked, and is also good for wafer tracking purposes.

The fab that is used for simulation is based on the line introduced by Wein (1988), and consists of 24 stations. The simulation software AweSim is used to build the model, and each strategy is run for thirty replications for throughputs of 300, 400, and 500 lots. Lots are released into the fab using a poisson arrival process, and the FIFO dispatching rule is used at all stations. Processing times, machine failures, and machine repair times are all exponentially distributed.

A detailed analysis is done on the performance measures listed above and in all cases the rendezvous strategy is the superior strategy. Hypothesis tests are then conducted to show that there is a statistically significant difference between the rendezvous and Zargar's fourth strategy, which shows the second best results. The tests show the differences are significant at a 95 percent confidence level for all statistics except the waiting time in photolithography. This study concludes that the proposed rendezvous strategy is the best option for this for dealing with rework in the studied fab, as it has the best performance and makes lot tracing fairly simple.

3.3.2 Dispatching Rules

As stated previously, the purpose of a dispatching rule is to optimize key performance measures of a system by ensuring the efficient flow of product. The most typical performance measures looked at in semiconductor fabs are machine utilization, product yield, throughput, and cycle time (Mittler and Schoemig 1999, 709). Other performance measures that are commonly looked at are the variability of cycle time and the percentage of on time deliveries (Rose 2002 and Mittler et al. 1999). Certain dispatching rules are geared to the improvement of a given performance measurement. A good example of this is how using an EDD rule tends to improve on time delivery. While this may be true, it may also be negatively effecting other performance measures, such as cycle time. As a result of this effect, a combination of key performance measures should be analyzed when picking an optimal dispatching rule.

There is sound logic behind all proposed dispatching rules, yet some fit certain situations much better than others. This can be seen by comparing the FIFO and SPT rules, as there are obvious benefits and downsides to each. With the FIFO rule, a job may be in the back of the line, but it may be the most important job to get through that machine. That job has to wait for all lots in front of it to be processed. An advantage to FIFO is that lots will not get stuck in queue for large amounts of time because lots are processed in order of arrival. The SPT rule maximizes the throughput of the station as it always processes the job with the shortest processing time. However, it has trouble when there is a wide range of processing times for products in queue. In this case, jobs with large processing times may sit in queue for a very long time before being processed. One rule that can be used to combat the SPT problem is called SPT^x (also known as absolute waiting time limit (AWTL)). This states that the “job to be worked next will be the one with the shortest processing time unless a job has waited x time units

or longer, in which case it becomes the next job” (Hopp, 2001). It can be seen from this simple example that choosing a dispatching rule tailored to the specific needs of the manufacturing floor and processing station is instrumental to profitable product flow.

Arzi and Raviv (1998) discuss how the performance of a re-entrant production line with sequence dependent setup times can be improved with real-time dispatching rules. An extensive experiment is conducted to study the effect of four different dispatching heuristics on the performance measures of throughput, total setup time, and work in process (WIP).

The model constructed is based on two workstations, lithography and all of the other stations combined into one. When the machine finishes processing, a dispatching rule is used to determine what job is processed next. Then, all of the waiting jobs of chosen type are processed. This type of rule is useful at stations that have large setup times required when changing the product being processed.

The four dispatching rules studied are marginal set-up time, marginal set-up time with look ahead, marginal set-up with grouping principle, and marginal set-up time with grouping principle and look ahead. Marginal set-up time is a ratio of the set-up time for job j divided by the number of job j in queue. These ratios are calculated for each job, and the minimum ratio is chosen for dispatching. Choosing the minimum ratio allows the job with a small set-up time or with a large amount of jobs in queue to be processed next. Look ahead takes the total processing time for all of job j to be processed and uses this time to determine how many jobs of type j will arrive in this time. The jobs that will arrive during processing are added to the amount of jobs in the ratio calculation. The grouping principle looks to combine jobs with relatively short set-up times between the jobs, and these groups are then looked at as single jobs. As with the look ahead rule, all of the jobs in the group are added to the amount of jobs in the ratio calculation.

The marginal set-up time with grouping and look ahead is simply a combination of all three and uses the same ratio to determine what is processed next.

The simulations are run using SIMAN IV for a six-week production week with a warm-up period of twelve weeks. Two commonly used dispatching rules were also tested, FIFO and improved FIFO. Improved FIFO chooses the first job in queue unless there is a machine already running that job type, in which case the job is sent directly to that machine. The fab is loaded with five products that visit each workstation twelve times. Fab loading is tested at three levels, with exponentially distributed interarrival times of 58, 67, and 49 min.

After all of the experiments are run, an analysis of variance (ANOVA) test is done to determine the significance of the individual factors. The factors that are concluded to be significant are the dispatching rule, loading level, and set-up time. Following this analysis, pairwise tests are carried out to determine if there is significance between each of the systems. The best results are obtained by using the marginal set-up with the grouping principle and no added value was found using look ahead.

Hung and Chen (1998) conduct a simulation study that compares many commonly used static dispatching rules with two “look-ahead” rules. The means of comparison in this study is based on product flow time, or cycle time. The goal of the study is to find a dispatching rule that reduces flow times while maintaining high machine utilization. They discuss the inherent trade off between flow time and machine utilization based and its relation to WIP.

The common dispatching rules that are studied are FIFO, SPT, shortest remaining processing time (SRPT), next queue length (NextQL), next queue time (NextQT), and EDD. The two proposed look-ahead rules that these are compared with are called SimBased and Queue Prediction (QP). SimBased uses a simulation within the simulation to determine the flow times

of the products in a given queue to determine what should be processed next. The product with the smallest expected flow time is chosen. The flow times are determined by simulating ahead a given number of processing steps. QP uses an analytical model to determine, based on historical data, the number of products in queue at a given point in time. The QP rule then chooses the lot that has the least average waiting time for a number of subsequent operations to be processed next. The number of processing steps to “look ahead” for each of these rules was optimized to four using simulation.

A ten-product fab with thirty workstations was used for the simulation. The fab is run for 24 months, using the first two months as a warm-up period. A fixed product mix and a changing product mix are also run in the fab. The results of the simulation show that the SRPT rule performs the best in terms of machine utilization and bottleneck flow time in both fabs. Hung and Chen reason that because SRPT uses more global information than the other dispatching rules, it performs the best. They go on to say that there is a great possibility for future research with the development of a shortest remaining flow time rule (SRFT). This rule would add the expected waiting time to the remaining processing time.

Cigolini et al. (1999) try to improve the current dispatching rules in place in a semiconductor manufacturing facility in Milan, Italy. The fab is very large, with over 250 different products being routed through more than 120 machine groups.

In the fab, the current dispatching rules that are used are dependent on the type of machine. For machines that can handle a single lot at a time, the lots are split into two queues, one for urgent jobs and one for normal jobs. If the machine requires a large set-up time, the lots are ordered in each of these queues according their setup times, with the shortest given priority. If two job lots have the same set-up time, the FIFO rule is used. When the machine becomes

idle, the first lot is taken from the urgent queue and if the urgent queue is empty, the first lots is taken from the normal queue.

Dispatching for machines that can batch lots is handled differently. It is first necessary to define the criteria for this dispatching strategy. MaxBS and MinBS refer to the maximum and minimum batch size, respectively, and WNLTT refers to the wait-no-longer-than-time. MaxBS, MinBS, and WNLTT are all predetermined values. At machines that batch lots, there is a single queue that contains both the normal and the urgent jobs. When the machine becomes idle, the queues are scanned for a batch that is greater or equal to MaxBS. If this is the case, that batch is immediately started. If there is not MaxBS in the queue, the machine will wait for WNLTT, or until MaxBS has accumulated in queue. If MaxBS occurs during the WNLTT, that batch is immediately started. If MaxBS has not occurred and WNLTT has passed, the queues will be scanned for MinBS, and if there is a batch meeting this criterion, it is immediately started. If MinBS is not met, a new WNLTT is started and the same rules are applied.

Cigolini et al. were tasked to develop new dispatching criteria for this fab. They again used different dispatching strategies for single lot and batching machines. For single lot machines, each is carefully categorized based upon its criticality to flexibility and capacity. A machine is said to be flexibility critical if it requires sequence-dependent set-up times and is said to be capacity critical if its average utilization rate accounts for more than a pre-determined threshold. For machines that are flexibility and capacity critical, a maximum capacity gain (MCG) dispatching rule is proposed. This rule attempts to minimize the overall set-up time among possible sequences of lots in queue. For machines that are only capacity critical, lots are divided into two queues. One of the queues contains lots that have processing times less than a predesignated level and are ordered by the SPT rule. The other queue contains the remaining

lots and is ordered by a slack per operation (S/OPN) rule. For machines that are only critical by flexibility, the minimum setup rule is used, with the S/OPN used in case of ties. In the last case, machines without either criticality, the S/OPN rule is used.

For workstations that batch lots, the criticality to capacity is again used, as well as MaxBS and WNLTT. For machines that are capacity critical, when the machine becomes idle it will check to see if MaxBS is available, and if it is, that batch is immediately processed. If this is not the case, WNLTT is used, and if MaxBS has not been reached by the WNLTT, the largest batch is immediately processed. The SPT rule is used to break ties if more than one batch has MaxBS available when the machine becomes idle. For non-critical machines, as soon as the machine becomes idle, the largest batch available is processed.

This new dispatching scheme was tested using a simulation model written in Siman V on a UNIX operating system. For the simulation, one worker was assigned to each machine and tools and fixtures were left out of the model. Also, there is no material handling and all buffer constraints are eliminated. The simulation model does include machine breakdown and repair data, preventative maintenance schedules, scrap losses, and random arrivals of urgent and normal lots to the system. The simulation model was run at three levels of loading: an average of 27, 30, and 33 lot starts per day.

The results of the simulation show that the new system improves average cycle time, WIP, and on time delivery. Also, it seems more capable of handling high workloads than the previous system. One downside of the new system is that it introduces more variability into the system. Implementation of the new dispatching strategies was not discussed in the paper.

A study done by Mittler and Schoemig (1999) compares three dispatching rules that claim to reduce the mean and variance of cycle time of small fabs (see Mittler and Schoemig

(1999) for a detailed explanation of the proposed rules). They are minimum inventory variability scheduling (MIVS), fluctuation policies for the mean of the cycle time (FSMCT), and the fluctuation policies for the variance of the cycle time (FSVCT). These three rules are compared to the traditional rules FIFO and EDD. The test is conducted on two MIMAC (Measurement and Improvement of Manufacturing Capacities) datasets, set one and three, which are available from the Arizona State University web site (Test Beds 2003). Dataset one has two products and 16,000 wafer starts per month, while dataset three has eleven products with 21,400 wafer starts per month. Both datasets contain rework but the rework strategy used in the study is not discussed. The statistics gathered are the mean cycle time (MCT) and the standard deviation of the cycle time (SCT).

For dataset one, FSVCT outperforms all other dispatching rules in MCT and SCT while MIVS only outperforms FIFO and EDD by a moderate amount. Both FIFO and EDD outperformed the FSMCT rule for dataset one. Very different results are obtained for dataset two, as MIVS outperforms the others in terms of mean cycle time. However, it only shows a 2.5 percent improvement over FIFO. For SCT, FSVCT performs better than all other dispatching rules and is about 22 percent better than FIFO. The conclusions drawn from this research are that the dispatching rules that are appropriate for small models are not applicable to these larger models. The performance of a given dispatching rule depends on characteristics of the fab, such as size and product mix and they recommend that managers use a dedicated simulation model of their particular fab for choosing dispatching rules.

Dabbas et al. (2001) attempt to validate the approach taken by Dabbas and Fowler (1999) on using a combined dispatching criterion to optimize multiple performance measures simultaneously. Simulation, using ManSim/X, is used to test the combined dispatching rule

against singular dispatching rules. This test is conducted on a mini-fab model and also on a full fab model.

The individual dispatching criterion that are combined in this study are critical ratio (CR), throughput (TP), flow control (FC), and Line Balance (LB). These criterion are given different weights, and the combined value of their weights is used to make dispatching decisions. Their respective weights are determined through experimental design and data transformation. This combined criterion is tested against the CR, fewest lots at next queue (FLNQ), and SPT rules individually. The performance measures used to compare these dispatching rules are on-time delivery (OTD), variance of OTD, MCT, and variance of MCT.

The simulation that is run is interrupted after some time has passed, and sends the current system state to a remote “User-Access” module. This module then generates a new list of priorities for all lots based on the current system status and sends the information back to the simulation. The simulation then runs until it is again interrupted.

The mini-fab model used has six workstations with three products, all of which use the same routing. The model analysis led to the following weights of .19, .19, .62, and 0 to LB, CR, TP, and FC, respectively. The results of this show that the combination dispatching rule significantly improves all performance measures versus the best single dispatching rule from those tested (CR, FLNQ, and SPT). Similar results were obtained in the full fab model. The weights used in the full model were .31, 0, .16, and .53 for LB, CR, TP, and FC, respectively. Statistically significant improvements were obtained between the combination rule and the best single dispatching rule for all performance measures except for the variation of MCT. For this measure, the CR rule performed as well as the combination rule.

This combination rule has been implemented in one of Motorola's semiconductor fabs since October 1998. Improvements in OTD, CT and lateness have been observed at this facility, giving the criterion credibility in industry. Recommended future research includes applying different weights to different types of machines, and developing a model where the weights will change with the status of the model.

Lee et al. (2001) introduce a new dispatching rule in this study, the balancing work content (BWC) rule. This rule gives priority in queue to those products that have more work and longer processing times at the bottleneck workstation ahead. The idea for this rule comes from the desire to never starve a bottleneck station, as that equates to forever lost throughput. It is considered to be a dynamic rule because it takes the current state of the system into account when making dispatching decisions.

The fab is modeled as two workstations (both bottlenecks) that product flows between with a delay time between leaving one and arriving at the other. The model is developed using Extend 4.0. Three different dispatching rules are considered, FIFO, SPT, and BWC, and the performance measures captured are the mean cycle time and the standard deviation of cycle time. Orders are released at a constant rate into the fab. Two situations are examined; deterministic processing times and stochastic processing times. For the stochastic processing times, three different coefficients of variation are used, .5, 1.0, and 1.5.

The results of this simulation show that the BWC rule gives a smaller mean cycle time and smaller standard deviation of cycle time than the other two rules in both situations. In fact, in the more realistic stochastic situation, BWC showed greater improvements than in the deterministic system. While these results are easy to see, there are no hypothesis tests done to prove that the differences in mean cycle time and the standard deviation of cycle time are

statistically significant. Furthermore, this model is very simplistic in nature and needs to be validated in a full fab model before its results can be credible in industry.

Rose (2001) conducts a study that focuses on the SPT rule and its effect on cycle time in a full fab simulation model. He proves that using this rule will decrease cycle time in a simple single stage model and is interested in whether extending these findings to a complex fab is an appropriate leap. Factory Explorer 2.6 from WWK is used to build the model, and the data used is set 6 from the Arizona State University MIMAC test bed.

Rose (2001) compares the FIFO rule to three variants of the SPT rule:

1. SPT and absolute waiting time limit (AWTL) – chooses the lot with the shortest processing time unless a lot has waited longer than the AWTL, in which case that lot gains priority in the queue.
2. SPT and mean waiting time limit (MWTL) – chooses the lot with the shortest processing time unless a lot has waited longer than a multiple of the average waiting time of all lots, in which case it gains priority in the queue.
3. FIFO or SPT according to queue length (FSQL) – ranks lots using FIFO unless a specified queue length is reached, in which case SPT becomes the raking rule.

A series of experiments are run varying the waiting time limits from one to thirty hours. The results show that there is no predictability when changing from the FIFO rule to an SPT rule. Some of the products had small increases or decreases in cycle time, but the majority showed no significant difference. Also, all of the variants tested result with cycle times that fall between the basic SPT rule and the FIFO rule. He attributes these findings to the fact that the SPT rule is a “local” rule and changes from workstation to workstation. “As a consequence, the effect of

using SPT depends both on the products' recipes and the product mix.” He concludes that there is no general way to predict the change in cycle time using an SPT rule.

Rose (2002) examines the cycle time and on time delivery performance of a fab using the critical ratio (CR) dispatching rule. The CR rule is a ratio of the due date (Due) minus the current time (Now) divided by the total remaining processing time (TRPT),

$$CR = \begin{cases} \frac{1 + Due - Now}{1 + TRPT}, & \text{if } Due > Now \\ \frac{1}{(1 + Now - Due)(1 + TRPT)}, & \text{otherwise.} \end{cases}$$

He then discusses the importance of correctly determining the due dates of product when using the CR dispatching rule. He goes on to say that many fabs use a flow factor (FF) to determine due dates by multiplying the FF by the raw processing time to get an expected due date. FF refers the ratio of the actual processing time to the raw processing time of a product. FF is referred to as XTheoretical (XT) or the “X” Factor in other literature.

Six of the MIMAC datasets are used (1,3,4,5,6,7) using Factory Explorer 2.6 from WWK with a replication length of seven years with the first two years truncated as a warm up period. Datasets one and three contain rework data, but the rework strategy used is not discussed. The FIFO rule is used as a benchmark, and then the CR rule is used with the FF ranging from 1.0 to 3.5 in increments of .1.

The results of this study are rather striking, as a .1 step increase in the FF makes the cycle time drop nearly 100% in a some of cases. The magnitude of the cycle time improvements when the FF is increased are not seen in all the fabs tested, and depend heavily upon the loading of the fab. Rose concludes that in order to accurately set due dates using the CR dispatching rule, the fab must be simulated under heavily loaded conditions using the FIFO dispatching rule. From there, the average cycle times can be gathered, and dividing them by the raw processing time

gives the FF value for the product. He suggests that a small safety buffer of .1 or .2 is added to the FF value. He also notes using this methodology as compared to the FIFO rule will increase average cycle times by a small amount, but the increase in time delivery is worth the trade-off.

3.3.3 Order Release and Dispatching Rules

Wein (1988) performs a benchmark study in the semiconductor simulation field. This research is concerned with the effect that scheduling, particularly order release and dispatching rules, have on cycle time in a semiconductor fab. The order release rules tested are poisson, deterministic, constant work in process (CONWIP), and workload regulation (WR). Many dispatching rules are tested, including FIFO, SRPT, and lowest number in the next queue per machine (LWNQ/M). Refer to Wein (1988) for a detailed list and description of all of the proposed dispatching rules.

Three fabs are tested, each of which being slightly different than the other two. The differences in the fabs are based on the number of workstations and the number of operators. The configuration changes alter the number of bottleneck workstations in the fabs. All fabs have one job type with 124 operations. Some simplifying assumptions are made in this simulation. These include constant processing times at all stations, one product loading, no “hot” lots, and a simplified fab model.

The results of this study show that scheduling has a significant effect on average cycle time. It also concludes that the effect of order release rules have a greater impact than that of dispatching rules. In all three fabs, WR performed better than all other order release rules, followed by deterministic, CONWIP, and poisson. The optimal dispatching rule is dependent on the fab and the order release rule. For instance, SRPT performs better than FIFO for poisson

input, performs the same as FIFO with CONWIP policy, and performs worse than FIFO with a deterministic release policy.

Resulting from these findings, Wein concludes that input control (order release rule) can significantly improve the performance of wafer fabs. The amount of the improvement depends on the fab type and dispatching rule used. There are also some simplifying assumptions made in this research, and the effect of them must be understood in a full fab model to truly understand what impact scheduling can have.

Jeong and Lee (unknown) conduct a study to show how a combination of order release and dispatching rules effect fab performance. They use the fab line from Wein (1988) and make four variants of that line based on different types of machine failure in the wafer fab line. Four different order release strategies are used, deterministic, poisson process, WR, and starvation avoidance (SA). The dispatching rules used are FIFO, SRPT, LWNQ/M. Thirty replications of one year are performed for each combination.

In this experiment, Jeong and Lee compare the twelve combinations of policies at a level which 90% of the maximum throughput is observed. The deterministic order release rule gives the best cycle time performance, regardless of the dispatching rule used in combination. The best and worst policies are found to be the SRPT-SA and LWNQ/M-Poisson, respectively. This analysis is lacking more in depth statistical analysis including whether the differences in the different policies are significantly significant.

Bahaji, Nizar (2000) researches the effect that combinations of order release rules and dispatching rules have on various performance measures in fabs. These combinations are tested in two different fab settings, a make-to-order and a make-to-stock fab. The order release policies tested are a fixed release policy (push) and a constant WIP policy (pull). Fourteen dispatching

rules are tested in combination with these order release policies in both fab types. This study attempts to improve multiple performance measures simultaneously by using dynamic, composite dispatching rules that take the current state of the fab into account when making decisions.

Bahaji models dataset five from the MIMAC test beds using AutoSched AP. Dataset five is chosen as it is known to be the most complex from the test bed. This data set contains 21 products with 10,000 wafer starts per month. Rework is not included in this fab. The full fab is used for the make-to-order type fab, while three of the twenty-one products are used in the make-to-stock fab. The dispatching rules used include FIFO, CR, EDD, LWNQ, ESD, and many composite rules based upon these rules. Refer to the original research for an in-depth discussion of the dispatching rules used. Many performance measures are analyzed, including mean cycle time, standard deviation of cycle time, 98 percent cycle time, mean WIP level, mean throughput rate, mean tool group utilization, and mean tardiness. The method of replication and deletion is used to run ten replications of each of experiments.

When modeling the two different fab types, percent utilization, percent down, and average queue length are the factors that were taken into consideration. The releases of product in the three product fab are increased in an attempt to make these factors close to the same between fabs. To determine the due dates of the products, two times the theoretical processing time of the lot is added to the start date.

ANOVA and Ryan multiple comparison tests are used to determine which rules are significantly different from the others. The results, based upon these tests, conclude that the composite dispatching rule developed by Bahaji, $Wt(PT+WINQ)/XF$, performs very well for both fab types, both order release strategies, and for most performance measures. This rule uses

a ratio of the processing time (PT) of the lot plus the sum of processing times of lots in the next queue (WINQ) divided by the X Factor (XF) to attempt to give priority to lots that have small workloads at the next processing station and that are behind schedule. The formula for this rule is

$$Wt(PT + WINQ) / XF = \exp(-XF) \cdot \left(\frac{PT + WINQ}{XF} \right) + \exp(XF) \cdot \left(\frac{1}{XF} \right).$$

Bahija's findings are significant as a thorough statistical analysis is performed that compares many common benchmarked rules to the composite rules he developed. Also, the results show that the dispatching rules found to be robust are superior for most of the performance measures tested.

3.3.4 Order Release and Dispatching Rules with Rework

Some studies focus on the effect of rework, such as the study done by Sheng-Yuan et al. (2001) that concludes order release rules and dispatching strategies are affected by the presence of rework in the system. They go on to investigate the effect of three different levels of rework (1%, 5%, 10%) when different order release rules and dispatching strategies are used. The study uses a medium size fab in Taiwan for the simulation data.

The dispatching rules that used are divided into four categories that are developed by Blackstone et al. (1982).

- 1) Strategies involving processing time
- 2) Strategies involving due dates
- 3) Strategies involving neither processing time nor due dates (simple)
- 4) Strategies involving two or more of the first three classes (combined)

The rework strategy used is to hold the mother lot until the child lot has been reworked, then combine the child lot and the mother lot after the child lot has been reworked. This strategy is chosen because it is the most practical way that rework is handled in industry. The performance measures chosen are average WIP, average cycle time, standard deviation of cycle time, average tardiness, tardy rate, delay cost, and daily throughput. Due dates were established by using a flow factor of 4.4.

A full factor experiment is carried out with seven order release strategies, eight dispatching rules, and three levels of rework. The order release strategies used are WR, CONWIP, SA, uniform distribution (UNIF), poisson distribution (POISS), two-boundary (TB), and WCEDD. Dispatching strategies used are FIFO, EDD, CR, next queue length (NexQL), SRPT, COVERT, SA+, and TB+. Descriptions of the order release strategies and dispatching rules are not discussed. The three levels of rework are specified to be one, five, and ten percent. Each combination of strategies is run for six replications.

The conclusion to the study is that the overall system performance can be greatly improved by selecting appropriate order release strategies and dispatching rules based on different rework levels. The combinations of TB*EDD, TB*NexQL, WR*EDD, and WR*NexQL are the most stable combinations under the different rework conditions.

Some shortcomings of the research done by Sheng-Yuan et al. are that the conclusions are drawn on one fab that ran a three-product mix. It is appropriate to determine if similar conclusions can be drawn from different fabs running different product mixes. Also, hypothesis tests should be carried out on the performance measures to determine if there is differences are statistically significant.

4. THE SIGNIFICANCE OF REWORK

One thing for certain is that whether or not rework was included in previous research, rework is present in modern fabs (Reduce 2003). In past research, there are many different viewpoints on the importance of including rework in simulation models of semiconductor fabs that are discussed in Chapter 3. Some papers find that the inclusion of rework greatly alters performance measures (Grewal et al. 1999, Sheng-Yuan et al. 2001) while others use models that do not contain rework to draw conclusions (Collins, Torsina, and Balgemann, 1999, Rose 2001). This study's hypothesis is that the presence of rework significantly effects key fab performance measures, including average cycle time, standard deviation of cycle time, and average WIP.

To test this hypothesis, a simulation model of a fab without rework is constructed so the comparison of performance measures can be explored when rework is introduced to the model. Experiments are then run for both of these fabs, and the results are analyzed to determine whether the performance measures of these two fabs are significantly different. By showing that rework does significantly effect the performance measures in a fab and with the knowledge that rework is present in most modern fabs, including rework in semiconductor research becomes imperative.

4.1 Fab Description

Previous research shows the importance of modeling realistic fabs. For example, Mittler and Schoemig (1999) find that their proposed dispatching rules perform very well in small fab models, but perform poorly when tested in a larger, realistic fab model. Therefore, in an effort to draw conclusions valid to the semiconductor industry, realistic fab data is needed. The Arizona State University website (Test Beds 2003) contains the MIMAC datasets, which contain real fab

data that is largely used in past research. Three of the seven datasets contain rework, and of those three, dataset three is the most comprehensive, as it has the most products, eleven, and the most wafer starts per month, approximately 21,400. Therefore, dataset three is used to model the fab in this research. Refer to Appendix K for a more detailed description and data from this fab.

In this fab, a constant lot release policy is followed for all eleven products, processing times are constant, and the time between machine failures, machine repairs, and preventative maintenance tasks are exponentially distributed. Also, the products go through a range of 275 to 500 processing steps, with 7 to 15 masking layers. A masking layer refers to when a new pattern

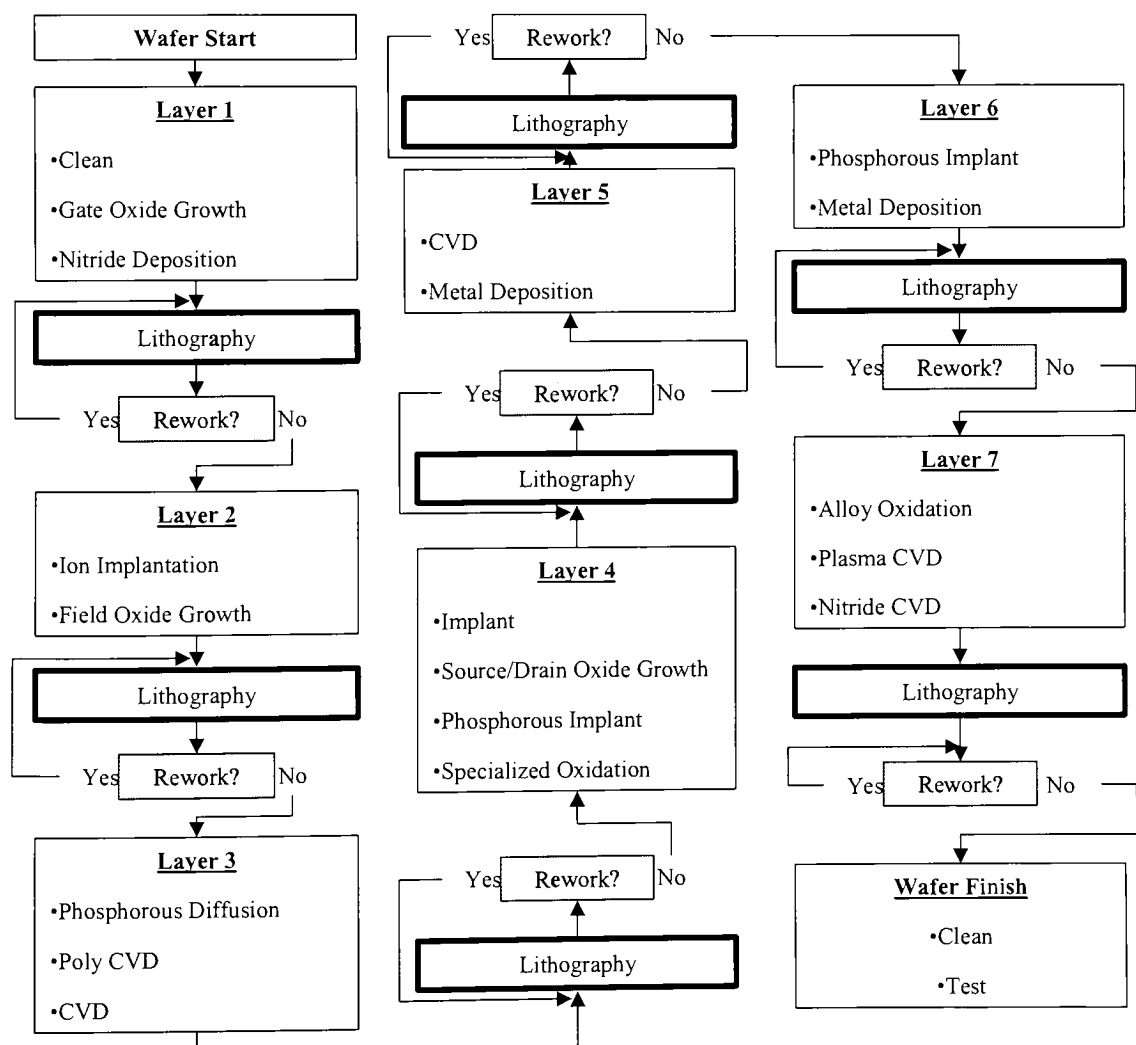


Figure 4.1. Flow of Product 9 through the Fab

is transferred to the wafers, which happens at lithography steps. It is at these lithography steps when the possibility for rework arises. Wafers travel through the fab in lots of fifty, therefore when the lot passes through a lithography step, some of the wafers will likely need to be reworked. The dataset contains values that specify the percentage of wafers that need to be reworked at each one of these steps. The values of potential rework range from .7 to 27 percent. Figure 4.1 shows the flow of product 9 through its processing. This particular product has the smallest routing of the eleven products, with 7 masking layers and 304 processing steps. The full routing for this product can be seen in Appendix K.

When rework occurs, the lot splits into a mother lot consisting of all of the wafers that do not need to be reworked, and into a child lot with all of the wafers needing rework. The mother lot then waits for the child lot to go through the necessary rework steps and once the child lot has completed the rework loop, the mother and child lot are combined together for all further processing.

There are 73 tool groups on which the wafers are processed. Some of these tool groups contain one machine, while some contain multiple machines. For instance, there are thirteen steppers that available for the lithography process. Wafers travel through these tool groups in a re-entrant manner, meaning the same wafer will visit the same machine numerous times. This behavior is one of the main difficulties in modeling semiconductor fabs. Also setups are needed at tools when a lot arrives that has different characteristics than the previous lot that the tool processed. These setup times and characteristics are defined in the dataset.

4.2 Simulation Model

To model this fab, the simulation software AutoSched AP developed by Brooks Automation is used. This software is geared towards semiconductor manufacturing and easily handles the complex processing parameters of a fab, such as rework and re-entrant flow. The interface of this software is based in Microsoft Excel, which allows for easy data transfer and manipulation.

All of the data described above is transferred into the AutoSched AP. There are some modeling assumptions that are important to note. One assumption deals with batching, which refers to tools being capable of handling multiple wafers or lots simultaneously. At such stations, the dataset gives the number of wafers that the tool can handle, which can then be divided by fifty to give the number of lots that the tool can handle. The problem lies in that, in some cases, the tool can only handle 16 wafers at a time. Wafers travel in lots of 50, therefore at such tools, the load, unload, and processing times are quadrupled to adjust for the batching restrictions. However, the setup time will not be quadrupled, as the four batches are processed consecutively, therefore not needing setups between them. Also, the FIFO dispatching rule is used for all queuing decisions.

Two models are built, one containing rework and one without rework. These models are then evaluated to determine if the presence of rework effects key performance measures in the fabs. In the model containing rework, the rework strategy that is used holds the mother lot at the rework step until the child lot has completed the rework loop, and then combines them for all further processing. The performance measures analyzed are average cycle time, standard deviation of cycle time, and average WIP for both fabs.

4.3 Verification and Validation

After the simulation model is constructed, verification and validation steps are done to ensure that the model is working as intended and correctly represents the actual system. AutoSched AP has an extensive trace feature that allows each step of the simulation model to be closely scrutinized. This feature is used to verify that such things as the rework strategy, batching, setups, and machine downtimes are being modeled correctly.

After these things are verified, the model is validated against results for the fab from the MIMAC Test Bed (Test Beds 2003), which were obtained using Factory Explorer simulation software. These results are derived from one replication, with a warm-up period of 10,000 hours and a run length of 50,000 hours. Table 4.1 shows how similar the throughput is for each part between this model results and the reference values. Also, the cycle times are collected, and the differences in cycle times range from 5 to 10 percent, with an average of 7.3 percent. Based upon these results from only one replication, it is concluded that the fab is accurately representing the actual system.

Table 4.1. Validation Run Against Factory Explorer Results

Part	Throughput (lots)	
	This Study	Reference
A	2449	2445
AT	686	687
C	687	686
D	587	586
F	490	489
H	5976	5974
R	5192	5195
U	1909	1906
X	3233	3234
Y	2056	2056
Z	540	540

4.4 Analysis Methodology

Following the experiments, the results are analyzed using ANOVA tests to determine if there are statistically significant differences in the performance measures between the fab with rework and the fab without rework. The Minitab software program is used for this testing. From the ANOVA test, a p-value is generated, which denotes the level of confidence to which the values of the performance measures are different. For the purposes of this study, the performance measures in the fabs are said to be different if their p-values are .05 or smaller, meaning that the differences are significant at a confidence level of 95 percent.

4.5 Experimentation and Analysis

After the model is verified and validated, the experiments are run. As discussed above, the objective of this analysis is to determine the role that the presence of rework has on the chosen performance measures. The simulation models of the two systems are run, one with rework present, and one without rework. Each model was run for 10 replications of 50,000 hours each with a warm-up period of 10,000 hours.

An ANOVA test is then performed to determine if there are significant differences in the performance measures due to the presence of rework. The results in Table 4.2 show that at an alpha level of .05 (the detailed results of these simulation models can be seen in Appendix A), there is a significant difference between the fab with rework and the fab without rework for all of the performance measures studied. The results show that the average cycle time increases by five percent, the standard deviation of cycle time increases by six percent, and the average WIP increases by five percent when rework is included. Such differences can have a significant financial impact in semiconductor fabs.

Table 4.2. The Effect of Rework on Fab Performance Measures

	Rework	No Rework	
	Fab	Fab	P-value
Avg. CT (hrs.)	339.987	323.857	0.000
St. Dev. CT (hrs.)	83.238	78.721	0.000
Avg. WIP (lots)	189.137	180.166	0.000

4.6 Summary

From these results, it can be concluded that rework significantly effects the productivity of a fab. Consequently, research that does not include rework can lead to findings that are significant, but may not be achievable in a real fab. As the goal of most research is to have the findings be accepted in industry, rework should be included in semiconductor research involving shop floor control decisions.

Rework exists in and significantly impacts the performance of modern day fabs. Therefore, anything that can be done to minimize the detrimental impact that rework causes should be investigated. The rest of this research focuses on identifying operational decisions that can help to reduce the impact of rework, and to test these decisions in a simulation model.

5. A STUDY OF DISPATCHING RULES AND REWORK STRATEGIES

As discussed earlier, the semiconductor industry is fast paced and manufacturers must be able to quickly adapt to changes in the market. To do this, the dynamics of the fab must be thoroughly understood in order to make proper decisions that optimize the system relative to key performance measures. Based on the research in Chapter 4, the presence of rework is shown to have a significant effect on these key performance measures. Consequently, it is beneficial to investigate possible ways to minimize the negative impact that rework has in fabs. Past research has targeted dispatching rules and rework strategies independently to help fabs run efficiently in the presence of rework.

The scope of this work of this experiment is to evaluate alternative combinations of previously studied dispatching rules and new and existing rework strategies for use in semiconductor fabs. In particular, this study evaluates whether there is a robust combination that is best for all (or a large class of) fabs, or which combinations are best for various fab types and rework levels. Simulation is used to develop a valid model based on realistic fab data from the MIMAC test beds (Test Beds 2003). Using this model, a four-factor experiment is conducted to determine the effect of dispatching rules, rework strategies, rework levels, and fab types on fab performance measures. These performance measures include average cycle time, standard deviation of cycle time, percentage on time, average WIP, and average XT. Finally, conclusions are formed based on a detailed statistical analysis of the experimental results.

5.1 Methodology

5.1.1 Experimental Design

To evaluate combinations of rework strategies and dispatching rules, a four-factor full factorial experiment is conducted. The factors include dispatching rules, rework strategies, rework levels, and fab types. These factors and the factor levels are summarized in Table 5.1. A total of 120 experiments are run when all of the combinations of the factors are exhausted.

Table 5.1. Experimental Design

Factors	Levels
Dispatching Rules	FIFO, SPT, EDD, CR, RWK
Rework Strategies	Wait, Split, Rendezvous, First Bottleneck
Rework Levels	1%, 5%, 10%
Fab Types	Make-to-Order, Make-to-Stock

5.1.1.1 Dispatching Rules

The dispatching rules that are used include first-in-first-out (FIFO), shortest processing time (SPT), earliest due date (EDD), critical ratio (CR), and rework priority (RWK). These rules are chosen as they are commonly used in fabs and are the benchmark rules used in most of the semiconductor simulation research (see Mittler and Schoemig 1999, Lee et al 2001, Rose 2001, and Rose 2002). Although these rules are previously discussed in this research, they will be defined to avoid any confusion.

FIFO is the most common dispatching rule used in all manufacturing. This rule states that lots are processed in order of their arrival. This rule is beneficial in that it guarantees that lots do not get stuck in queue for large amounts of time resulting from other lots getting priority over them. The major drawback to FIFO is that lots cannot be expedited to improve performance, such as a lot gaining priority so that it can finish on time.

The SPT rule ranks lots in order of their processing time at that given station, with the shortest processing time given priority. If two lots have equal processing times, the FIFO rule is

used to break the tie. The advantage of using this rule is that the station's output rate will be maximized, with the disadvantage being that lots with relatively large processing times at a station may get stuck in queue for a long time. The third rule tested is the EDD rule that gives priority to lots that have the earliest due date. Intuitively, this rule aims to improve on time performance.

The next rule, CR, behaves similarly to EDD, but with one major difference. The CR rule uses a ratio,

$$CR = \frac{\text{Time Until Due}}{\text{Remaining Processing Time}},$$

to determine the queuing order, lowest value first. This ratio gets smaller as the value of the remaining processing time subtracted from the time until due gets small. Note that this calculation is slightly different than the CR formula presented by Rose (2002). This value is known as the slack time, or time remaining that the lot can spend in non-processing operations and still finish on time. When the CR equals one, the lot's time until due equals the remaining processing time, and if any time is spent in non-processing operations, it will be late.

The last rule tested is the RWK rule, which gives priority in queue to lots that are designated as rework lots. If there is more than one rework lot, the FIFO dispatching rule is used to determine the order in which the reworked lots are processed. With this rule, all non-rework lots are ordered using the FIFO rule. Once the rework lot joins the mother lot, which is dependent on the rework strategy chosen, the lot is no longer considered a rework lot. This rule is chosen as this study aims to minimize the impact of rework on a fab.

All of these rules are fairly simple to implement in a production fab. Of these rules, the most difficult to implement is the CR rule, as each time a new lot enters the queue, the CR of

each lot in queue must be calculated and ordered accordingly. Some sort of automated control system would make implementation of this rule much simpler.

5.1.1.2 Rework Strategies

Four rework strategies are tested. Three of the strategies are previously studied, and one is developed in this research. The first strategy holds the mother lot at the rework step until the child lot has gone through all of the rework steps, then the mother lot and child lot are combined for all further processing (Zargar 1995). This strategy is called the wait (WAIT) strategy in further discussion. The second permanently splits the mother lot and the child lot, therefore allowing the mother lot to continue processing while the child lot is being reworked (Zargar 1995). This strategy is appropriately named the split (SP) strategy. The third strategy that is tested is the rendezvous strategy (RV), which splits the mother lot and the child lot, allowing the mother lot to go through the next processing step. After the mother lot goes through the next processing step, it is held at that processing step until the child lot has been reworked and goes through the next processing step, at which point they are combined for all further processing (Sha et al. 2001). The other rework strategies proposed by Zargar and Sha et al. are not used, as they are not practical in a semiconductor fab.

The fourth rework strategy that is tested is one that is derived in this research and named the first bottleneck (FBN) strategy.

Definition: *First Bottleneck (FBN) Rework Strategy* – Mother lot proceeds through all processing stations until the first bottleneck station and then waits to be rejoined with the reworked child lot.

This strategy splits the mother and the child lot when rework occurs, then sends the mother lot ahead for processing until it reaches the first bottleneck station. The mother lot then waits at the first bottleneck until the child lot arrives. The two lots are then combined for processing at the bottleneck station and for all further processing.

The first bottleneck station for the FBN rule is determined by running an experiment where the mother and child lots are split after rework occurs, and are then recombined at the station before the next possibility of rework. This gives the worst-case scenario in terms of station loading for each set of stations. The first station in each set that has above 85 percent utilization under this scenario is designated as the first bottleneck (Tyan et al. 2002). Before processing at this station, the mother lot waits for the child lot, and when the child lot arrives, they are combined for all further processing.

This strategy aims to capitalize on the underutilized stations following rework steps that are not considered to be bottlenecks. The mother lot and child lot will flow through these stations independently rather than as a combined lot, as they would with the WAIT and RV strategies. This major benefit of this strategy comes when some of these underutilized stations have per part processing times. Allowing the mother lot to flow through such stations ahead of the child lot can significantly reduce the cycle time of the lot. Furthermore, the mother lot waits at the bottleneck machine for the child lot, where it would be waiting in queue anyways. It is rather clear how this rework strategy can be advantageous when it is considered in this manner.

5.1.1.3 Rework Levels and Fab Types

The rework data for each fab are set to three levels; one, five, and ten percent at all steps containing rework. These levels are chosen as they approximately span the range of the rework

level found in the MIMAC datasets. Rework levels range from .7 to 27 percent at lithography stations in the dataset, however, the majority of rework percentages are between one and ten percent. Furthermore, previous research that has been done that included rework has used these same three rework levels, such as the work done by Sheng-Yuan et al. (2001).

To model the two different fab types, fab three from the MIMAC Test Bed, which is described in Chapter 4.1, is used. The first fab uses all eleven products from the dataset to represent a make-to-order (MTO) type of fab. The second fab is the same fab with only two of the eleven products, to represent a make-to-stock (MTS) fab. The two chosen products have their arrivals increased so that the utilizations of the bottleneck stations are equivalent in both fabs. This allows the results to show whether the combinations of dispatching rules and wafer strategies are effected by fabs of different size and complexion while taking out variability of using completely different fabs. The data, including the routings, from these fabs can be seen in Appendix K.

5.1.2 Performance Measures

As discussed previously, the performance measures that are analyzed in this study are the average cycle time, standard deviation of cycle time, percentage on time, percent idle, average WIP, and average XT. These are chosen for a couple of reasons. First and foremost, they are very good indicators of the overall performance of a fab. Also, they are many of the commonly used performance measures in the papers discussed in the literature review chapter. Throughput was not used as a performance measure, as in this case, the throughput is not restricted by the capacity of the fab, rather it is restricted by the release rate of lots into the fab. Therefore, regardless of the strategy used, the throughput remains the same.

Average cycle time, standard deviation of cycle time, and average WIP are all easily understood performance measures. One that needs more explaining is percentage on time. In order to use percentage on time as a performance measure, there must be an acceptable way to determine product due dates. Rose (2002) proposes a method to do this using a flow factor approach (FF) that takes a ratio of the average cycle time and the raw processing time and adds a small buffer to the ratio to determine the due date. This is the method that is used to assign due dates in both of the fabs (see Chapter 3.3.2).

The FIFO/WAIT strategy is used for each of the three rework levels and in both fab types to determine the average cycle time for each product in each fab and at each rework level. From the average cycle time, the FF is determined by dividing the average cycle time by the raw processing time for that product.

Experiments are run that used different buffers to try and select a buffer that causes the fabs to achieve an on time percentage of approximately 90 percent. Ninety percent is chosen as it not only seems to be a realistic goal for a manufacturing facility to achieve, but is not too large so that differences in the strategies tested cannot be seen. The buffer chosen to achieve approximately 90 percent on time performance is .09.

The percent idle performance measure is a measure of the overall utilization of the fab, with higher percent idle being superior as the same throughput is being obtained with less utilization, therefore the product is being produced more efficiently. Finally, the average XT performance measure is a ratio of the actual cycle time to the raw processing time. The ideal XT value is 1, meaning that the lot has not waited at all during its processing, therefore its actual cycle time is equal to the raw processing time. Any time that the product waits during its

processing increases its XT value. This is a commonly used performance measure in semiconductor manufacturing.

5.1.3 Simulation Modeling

The simulation model developed for the experiment in Chapter 4 is used to model the MTO and MTS fabs. All of the of the different dispatching rules, rework strategies, and rework levels needed for these experiments are incorporated into the each of the models. These modifications were verified using the same methods as described in Section 4.3.

5.1.3.1 Modeling the Make-to-Order Fab

As stated previously, the MTO fab uses all eleven products from the dataset. Appendix K contains information regarding this dataset. During verification of this fab, it is noticed that, at the ten percent rework level, the furnaces are highly utilized (over 99%) with a large average WIP in each queue. This is of concern, as any combination of rework strategy and dispatching rule that cause this queue to build up to a slightly larger amount could cause the system to never reach steady state, or explode. To alleviate this problem, furnaces are added to the model and tested in the 10 percent rework fab using all of the dispatching rules in this experiment. It is determined that adding four furnace 3's and two furnace 5's is enough to ensure that none of the dispatching rules cause the fab to explode under the WAIT, RV, and FBN rework strategies. Adding these furnaces does not significantly change the WIP at the rework stations, which are of main interest in this study.

5.1.3.2 Modeling the Make-to-Stock Fab

After the MTO fab (11 products) is built and verified, the MTS fab is constructed. Two products from the MTO fab (products 1 and 5) are used in the MTS fab. These products are chosen as they use all but two of the stations in the fab. The two stations that are not used are not bottleneck stations or involved in the rework steps. The interarrival times of these two products are decreased so that the bottleneck stations, mainly the furnaces and photolithography stations, have approximately the same utilization rates and average queue lengths as the MTO fab. The interarrival times of products one and five are changed from 20.81 to 4.16 hours and 17.47 to 10.48 hours, respectively.

As the interarrival times of these two products are decreased, the utilization of the furnaces become roughly the same as the MTO fab, but some small changes are needed at the furnaces, photolithography, and implant stations. The utilizations and queue lengths of these stations are not as large as they are in the MTO fab, therefore some minor changes are made to the fab and can be seen in Table 5.2. Making these changes is important because having small or empty queues at these stations renders the dispatching rules useless.

Table 5.2. Variation in Quantity of Stations between Fabs

	Initial Fab	MTO	MTS
Stepper	13	13	9
Furnace3	8	12	8
Furn 4	2	2	1
Furnace5	2	4	2
High Implant	3	3	2
Med Implant	4	4	3

The utilizations and average queue lengths of stations with above 50 percent utilization in the MTO and MTS fabs can be seen below in Table 5.3.

5.1.3.3 Warm-up Period Determination

As semiconductor fabs are generally run continuously (non-terminating), there needs to be a warm-up period at the beginning of each simulation run to get the fab to steady state production prior to collecting the statistics that will be used for analysis. Even though the test bed contains a warm-up period to use, it needs to be verified as the models contains different rework

Table 5.3. Comparison of Station Utilization and Average Queue Length Between the Make-to-Stock and Make-to-Order Fabs

Station Name	Utilization Comparison			Average Queue Length (lots)		
	MTO	MTS	Difference	MTO	MTS	Difference
FURN3_Furnace_Tube	99.92	99.91	0.01	5.87	5.53	0.34
STEP_Photo_Stepper	97.67	98.90	-1.23	3.89	5.27	-1.38
FURN5_Furnace_Tube	97.32	99.67	-2.35	1.72	2.68	-0.96
FURN4_Furnace_Tube	97.30	96.86	0.44	1.95	1.44	0.51
FURN1_Furnace_Tube	92.90	89.87	3.03	0.87	0.82	0.05
HIGH_High_Current_Implant	92.28	89.40	2.88	3.04	2.56	0.48
MED_Med_Current_Implant	90.72	87.41	3.31	3.89	3.18	0.71
PR3_Probe	89.68	86.87	2.81	0.61	0.55	0.06
PHOS_Furnace_Tube	82.85	51.39	31.46	0.41	0.06	0.35
COAT5_Coater	76.83	60.17	16.66	0.42	0.16	0.26
PLAM_Dry_Etch	75.78	59.21	16.57	0.62	0.21	0.41
CVD1_CVD	69.89	42.25	27.64	0.81	0.07	0.74
PIRH2_Strip	69.77	49.27	20.50	0.50	0.12	0.38
CVD5_CVD	69.65	48.88	20.77	0.67	0.21	0.46
CVD4_CVD	67.89	43.71	24.18	0.59	0.13	0.46
LFE_Asher	66.19	43.11	23.08	0.35	0.05	0.30
WATJ_Metal_Dep	65.72	46.85	18.87	0.34	0.06	0.28
PR1_Probe	65.56	16.31	49.25	0.04	0.00	0.04
FURN2_Furnace_Tube	62.27	35.40	26.87	0.21	0.03	0.18
COAT1_Coater	59.93	49.23	10.70	0.28	0.17	0.11
PR2_Probe	59.48	86.81	-27.33	0.02	0.51	-0.49
CVD2_CVD	50.27	33.19	17.08	0.06	0.01	0.05
ITP_Metrology	50.20	33.00	17.20	0.35	0.10	0.25
EVAP_Metal_Dep	50.01	28.97	21.04	0.24	0.07	0.17

percentages, dispatching rules, and rework strategies than the original dataset. A graphical method is used to determine the warm-up time in both the MTO and MTS fabs at ten percent rework using the WAIT rework strategy and the FIFO dispatching rule. If the appropriate warm-

up period is determined for the ten percent fabs, it is also large enough for the one and five percent rework fabs.

After the simulations are run, the average cycle time and WIP are plotted against time. Upon analyzing these plots, it is clear that the MTO system reaches steady state around 8,000 hours and the MTS fab previous to that. An example of this can be seen in Figure 5, which contains the first 20,000 hours of average cycle time and WIP data for the MTO fab. Therefore, the warm-up period is determined to be 10,000 hours, as a small buffer is added as a precaution to ensure the system is at steady state when data collection starts. It is interesting to note that this warmup time is the same as the given warmup time in the test bed.

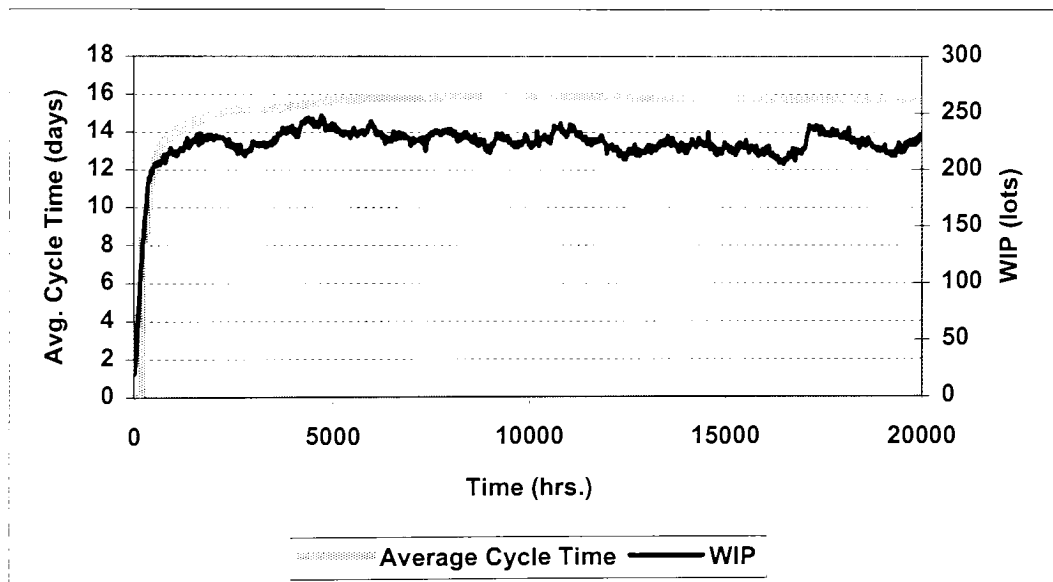


Figure 5.1. Average Cycle Time and WIP Plotted Against Time to Determine the Warmup Period

5.1.3.4 Data Collection Technique and Replication Length

The method of collecting data needs to be determined before experimentation can begin. There are a few common approaches that can be used, including the method of batch means and method of replication and deletion. The method of batch means allows each replication to begin with the system in the same state as when the previous replication ended and is the chosen for

this study. The method of batch means is chosen over the other common approach, the method of replication and deletion, as the method of batch means does not need a warm-up period for each replication. This becomes important when simulation time is taken into account, as the 10,000 hour warm-up period takes approximately 45 minutes to run.

In general, the longer the simulation replications are, the more representative of the actual system the resulting data will be. However, as previously stated, with this complex of a model, simulation time becomes a limiting factor. Therefore, ten replications of 50,000 hours each is chosen as an upper limit for run length. In an effort to reduce the length of the simulation replication runs, simulations are run with different replication lengths to determine if the differences in the results are statistically different than the 50,000 hour replications. If the results from between the 50,000 hour replications and shorter replications are not significantly different, the shorter replication length will be used.

Five simulations are run for ten replications each with run lengths at intervals of 10,000 hours, starting at 10,000 and ending at 50,000 hours in the MTO fab at ten percent rework using the FIFO/WAIT strategy. Hypothesis tests are done for each product, using paired t-tests at a 95 percent confidence level, to determine if the average cycle time and standard deviation of cycle time for each of the different run lengths differs from that of the 50,000 run length trial. It is determined that there are no significant differences in average cycle time between the 50,000 hour replication length and any of the others (see Table 5.4). For the standard deviation of cycle time, there was a significant difference between the 50,000 and 10,000 replication lengths for two of the products, but no significant differences for any of the other run lengths (see Table 5.3). Therefore, an appropriate replication run length was determined to be 20,000 hours.

Table 5.4 Paired T-Test for Difference in Means between 10,000 and 50,000 Hour Replications

10,000 vs. 50,000 hour replications		
	P-value	95% CI (hrs.)
A	0.832	(-9.17, 7.55)
AT	0.797	(-9.55, 7.54)
C	0.805	(-9.32, 7.44)
D	0.916	(-2.96, 3.26)
F	0.988	(-2.45, 2.49)
H	0.89	(-3.21, 2.83)
R	0.861	(-6.92, 5.89)
U	0.822	(-9.78, 7.96)
X	0.843	(-6.46, 5.39)
Y	0.868	(-7.18, 6.16)
Z	0.61	(-4.13, 2.57)

Table 5.5. Paired T-Test for Difference in Standard Deviations between 10,000 and 50,000 Hour Replications, and 20,000 and 50,000 Hour Replications

10,000 vs. 50,000 Hour Replications			20,000 vs. 50,000 Hour Replications	
	P-value	95% CI (hrs.)	P-value	95% CI (hrs.)
A	0.21	(-9.00, 2.27)	0.15	(-2.007, 0.361)
AT	0.21	(-10.15, 2.56)		
C	0.175	(-10.36, 2.18)		
D	0.209	(-2.246, 0.566)		
F	0.047	(-2.865, -0.023)**		
H	0.132	(-2.759, 0.427)		
R	0.156	(-6.45, 1.21)		
U	0.174	(-9.62, 2.02)	0.202	(-5.03, 1.22)
X	0.164	(-6.05, 1.20)		
Y	0.027	(-7.72, -0.59)**		
Z	0.134	(-2.782, 0.438)		

5.1.4 Statistical Analysis Methods

As stated previously, the goal of this thesis is to determine which dispatching rules, rework strategies, and combinations of the two are robust across performance measures in both fabs and at each rework level. In order to draw such conclusions, detailed statistical analysis is done. The statistical software program Minitab is used for this analysis.

Based upon the results previous research, it is expected that the factors tested in this research are significant. Bahaji (2000), Hsu et al. (2001), Sha et al. (2001), conclude that

dispatching rules and fab types, dispatching rules and rework levels, and rework strategies, respectively, are all significant factors. The following analysis methodology focuses on validating these findings and understanding how the interaction of these factors effect fab performance. All of the tests below are conducted for each of the performance measures tested.

Initially, an ANOVA test is conducted on all four factors studied to determine whether each of the factors (main effects) and their interactions (interaction effects) are significant. The output of the ANOVA test generates a confidence level, or p-value, that each of the factors and their interactions are significant at. In this study, a 95 percent confidence level is used to determine the significance of the factor and interaction terms. Therefore, a factor or interaction term with a p-value of .05 or smaller is said to be significant.

The significance of the interaction terms are of main interest from the four factor analysis. Specifically, the four factor interactions are expected to be significant, concluding that the different combinations of the four factors significantly effect the results of the performance measures. Based upon this result, the next step is to test for the significance of the three way interaction of dispatching rule, rework strategy, and rework level in each fab type. Once again, these three way interactions are expected to be significant.

After the three way interactions are shown to be significant, two factor ANOVA tests are done in each fab type and at each rework level. The results of these tests show, at each rework level and in each fab type, whether the dispatching rule and rework strategy are significant independently, and also whether the combination of a dispatching rule and rework strategy is significant. The hypothesis of this thesis anticipates this two way interaction to be significant.

Next, Tukey pairwise comparison tests are done on all factors determined to be significant from the two factor ANOVA tests. The dispatching rule, rework strategy, and

combination of the two are all anticipated to be significant. The Tukey test determines which factor levels are statistically significant from each other. Significance is determined by evaluating the confidence intervals generated for mean value of the performance measure of each factor level. Using this test, if the confidence intervals overlap for two factor levels, the factors are said to not be statistically different from each other. Alternatively, if the confidence intervals do not overlap, the factors are said to be statistically different from each other.

After this analysis, the dispatching rules, rework strategies, and combinations of dispatching rules and rework strategies that are the best for each performance measure, in each fab, and at each rework level can be determined (Law and Kelton 2000). It is important to note that, in some cases, there may be more than one dispatching rule, rework strategy, or combination of them that are significantly the best, but not significantly different from each other. For example, in the MTO fab at one percent rework, the FBN rework strategy may have the best results for average cycle time, but the results may not be significantly different from the WAIT strategy. In such cases, there is said to be a top group of strategies.

Now that the two factor analysis is complete, the top group of dispatching rules, rework strategies, and combinations can be charted to determine which are robust for most or all performance measures at all rework levels and fab types. For the purpose of this study, a strategy is considered if it appears in the top group of at least twenty-five percent of the performance measures.

From the previous analysis, if the fab type and rework level are known, the best combination of dispatching rule and rework strategy can be chosen to optimize one or more performance measures. However, determining whether there are dispatching rules and rework

strategies that are robust regardless of the fab type and rework level is important, as the fab type and rework level may not be fully understood or may change over time.

In order to make this generalization, the strategies that perform well in each fab type, regardless of rework level, are chosen. In each fab type there are three rework levels and five performance measures (percent idle is left out and is discussed in chapter seven); therefore there are fifteen separate groups a strategy may appear in. Based upon the criterion discussed previously, for a strategy to be considered, it must appear in the top group of at least four of the 15 performance measures groups.

Two factor ANOVA tests are done on this top group of strategies for each performance measure in each fab type using the dispatching rules and rework strategies as the factors. The data from all three rework levels is analyzed together, and the rework level is used as a blocking factor in the ANOVA analysis. This means that the differences in the performance measures due to the change in rework level are accounted for. Resulting from this ANOVA analysis, Tukey pairwise comparison tests are then done for all of the significant factors and interactions. These results show, in each fab type, which dispatching rule and rework strategy are the best regardless of rework level.

After the two factor analysis, another two factor analysis is done to determine which dispatching rule and rework strategy are the best regardless of rework level and fab type. To do this, the factor fab type is included in the ANOVA analysis as another blocking level. The same criterion is used to determine if a strategy is robust, that is, the strategy must appear in the top group of at least twenty-five percent of the performance measures. In this analysis, there are five performance measures, three rework levels, and two fabs, for a total of thirty top groups. Therefore, a strategy must appear in at least eight of the thirty to be considered robust.

Following ANOVA analysis of the robust strategies, for all factors that are considered significant, Tukey pairwise comparison tests are done to determine which dispatching rules and rework strategies are significantly different than the rest. From these tests, the best dispatching rule and rework strategy regardless of rework level and fab type are determined.

5.2 Analysis of Results

From the results of the analysis discussed in Section 5.1.4, there are some interesting observations regarding the split rework strategy and percent idle performance measure that need to be addressed. Following those sections, the results from the analysis are discussed in detail.

5.2.1 Split Strategy Results

During experimentation, it is discovered that using the SP rework strategy with any combination of dispatching rule and rework strategy at all rework levels causes the fabs to become overloaded and never reach steady state. Recall that the SP strategy causes all lots that need rework, which are usually of small quantities, to become their own independent lot and are never rejoined with their mother lot. Resulting from this, these small lots are being processed in tools that require long processing times, such as the oxidation furnaces. These stations are already highly utilized, therefore adding more lots at these stations causes their queues to build up faster than the station can process lots, causing WIP levels to constantly increase. Consequently, the SP strategy is not recommended in a fab with such numerous possibility for rework. A graph is shown below (Figure 5.2) that shows the average cycle time of the first 200 days for the WAIT and SP strategy. From this result, the SP strategy will be left out of the statistical analysis.

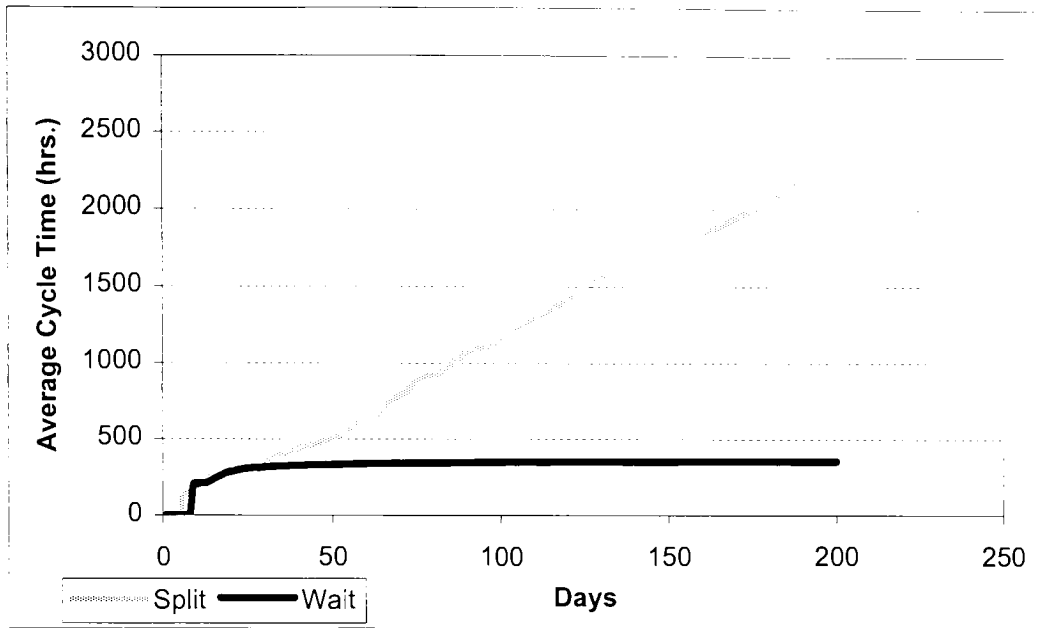


Figure 5.2. Comparison of Average Cycle Time between the Split and Wait Rework Strategies

5.2.2 Percent Idle Performance Measure

While initially looking at the experimental results, the percent idle performance measure becomes a concern. As previously stated, if a fab can achieve the same throughput with a higher idle rate, it is producing lots more efficiently. While this is true, the FBN and RV rework strategies inherently perform worse in this measure than the WAIT strategy. This is because all processing stations before the first bottleneck and the rendezvous point have their loading increased as both the child and mother lots travel through these stations independently. Therefore, this performance measure is biased towards the WAIT rework strategy. The results from this performance measure are tabulated in the analysis, but are not used when determining the robustness of a strategy.

5.2.3 Four Factor Analysis

After all of the experiments are run, an ANOVA analysis is conducted on all four factors in this experiment. The purpose of doing this is to determine which of the factors significantly effect the performance measures in the fabs. The results of this test show that all of the factors and their interactions are significant at 95 percent confidence for all of the performance measures tested. Table 5.6 shows the ANOVA results for average cycle time. In the ANOVA table, the factors, fab type, dispatching rule, rework strategy, and rework level, are denoted Fab, DR, RS, and RL respectively. The ANOVA tables for the other performance measures can be seen in Appendix C. Now that the all of the factors and their interactions are shown to be significant, ANOVA analysis is done for each fab type.

Table 5.6. Four-Factor ANOVA Table for Average Cycle Time

Source	DF	Seq SS	Adj SS	Adj MS	F	P
Fab	1	559924.000	559924.000	559924.000	40000.000	0.000
DR	4	230462.000	230462.000	57615.000	4077.990	0.000
RS	2	79710.000	79710.000	39855.000	2820.920	0.000
RL	2	520896.000	520896.000	260448.000	18000.000	0.000
Fab*DR	4	1628.000	1628.000	407.000	28.800	0.000
Fab*RS	2	464.000	464.000	232.000	16.410	0.000
Fab*RL	2	12813.000	12813.000	6406.000	453.440	0.000
DR*RS	8	77275.000	77275.000	9659.000	683.680	0.000
DR*RL	8	130628.000	130628.000	16328.000	1155.720	0.000
RS*RL	4	48641.000	48641.000	12160.000	860.700	0.000
Fab*DR*RS	8	911.000	911.000	114.000	8.060	0.000
Fab*DR*RL	8	3124.000	3124.000	391.000	27.640	0.000
Fab*RS*RL	4	1329.000	1329.000	332.000	23.510	0.000
DR*RS*RL	16	35314.000	35314.000	2207.000	156.220	0.000
Fab*DR*RS*RL	16	4959.000	4959.000	310.000	21.940	0.000
Error	810	11444.000	11444.000	14.000		
Total	899	1719521.000				

5.2.4 Analysis of the Make-to-Order Fab

Following the fourfactor analysis, it is now necessary to determine if, for each fab type, each of the threefactors, dispatching rule, rework strategy, and rework level, and their interactions are significant. To determine their significance of these factors in the MTO fab,

ANOVA analysis is once again performed. The analysis concludes that, for all performance measures, all of the factors and their interactions are significant at a confidence level of 95 percent. The ANOVA tables for these tests can be seen in Appendix D.

Based upon these threefactor results, twofactor ANOVA analysis using the dispatching rule and rework strategy factors is now done for each rework level. The results of these tests show that the factors and their interactions are significant for all performance measures and at all rework levels. The raw data from these experiments can be seen in Appendix B. The ANOVA table for average cycle time at one percent rework can be seen in Table 5.7. The p-values in the right hand column show the level of significance that the factors are significant to. The p-values of .000 conclude that the factors are all significant to at least a 99.9 percent confidence level. The rest of the ANOVA tables for the MTO fab can be seen in Appendix E.

Table 5.7. ANOVA Table for Average Cycle Time in the MTO Fab at 1 Percent Rework

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	11127.730	11127.730	2781.930	2093.760	0.000
RS	2	157.390	157.390	78.690	59.230	0.000
DR*RS	8	103.810	103.810	12.980	9.770	0.000
Error	135	179.370	179.370	1.330		
Total	149	11568.310				

Now it can be said that the dispatching rule, rework strategy, and their interaction are all significant at each rework level in this fab. The next step in the analysis is to determine which dispatching rules, rework strategies, and combinations are significantly better than the others. Simply ranking the results from best to worst is not an acceptable method as there is variability associated with the experimental data. This variability has to be taken into account when determining whether one factor is significantly better than another. Therefore, Tukey pairwise comparison tests are used for this purpose, as they determine whether each dispatching rule,

rework strategy, and combination of them is statistically significant from each other at a predetermined confidence level. A 95 percent confidence level used in this research.

A pairwise comparison chart based upon these Tukey test results for average cycle time at one percent rework can be seen in Figure 5.3. The vertical lines in the significance column show the strategies that are statistically the same as each other. For example, in the leftmost table in Figure 5.3, the first strategy is not statistically different from the next three, but is statistically different that the fifth. The rest of the pairwise comparison tables for the MTO fab can be seen in Appendix E. After all of the Tukey pairwise comparison tests are done in the MTO fab, the top group of strategies for each performance measure and each rework level were charted to determine if a strategy is robust across rework levels and performance measures.

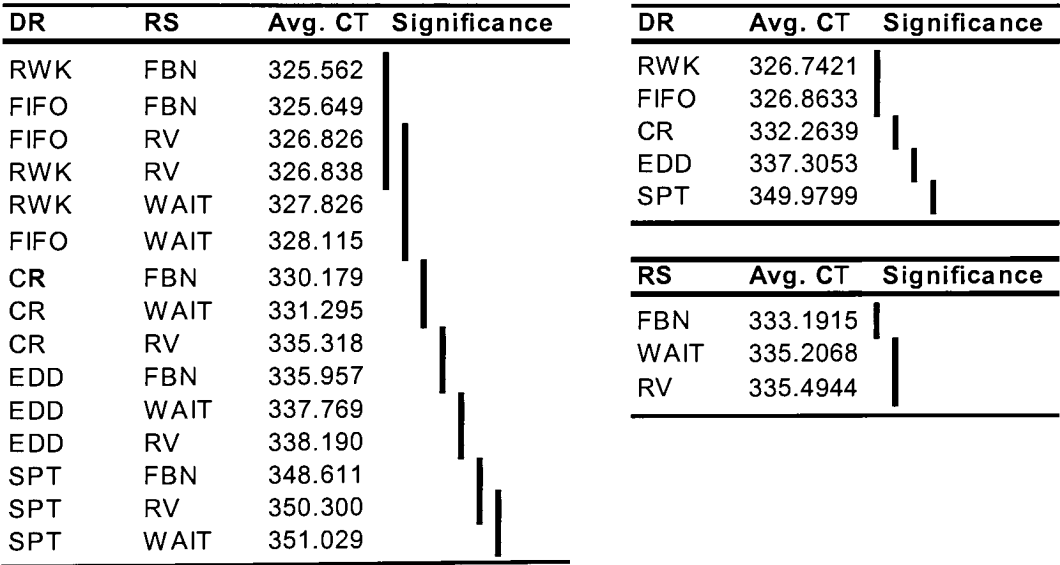


Figure 5.3. Tukey Pairwise Comparison Test for Average Cycle Time in the MTO Fab at 1 Percent Rework

Table 5.8. Top Groups of Dispatching Rules in the Make-to-Order Fab

% Rework	Avg. CT	Std. Dev. CT	% On Time	Avg. WIP	Avg. XT
1	RWK	CR	RWK	RWK	RWK
	FIFO		FIFO	FIFO	FIFO
			CR		
5	RWK	RWK	RWK	RWK	RWK
	FIFO	FIFO	FIFO	FIFO	FIFO
10	RWK	RWK	RWK	RWK	RWK
		FIFO			

From these tables it is clear that the RWK and FIFO dispatching rules are robust at one and five percent rework (see Table 5.8), and then at ten percent rework, the RWK rule outperforms all other rules. For rework strategies, the FBN strategy created in this research is robust across all performance measures and rework levels, while the WAIT strategy only appears in a few instances (see Table 5.9).

Table 5.9. Top Groups of Rework Strategies in the Make-to-Order Fab

% Rework	Avg. CT	Std. Dev. CT	% On Time	Avg. WIP	Avg. XT
1	FBN	WAIT FBN	FBN	FBN	FBN
5	FBN	WAIT FBN	FBN	FBN	FBN
10	FBN	FBN WAIT	FBN	FBN	FBN WAIT

The primary interest in this research, the combination of a dispatching rule and rework strategy, shows that the rework strategy created in this study, FBN, performs very well in combination with the RWK and FIFO dispatching rules (see Table 5.10) at all rework levels. Once again, the reason that the FBN strategy is superior is that it allows the mother lot to go through non-bottleneck processing stations, especially per piece processing stations ahead of the child lot, thus saving processing time at these stations. For simplicity, the combination of a dispatching rule and a rework strategy will be referred to as a strategy from this point on in discussion. It is important to note that, although the RWK/FBN strategy finishes ahead of the

FIFO/FBN strategy for almost every performance measure, the differences between them are not statistically significant at a 95 percent confidence level.

It is also interesting to note that the CR rule, which is shown to be an effective rule for on time performance in previous research, performed poorly in general. This rule is only in a few top groups at one percent rework, and in none at five and ten percent rework. Also, the EDD and SPT dispatching rules are not in the any of the top groups at any rework level. Possible reasons for these findings are discussed in Section 5.3.

Table 5.10. Top Groups of Strategies in the Make-to-Order Fab

% Rework	Avg. CT	Std. Dev. CT	% On Time	Avg. WIP	Avg. XT
1	RWK / FBN	CR / WAIT	CR / FBN	RWK / FBN	RWK / FBN
	FIFO / FBN	CR / FBN	CR / WAIT	FIFO / FBN	FIFO / FBN
	FIFO / RV		RWK / FBN	FIFO / RV	FIFO / RV
	RWK / RV		FIFO / FBN	RWK / RV	RWK / RV
			RWK / RV		
			FIFO / RV		
			RWK / WAIT		
			FIFO / WAIT		
5	RWK / FBN	RWK / FBN	RWK / FBN	RWK / FBN	RWK / FBN
	FIFO / FBN	FIFO / FBN	FIFO / FBN	FIFO / FBN	FIFO / FBN
		RWK / WAIT			
		FIFO / WAIT			
		CR / WAIT			
		RWK / RV			
		FIFO / RV			
10	RWK / FBN	RWK / FBN	RWK / FBN	RWK / FBN	RWK / FBN
	FIFO / FBN	RWK / WAIT	FIFO / FBN	FIFO / FBN	FIFO / FBN
		FIFO / FBN	RWK / WAIT		RWK / WAIT
		FIFO / WAIT	FIFO / WAIT		
		RWK / RV			
		FIFO / RV			

5.2.5 Analysis of the Make-to-Stock Fab

Analysis of the data from the MTS fab experiments show results that are very similar to those of the MTO fab. The raw data from these experiments can be seen in Appendix B. Once again, the three factor ANOVA analysis is done with the dispatching rule, rework strategy, and rework level factors. The results show that the factors and their interactions are all significant at

95 percent confidence for all performance measures. These ANOVA tables can be seen in Appendix F.

Based upon these results, twofactor ANOVA tests are done on all combinations of dispatching rules and rework strategies at each level of rework. For all of the performance measures and at all rework levels, the factors and their interactions are found to be significant at a 95 percent confidence level with the following exceptions. At one percent rework, the rework strategy and the interaction of dispatching rule and rework strategy for the standard deviation of cycle time are not significant. Also, at one percent rework, the interaction of dispatching rule and rework strategy for percent idle is not significant. The full ANOVA results can be seen in Appendix G.

As done in the MTO fab, Tukey pairwise comparison tests are conducted for each of the factors and their interactions to determine what factors and interactions are statistically superior to the others. The full results can be seen in Appendix G. Table 5.11 shows the top groups of dispatching rules, and from this table, it is clear that the RWK and FIFO dispatching rules are again the best for the one and five percent rework levels, and for the ten percent rework level, the RWK rule becomes superior.

Table 5.11. Top Group of Dispatching Rules in the Make-to-Stock Fab

% Rework	Avg. CT	Std. Dev. CT	% On Time	Avg. WIP	Avg. XT
1	RWK	FIFO	CR	RWK	RWK
	FIFO	RWK	RWK	FIFO	FIFO
			FIFO		
5	RWK	RWK	RWK	RWK	RWK
	FIFO	FIFO	FIFO	FIFO	FIFO
10	RWK	RWK	RWK	RWK	RWK
		FIFO			

Furthermore, the FBN rework strategy is once again very robust across all performance measures and rework levels (see Table 5.12). There are only two instances where there are other

strategies in the top group, and they are both in the standard deviation of cycle time performance measure. Also very similar to the MTO fab, the strategies that are the most robust are again RWK/FBN and FIFO/FBN (see Table 5.13). It can once again be noticed that the CR, EDD, and SPT dispatching rules do not perform well for most of the performance measures. The CR rule is only in the top group of dispatching rules for percentage on time at one percent rework, and in a couple of top strategies at one percent rework. The EDD and SPT rules are once again not in any top groups. Possible reasons for these findings will be discussed in Chapter 5.3.

Table 5.12. Top Groups of Rework Strategies in the Make-to-Stock Fab

% Rework	Avg. CT	Std. Dev. CT	% On Time	Avg. WIP	Avg. XT
1	FBN	FBN WAIT RV	FBN	FBN	FBN
5	FBN	FBN	FBN	FBN	FBN
10	FBN	FBN WAIT	FBN	FBN	FBN

Table 5.13. Top Groups of Strategies in the Make-to-Stock Fab

% Rework	Avg. CT	Std. Dev. CT	% On Time	Avg. WIP	Avg. XT
1	RWK / FBN FIFO / FBN RWK / RV FIFO / RV RWK / WAIT	RWK / FBN FIFO / FBN FIFO / RV RWK / RV FIFO / WAIT RWK / WAIT CR / FBN CR / RV	CR / FBN CR / WAIT FIFO / FBN RWK / FBN	RWK / FBN FIFO / FBN RWK / RV FIFO / RV RWK / WAIT	FIFO / FBN RWK / FBN RWK / RV FIFO / RV RWK / WAIT FIFO / WAIT
5	RWK / FBN FIFO / FBN	RWK / FBN FIFO / FBN RWK / RV FIFO / RV RWK / WAIT FIFO / WAIT	RWK / FBN FIFO / FBN CR / FBN RWK / WAIT RWK / RV FIFO / RV	RWK / FBN FIFO / FBN	RWK / FBN FIFO / FBN
10	RWK / FBN FIFO / FBN	RWK / FBN FIFO / FBN RWK / WAIT RWK / RV FIFO / WAIT FIFO / RV	RWK / FBN FIFO / FBN RWK / WAIT	RWK / FBN FIFO / FBN	RWK / FBN FIFO / FBN RWK / WAIT

5.3 Performance of the CR, EDD, and SPT Dispatching Rules

In previous research, the CR and EDD dispatching rules are shown to be good for the percentage on time performance measure. Rose (2002) derives a heuristic for using the flow factor (FF) to set due dates in combination with the CR dispatching rule to achieve good on time performance. That methodology for setting due dates is used in this research, yet the results are contradictory to the findings from his study. The reason for this could be that these rules tend to make the products finish processing very close to their due dates with a small amount of slack. Slack refers to the difference in the time until due and the remaining processing time. In other words, the slack time is the maximum amount of time the lot can spend waiting to be processed before it becomes late. Therefore, when a lot has a small slack time and needs rework, the added time it spends in the rework loop will most likely make the lot late regardless of the dispatching rule or rework strategy used.

Figure 5.4 shows the slack time remaining when the lot finished processing for the EDD/WAIT and the FIFO/WAIT strategies in the MTO fab with ten percent rework. In this case, negative and positive slack denote the lot being early and late, respectively, with zero being the exactly on time. As a result, any lots finishing processing after their due date have a positive slack value. These graphs show how the EDD/WAIT dispatching rule has a rather peculiar distribution with two distinct peaks and a large upper tail. This is much different than the FIFO/WAIT distribution, which appears to be normally distributed. Consequently, the EDD distribution causes many lots to be late by a small amount of time and the range of slack values is much larger than with FIFO.

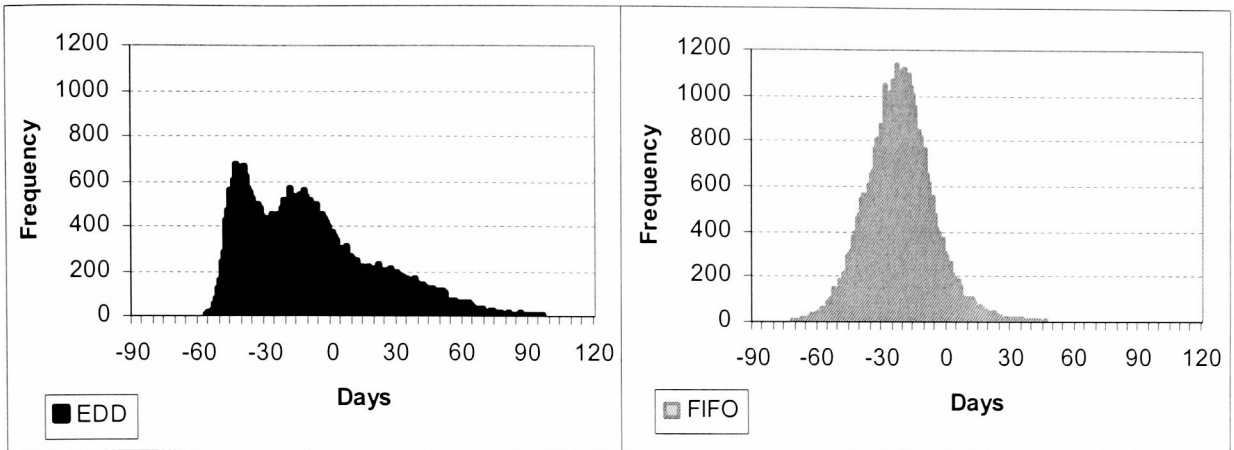


Figure 5.4. Slack Time for the EDD/WAIT and FIFO/WAIT strategies

The SPT rule performs poorly for all of the performance measures. The cause of this is most likely that the products with large processing times at a station get stuck in queue for a long time before they are selected for processing. The difference in on time performance between the SPT/WAIT and FIFO/WAIT strategies at ten percent rework can be seen in Figure 5.5. The parts are denoted with a lettering scheme on the x-axis. This graph shows how a few parts have good on time performance (e.g. Z) with the SPT rule, but others suffer at the expense of them (e.g. X). The routings for these parts can be seen in Appendix K.

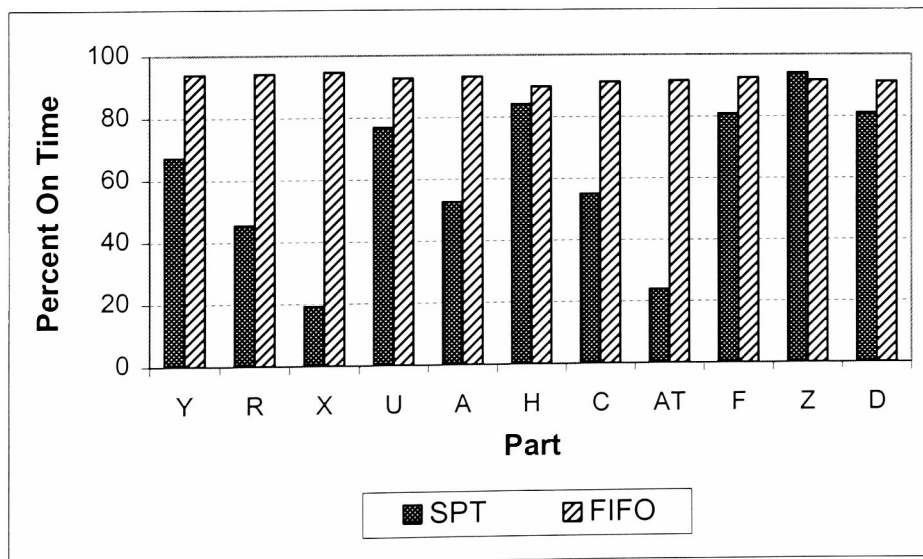


Figure 5.5. Percent On Time Comparison Between SPT/WAIT and FIFO/WAIT at Ten Percent Rework

5.4 Analysis of Robust Strategies

Resulting from the RWK/FBN and FIFO/FBN strategies being superior, it is decided to further analyze these two, along with the other strategies that perform fairly well across rework levels and fab types. The purpose of doing this is to determine if there is a strategy that is significantly superior across all performance measures regardless of rework level, and subsequently, regardless of rework level and fab type. A strategy is considered for this study if it appears in the top group of at least twenty-five percent of the performance measures.

5.4.1 Two Factor Analysis to Determine Robust Strategy in Each Fab Type

To determine if there is a dispatching rule and rework strategy that is superior regardless of rework level, a two factor analysis is conducted for the strategies that perform well in each fab type using rework level as a blocking factor. For this analysis, there are three rework levels and five performance measures; therefore there are fifteen separate groups a strategy may appear in. Consequently, for a strategy to be considered, it must appear in the top group of at least four of the 15 performance measures groups. Based upon this criterion, the strategies that are considered robust are RWK/FBN, FIFO/FBN, RWK/RV, FIFO/RV, RWK/WAIT, and FIFO/WAIT in both the MTO and MTS fabs.

ANOVA tests are done on this top group of strategies for each performance measure in each fab type. From the analysis of these top groups, in the MTO fab the dispatching rule and rework strategy are significant independently, but their interaction is not significant for any of the performance measures. These ANOVA tables can be seen in Appendix H. This signifies that, regardless of rework level, the dispatching rule and rework strategy chosen is important, but there is not a significant interaction between them. Tukey tests are then done for both

dispatching rule and rework strategy on every performance measure. The results from these tests show that RWK dispatching rule is significantly better than the FIFO rule for all performance measures. Also, for every performance measure, the FBN rework strategy is significantly better than the WAIT strategy, which is significantly better than the RV strategy. These Tukey test results can also be seen in Appendix H.

The results from the MTS fab are very similar, with only a few small differences. The ANOVA analysis shows that the combination of a dispatching rule and rework strategy is not significant in all of the performance measures except percentage on time (see Appendix I for ANOVA tables). Also, the dispatching rule and rework strategy are independently significant for all performance measures. Once again, the Tukey tests, which can be seen in Appendix I, reveal that the RWK dispatching rule is significantly better than FIFO for all performance measures. Furthermore, the FBN rework strategy is significantly better than the WAIT and RV strategies, and WAIT is significantly better than RV for all performance measures except for standard deviation of cycle time. For this performance measure, there is no significant difference between the WAIT and RV strategies.

These results are very interesting as with any amount of rework and in either fab type, the RWK dispatching rule and the FBN rework strategy are superior to the others tested. This concludes that in general, using the RWK/FBN strategy in either fab type with any rework level will be a very good solution.

5.4.2 Two Factor Analysis to Determine Robust Strategy Overall

From the previous section, it is determined that the RWK/FBN strategy is good to use in both fabs independent of the rework level. Now, the factor fab type will be included in the

ANOVA analysis as another blocking level so that the generalization can be further made that a strategy is robust across rework levels and fab types. The same criterion is used to determine strategies to be analyzed, that is, the strategy must appear in the top group of at least twenty-five percent of the performance measures. In this analysis, there are five performance measures, three rework levels, and two fabs, for a total of thirty top groups. Therefore, a strategy must appear in at least eight of the thirty to be considered. Based upon this criterion, the strategies used for this analysis are the same as in the previous section, the RWK/FBN, FIFO/FBN, RWK/RV, FIFO/RV, RWK/WAIT, and FIFO/WAIT. Following the ANOVA analysis, for all factors that are considered significant, Tukey tests are done to determine which strategies are significantly different than the rest.

The ANOVA analysis reveals that for all of the performance measures, the dispatching rule and rework strategy are significant at a 95 percent confidence level (see Appendix J). The Tukey tests for the dispatching rules shows that the RWK rule is significantly better than FIFO for all performance measures. Also, the Tukey tests for the rework strategies conclude that the FBN strategy is superior to the WAIT and RV strategies for all performance measures. These tests also show that the WAIT strategy is superior to the RV strategy across all performance measures.

From the ANOVA analysis, the combination of dispatching rule and rework strategy is also found to be significant for percentage on time, average WIP, and average XT. For the percentage on time measure, the RWK/FBN and FIFO/FBN strategies are statistically superior to all of the others tested, but are not significantly different than each other. This is not the case with average WIP and average XT, as these two measures show that the RWK/FBN strategy is superior to all others.

The conclusion that can be drawn from these results are that, regardless of the rework level and fab type, the RWK dispatching rule and FBN rework strategy will give good results in terms of the performance measures studied. Also, for some of the performance measures, the interaction between the dispatching rule and rework strategy is significant, therefore using them together will improve the performance of the fab.

5.5 Summary

The results of this experiment show the best combinations of dispatching rule and rework strategy to use at different rework levels and in different fab types to optimize various performance measures. These results show the RWK/FBN and FIFO/FBN strategies to be superior at one and five percent rework, and the RWK/FBN rule to be superior at ten percent rework in both fab types for most performance measures.

Also, resulting from the analysis of the robust strategies, the RWK/FBN strategy is shown to be robust for regardless of the rework level and fab type. It is important to note that in most other research, a dispatching rule or rework strategy has been shown to be superior in one or two performance measures, but perform poorly in others. The results of this study show that the top strategies are superior for most, if not all, of the performance measures studied.

This research used the FIFO/WAIT strategy as a baseline, as it is easy to implement and is benchmarked in most previous research. Therefore, it is useful to quantify the amount of improvement that the RWK/FBN strategy achieves over the FIFO/WAIT strategy to understand the impact that this strategy can have in a fab. These improvements can be seen in Table 5.14. The values in boldface are statistically significant at a 95 percent confidence level.

Table 5.14. Improvement of RWK/FBN over FIFO/WAIT strategies

Fab	Rework	Average CT (hrs.)	Std. Dev. CT (hrs.)	Percent On Time	Average WIP (lots)	Average Xtheor
MTO	1%	2.55	0.07	1.77	1.42	0.01
	5%	7.91	0.70	4.00	4.40	0.03
	10%	15.20	2.25	6.92	8.46	0.05
MTS	1%	2.85	0.57	1.49	0.96	0.01
	5%	11.08	2.63	5.17	3.72	0.04
	10%	21.42	5.11	9.36	7.19	0.07

The FBN rework strategy created in this research shows superior performance in both fab types and at all rework levels. This strategy capitalizes on the under-utilized stations following rework possibilities by allowing the mother and child lot to travel through these stations separately. Another important aspect of the FBN strategy is that it would be fairly easy to implement, even in a complex fab setting. This strategy is simply an extension of the wait strategy, with the mother lot going through some number of processing steps before it waits to be joined with the child lot. This strategy also keeps the reworked wafers with their original lot, making lot tracing simple. These things make the FBN strategy attractive from a management perspective.

6. CONCLUSIONS & RECOMMENDATIONS FOR FUTURE RESEARCH

6.1 Conclusions

The semiconductor industry is extremely competitive. Based on the nature of the industry, small improvements in performance can have a large financial impact. Rework is present in modern day fabs and is inherently harmful to the performance and thus the profitability of fabs. However, previous research in the semiconductor field is found to be rather inconclusive on the importance of including rework in research studies. Initially, this research determines if the presence of rework significantly effects fab performance.

An experiment is conducted which concludes that the presence of rework does have a significant effect on key fab performance measures such as average cycle time and average WIP. Therefore, including rework in semiconductor research is necessary, and investigating methods to lessen the detrimental effect that rework has in fabs should be explored.

Two operational decisions made in fabs that literature has shown to effect fab performance are dispatching rules and rework strategies. This experiment focuses on the interaction between existing dispatching rules and rework strategies, and how they effect key performance measures at different rework levels and in different fab types.

The results show the RWK/FBN and FIFO/FBN strategies to be superior at one and five percent rework, and the RWK/FBN rule to be superior at ten percent rework in both fab types. Also, the RWK/FBN strategy is shown to be robust for regardless of the rework level and fab type. The FBN rework strategy, which is developed in this study, is shown to be superior to the others proposed in previous literature. Furthermore, most other research has shown a dispatching rule or rework strategy to be superior in one or two performance measures, but perform poorly in others. These results show that the top strategies are superior for most, if not

all, of the performance measures studied. The RWK/FBN strategy shows significant improvements in performance measures including average cycle time, percentage on time, and average WIP over the FIFO/WAIT strategy. Such improvement can have large economic implications for semiconductor fabs.

6.2 Recommendations for Future Research

Resulting from this study is the opportunity for further research based upon findings and conclusions from this work. Such ideas include running more replications to determine if there is a statistically significant difference between the top two strategies. Also, with the FBN rework strategy, other methods of determining the first bottleneck after the possibility for rework can be explored. Furthermore, more complex dispatching rules can be tested in combination with the FBN rework strategy in an attempt to further improve fab performance. Also, in this research, when the RWK dispatching rule is used, if there is no rework in queue, the secondary dispatching rule is FIFO. Perhaps a different secondary dispatching rule could be used to improve the performance measures. Lastly, further validation of the FBN strategy in other simulation models can give the strategy further credibility in industry.

6.2.1 Discrimination between Top Strategies

This research has shown that the RWK/FBN strategy is robust and gives the best statistical results for most of the performance measures in both fabs. However, some of these results are not statistically significant from the top group of strategies. These results are based on ten replications for each experiment and at a confidence level of 95 percent.

Running additional replications for these top strategies can be done to get a better estimation of the true values of the performance measures and to make the sample standard deviation smaller. This will allow the confidence intervals generated by the Tukey test to be smaller and therefore the test will discriminate between the strategies to a further extent. Additional replications of each of these strategies can be run at all of the rework levels to determine if there are statistically significant differences between the top strategies.

6.2.2 New Methods for Determining First Bottleneck

The current method for determining what is the first bottleneck station after a rework step has passed is discussed in Chapter 5.1. Currently, a station with above 85 percent station utilization is determined to be a bottleneck. Experimenting with this utilization cutoff could help to see further increases in fab performance measures. There are also other measures that can be looked at to determine the first bottleneck, such as average or maximum queue size. The impact of setup times on bottleneck stations is ignored in this research and can also be investigated.

6.2.3 Alternative Dispatching Rules

The dispatching rules tested in this study, FIFO, SPT, EDD, RWK, and CR are very common and widely understood rules. Much literature has attempted to derive new, more complex dispatching rules, many of which are based upon these and other commonly used rules. This study focused on these simple rules in an attempt to begin to understand how dispatching rules and rework strategies can independently and interactively impact fab performance.

The RWK dispatching rule is found to be the best of the five tested in this study. When the RWK dispatching rule is used, if there is no rework in the queue, the secondary dispatching

rule used is FIFO. Perhaps a different secondary dispatching rule could be specified that would positively effect the overall performance of the fab. Also, stations could have different dispatching rules depending on how they effect the performance of a fab. For instance, stations that are under utilized may benefit from such rules as CR or EDD, as lots with large processing times or large due dates are not likely to get stuck in queue there. Similarly, stations with high utilizations may benefit from rules such as FIFO to ensure that one lot does not get stuck in the queue for a large amount of time. Determining the number of times that the queuing order changes at each station as a result of the chosen dispatching rule could also be beneficial in choosing different rules for different stations. There are also various other dispatching rules proposed in literature that could be attempted in combination with the FBN rework strategy.

6.2.4 First Bottleneck Validation

In this study, the FBN rework strategy is developed and proven to be better than the previously studied strategies. Now, it should be simulated in other fab models to further validate these findings. If other studies can prove this strategy to be superior and significantly impact fab performance, the implementation of this strategy in a full-scale production fab would give it further credibility in industry.

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APPENDECIES

The following Appendices contain raw data and statistical analysis from this research. Each appendix has an explanation of what it contains, and all tables and figures are labeled accordingly.

Appendix A. Results of Rework Strategy

This Appendix shows the results from test done to determine if rework makes a significant difference in fab performance.

Table A.1. Results from the Fab Without Rework

Rep.	No Rework Fab		
	Avg. CT (hrs.)	St. Dev. CT (hrs.)	Avg. WIP (lots)
1	323.323	78.546	179.870
2	323.326	78.492	179.870
3	324.188	78.718	180.360
4	324.913	79.002	180.750
5	322.917	78.355	179.640
6	324.086	78.917	180.290
7	323.873	78.717	180.170
8	324.191	78.867	180.360
9	323.470	78.722	179.950
10	324.281	78.875	180.400
Avg.	323.857	78.721	180.166

Table A.2. Results from the Fab With Rework

Rep.	Rework Fab		
	Avg. CT (hrs.)	St. Dev. CT (hrs.)	Avg. WIP (lots)
1	339.312	83.153	188.760
2	339.683	83.200	188.970
3	340.372	83.214	189.350
4	340.742	83.273	189.550
5	339.421	83.069	188.830
6	339.905	83.263	189.090
7	340.045	83.301	189.170
8	340.064	83.299	189.180
9	339.883	83.227	189.090
10	340.439	83.381	189.380
Avg.	339.987	83.238	189.137

Appendix B. Experimental Data

This appendix contains the raw data from the MTO and MTS fabs. All data shown is an average of ten replications.

Table B.1. MTO Fab Raw Data

	DR	RS	Average CT (hrs.)	Std. Dev. CT (hrs.)	Percent On Time	Percent Idle	Average WIP (lots)	Average XTheor
1%	FIFO	WAIT	328.12	79.65	92.45	59.24	182.53	1.45
	FIFO	RV	326.83	79.87	93.10	59.09	181.82	1.44
	FIFO	FBN	325.65	79.60	94.14	58.73	181.16	1.44
	SPT	WAIT	351.03	99.73	56.34	59.47	195.29	1.54
	SPT	RV	350.30	101.10	58.14	59.31	194.88	1.53
	SPT	FBN	348.61	99.86	59.73	58.96	193.95	1.53
	EDD	WAIT	337.77	102.39	72.96	59.35	187.90	1.47
	EDD	RV	338.19	104.30	71.17	59.21	188.14	1.47
	EDD	FBN	335.96	102.75	74.39	58.84	186.90	1.46
	CR	WAIT	331.30	77.78	94.84	59.21	184.30	1.47
	CR	RV	335.32	80.19	88.72	59.09	186.54	1.48
	CR	FBN	330.18	77.85	95.56	58.71	183.68	1.46
	RWK	WAIT	327.83	79.59	92.75	59.23	182.37	1.45
	RWK	RV	326.84	79.92	93.12	59.08	181.82	1.44
	RWK	FBN	325.56	79.58	94.21	58.73	181.11	1.44
5%	FIFO	WAIT	338.51	82.21	92.43	58.16	188.31	1.50
	FIFO	RV	336.73	83.46	92.31	57.76	187.32	1.49
	FIFO	FBN	330.86	81.61	96.38	56.81	184.06	1.47
	SPT	WAIT	362.44	102.66	55.27	58.41	201.63	1.59
	SPT	RV	369.11	115.05	52.32	58.01	205.34	1.61
	SPT	FBN	355.57	103.62	63.81	57.05	197.81	1.56
	EDD	WAIT	348.92	106.48	71.57	58.27	194.11	1.52
	EDD	RV	355.19	114.18	60.18	57.91	197.60	1.53
	EDD	FBN	342.76	106.49	76.89	56.93	190.68	1.50
	CR	WAIT	346.69	82.82	88.30	58.16	192.87	1.54
	CR	RV	426.61	116.33	0.68	58.10	237.33	1.87
	CR	FBN	346.11	84.41	89.20	56.83	192.55	1.54
	RWK	WAIT	337.32	81.94	93.13	58.16	187.65	1.49
	RWK	RV	335.95	83.32	92.75	57.76	186.90	1.48
	RWK	FBN	330.60	81.51	96.43	56.81	183.91	1.47
10%	FIFO	WAIT	359.45	87.86	91.09	57.29	199.96	1.59
	FIFO	RV	370.15	94.20	73.18	56.75	205.92	1.63
	FIFO	FBN	347.66	86.50	97.06	55.45	193.41	1.55
	SPT	WAIT	386.31	117.15	57.39	57.53	214.91	1.69
	SPT	RV	425.00	169.72	43.59	57.01	236.47	1.83
	SPT	FBN	380.43	118.12	61.90	55.69	211.64	1.68
	EDD	WAIT	372.28	118.32	65.24	57.41	207.11	1.61
	EDD	RV	391.89	130.01	38.74	56.91	218.02	1.69
	EDD	FBN	363.74	116.60	73.86	55.56	202.35	1.59
	CR	WAIT	400.35	104.22	9.76	57.40	222.72	1.76
	CR	RV	490.73	139.39	0.31	57.08	273.00	2.15
	CR	FBN	406.22	106.53	4.44	55.63	225.98	1.81
	RWK	WAIT	353.47	86.23	95.36	57.28	196.64	1.56
	RWK	RV	362.93	92.18	82.41	56.73	201.90	1.60
	RWK	FBN	344.25	85.61	98.01	55.43	191.51	1.54

Table B.2. MTS Fab Raw Data

	DR	RS	Average CT (hrs.)	Std. Dev. CT (hrs.)	Percent On Time	Percent Idle	Average WIP (lots)	Average XTheor
1%	FIFO	WAIT	373.34	41.61	91.69	71.41	125.32	1.46
	FIFO	RV	372.34	41.25	91.98	71.31	124.98	1.46
	FIFO	FBN	370.64	41.14	93.24	71.08	124.41	1.45
	SPT	WAIT	392.63	55.12	61.45	71.55	131.80	1.53
	SPT	RV	393.29	57.15	60.90	71.45	132.02	1.54
	SPT	FBN	390.34	55.07	64.57	71.23	131.03	1.53
	EDD	WAIT	380.74	59.86	76.62	71.47	127.80	1.48
	EDD	RV	379.46	59.83	77.56	71.38	127.37	1.48
	EDD	FBN	377.90	59.27	79.20	71.15	126.85	1.47
	CR	WAIT	376.29	43.56	95.31	71.39	126.31	1.47
	CR	RV	380.53	43.96	88.93	71.30	127.74	1.49
	CR	FBN	374.39	42.60	96.26	71.07	125.67	1.47
	RWK	WAIT	373.13	41.75	91.83	71.41	125.25	1.46
	RWK	RV	372.16	41.29	92.34	71.31	124.93	1.46
	RWK	FBN	370.49	41.05	93.18	71.09	124.36	1.45
5%	FIFO	WAIT	388.31	44.78	91.24	70.67	130.34	1.52
	FIFO	RV	386.14	43.25	91.69	70.40	129.62	1.51
	FIFO	FBN	378.51	42.25	95.92	69.78	127.05	1.49
	SPT	WAIT	407.47	60.02	62.06	70.82	136.77	1.59
	SPT	RV	413.15	65.82	56.71	70.55	138.68	1.61
	SPT	FBN	399.22	58.31	71.27	69.93	134.01	1.57
	EDD	WAIT	396.65	64.47	74.59	70.73	133.14	1.54
	EDD	RV	394.71	65.04	75.78	70.47	132.49	1.54
	EDD	FBN	388.58	62.92	81.96	69.86	130.43	1.52
	CR	WAIT	402.67	53.11	75.32	70.66	135.16	1.57
	CR	RV	448.52	60.57	6.93	70.57	150.55	1.75
	CR	FBN	391.11	47.58	94.28	69.78	131.28	1.54
	RWK	WAIT	385.70	44.16	93.07	70.67	129.47	1.51
	RWK	RV	384.08	43.03	92.95	70.40	128.93	1.51
	RWK	FBN	377.23	42.15	96.42	69.78	126.63	1.48
10%	FIFO	WAIT	422.43	51.02	88.51	70.07	141.80	1.65
	FIFO	RV	434.78	51.46	68.87	69.68	145.94	1.70
	FIFO	FBN	407.09	46.86	96.28	68.86	136.65	1.61
	SPT	WAIT	440.04	83.52	67.17	70.22	147.71	1.72
	SPT	RV	475.83	124.95	48.73	69.86	159.72	1.86
	SPT	FBN	432.67	87.24	72.28	69.03	145.23	1.70
	EDD	WAIT	432.63	73.29	70.64	70.14	145.22	1.68
	EDD	RV	440.40	74.55	63.17	69.77	147.83	1.72
	EDD	FBN	421.47	70.82	80.48	68.94	141.47	1.65
	CR	WAIT	474.16	74.89	10.48	70.15	159.16	1.85
	CR	RV	583.73	82.24	0.00	69.89	195.94	2.28
	CR	FBN	459.79	69.45	27.71	68.93	154.34	1.81
	RWK	WAIT	413.10	48.97	94.96	70.06	138.67	1.62
	RWK	RV	423.68	49.18	83.76	69.68	142.22	1.66
	RWK	FBN	401.01	45.90	97.87	68.85	134.61	1.59

Appendix C. Four Factor ANOVA Results

This Appendix contains the ANOVA results for all performance measures when all four experimental factors were included. These results show which factors and interactions of factors are significant.

Table C.1. ANOVA Table for Average Cycle Time

Source	DF	Seq SS	Adj SS	Adj MS	F	P
Fab	1	559924.000	559924.000	559924.000	40000.000	0.000
DR	4	230462.000	230462.000	57615.000	4077.990	0.000
RS	2	79710.000	79710.000	39855.000	2820.920	0.000
RL	2	520896.000	520896.000	260448.000	18000.000	0.000
Fab*DR	4	1628.000	1628.000	407.000	28.800	0.000
Fab*RS	2	464.000	464.000	232.000	16.410	0.000
Fab*RL	2	12813.000	12813.000	6406.000	453.440	0.000
DR*RS	8	77275.000	77275.000	9659.000	683.680	0.000
DR*RL	8	130628.000	130628.000	16328.000	1155.720	0.000
RS*RL	4	48641.000	48641.000	12160.000	860.700	0.000
Fab*DR*RS	8	911.000	911.000	114.000	8.060	0.000
Fab*DR*RL	8	3124.000	3124.000	391.000	27.640	0.000
Fab*RS*RL	4	1329.000	1329.000	332.000	23.510	0.000
DR*RS*RL	16	35314.000	35314.000	2207.000	156.220	0.000
Fab*DR*RS*RL	16	4959.000	4959.000	310.000	21.940	0.000
Error	810	11444.000	11444.000	14.000		
Total	899	1719521.000				

Table C.2. ANOVA Table for Standard Deviation of Cycle Time

Source	DF	Seq SS	Adj SS	Adj MS	F	P
Fab	1	378871.400	378871.400	378871.400	19000.000	0.000
DR	4	129897.400	129897.400	32474.400	1611.370	0.000
RS	2	14065.600	14065.600	7032.800	348.970	0.000
RL	2	72535.800	72535.800	36267.900	1799.610	0.000
Fab*DR	4	1562.500	1562.500	390.600	19.380	0.000
Fab*RS	2	2197.900	2197.900	1099.000	54.530	0.000
Fab*RL	2	143.900	143.900	71.900	3.570	0.029
DR*RS	8	10520.700	10520.700	1315.100	65.250	0.000
DR*RL	8	29621.400	29621.400	3702.700	183.730	0.000
RS*RL	4	8603.400	8603.400	2150.800	106.720	0.000
Fab*DR*RS	8	1391.900	1391.900	174.000	8.630	0.000
Fab*DR*RL	8	1207.600	1207.600	150.900	7.490	0.000
Fab*RS*RL	4	984.800	984.800	246.200	12.220	0.000
DR*RS*RL	16	10551.000	10551.000	659.400	32.720	0.000
Fab*DR*RS*RL	16	661.300	661.300	41.300	2.050	0.009
Error	810	16324.100	16324.100	20.200		
Total	899	679140.700				

Table C.3. ANOVA Table for Percent On Time

Source	DF	Seq SS	Adj SS	Adj MS	F	P
Fab	1	2194.000	2194.000	2194.000	181.800	0.000
DR	4	227271.700	227271.700	56817.900	4707.980	0.000
RS	2	39740.800	39740.800	19870.400	1646.480	0.000
RL	2	67319.000	67319.000	33659.500	2789.050	0.000
Fab*DR	4	3109.400	3109.400	777.300	64.410	0.000
Fab*RS	2	479.000	479.000	239.500	19.840	0.000
Fab*RL	2	541.200	541.200	270.600	22.420	0.000
DR*RS	8	22308.500	22308.500	2788.600	231.060	0.000
DR*RL	8	155159.700	155159.700	19395.000	1607.080	0.000
RS*RL	4	14271.800	14271.800	3567.900	295.640	0.000
Fab*DR*RS	8	2210.400	2210.400	276.300	22.890	0.000
Fab*DR*RL	8	663.000	663.000	82.900	6.870	0.000
Fab*RS*RL	4	355.800	355.800	89.000	7.370	0.000
DR*RS*RL	16	44775.000	44775.000	2798.400	231.880	0.000
Fab*DR*RS*RL	16	1671.500	1671.500	104.500	8.660	0.000
Error	810	9775.400	9775.400	12.100		
Total	899	591846.300				

Table C.4. ANOVA Table for Percent Idle

Source	DF	Seq SS	Adj SS	Adj MS	F	P
Fab	1	35882.710	35882.710	35882.710	60000000.000	0.000
DR	4	4.940	4.940	1.240	2064.310	0.000
RS	2	165.910	165.910	82.950	140000.000	0.000
RL	2	656.600	656.600	328.300	550000.000	0.000
Fab*DR	4	0.260	0.260	0.070	108.790	0.000
Fab*RS	2	7.510	7.510	3.750	6271.650	0.000
Fab*RL	2	22.740	22.740	11.370	19000.000	0.000
DR*RS	8	0.610	0.610	0.080	127.680	0.000
DR*RL	8	0.710	0.710	0.090	148.390	0.000
RS*RL	4	33.600	33.600	8.400	14000.000	0.000
Fab*DR*RS	8	0.050	0.050	0.010	10.960	0.000
Fab*DR*RL	8	0.050	0.050	0.010	10.060	0.000
Fab*RS*RL	4	1.380	1.380	0.350	577.780	0.000
DR*RS*RL	16	0.280	0.280	0.020	29.470	0.000
Fab*DR*RS*RL	16	0.030	0.030	0.000	3.550	0.000
Error	810	0.480	0.480	0.000		
Total	899	36777.880				

Table C.5. ANOVA Table for Average WIP

Source	DF	Seq SS	Adj SS	Adj MS	F	P
Fab	1	861845.000	861845.000	861845.000	310000.000	0.000
DR	4	45900.000	45900.000	11475.000	4114.450	0.000
RS	2	15848.000	15848.000	7924.000	2841.300	0.000
RL	2	95928.000	95928.000	47964.000	17000.000	0.000
Fab*DR	4	3159.000	3159.000	790.000	283.210	0.000
Fab*RS	2	1044.000	1044.000	522.000	187.130	0.000
Fab*RL	2	1039.000	1039.000	520.000	186.290	0.000
DR*RS	8	15306.000	15306.000	1913.000	686.010	0.000
DR*RL	8	24645.000	24645.000	3081.000	1104.600	0.000
RS*RL	4	9328.000	9328.000	2332.000	836.130	0.000
Fab*DR*RS	8	1046.000	1046.000	131.000	46.860	0.000
Fab*DR*RL	8	836.000	836.000	105.000	37.470	0.000
Fab*RS*RL	4	486.000	486.000	122.000	43.590	0.000
DR*RS*RL	16	6808.000	6808.000	425.000	152.560	0.000
Fab*DR*RS*RL	16	1139.000	1139.000	71.000	25.530	0.000
Error	810	2259.000	2259.000	3.000		
Total	899	1086616.000				

Table C.6. ANOVA Table for Average XT

Source	DF	Seq SS	Adj SS	Adj MS	F	P
Fab	1	0.130	0.130	0.130	557.490	0.000
DR	4	3.828	3.828	0.957	4116.500	0.000
RS	2	1.130	1.130	0.565	2430.290	0.000
RL	2	8.873	8.873	4.436	19000.000	0.000
Fab*DR	4	0.015	0.015	0.004	15.660	0.000
Fab*RS	2	0.006	0.006	0.003	12.080	0.000
Fab*RL	2	0.108	0.108	0.054	232.750	0.000
DR*RS	8	1.294	1.294	0.162	695.750	0.000
DR*RL	8	2.136	2.136	0.267	1148.790	0.000
RS*RL	4	0.727	0.727	0.182	781.340	0.000
Fab*DR*RS	8	0.014	0.014	0.002	7.740	0.000
Fab*DR*RL	8	0.031	0.031	0.004	16.470	0.000
Fab*RS*RL	4	0.019	0.019	0.005	20.040	0.000
DR*RS*RL	16	0.586	0.586	0.037	157.440	0.000
Fab*DR*RS*RL	16	0.076	0.076	0.005	20.450	0.000
Error	810	0.188	0.188	0.000		
Total	899	19.159				

Appendix D. MTO Three Factor ANOVA Tables

This appendix contains the ANOVA results from the make-to-order fab. These tests used the dispatching rule, rework strategy, and rework level as the factors.

Table D.1. ANOVA Table of Average Cycle Time

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	116321.000	116321.000	29080.000	2272.350	0.000
RS	2	39885.000	39885.000	19942.000	1558.320	0.000
RL	2	187088.000	187088.000	93544.000	7309.600	0.000
DR*RS	8	38317.000	38317.000	4790.000	374.260	0.000
DR*RL	8	52895.000	52895.000	6612.000	516.660	0.000
RS*RL	4	21219.000	21219.000	5305.000	414.510	0.000
DR*RS*RL	16	17308.000	17308.000	1082.000	84.530	0.000
Error	405	5183.000	5183.000	13.000		
Total	449	478215.000				

Table D.2. ANOVA Table of Standard Deviation of Cycle Time

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	76724.400	76724.400	19181.100	818.620	0.000
RS	2	13362.500	13362.500	6681.200	285.150	0.000
RL	2	37693.000	37693.000	18846.500	804.340	0.000
DR*RS	8	8165.600	8165.600	1020.700	43.560	0.000
DR*RL	8	12607.500	12607.500	1575.900	67.260	0.000
RS*RL	4	7496.500	7496.500	1874.100	79.990	0.000
DR*RS*RL	16	7074.500	7074.500	442.200	18.870	0.000
Error	405	9489.500	9489.500	23.400		
Total	449	172613.500				

Table D.3. ANOVA Table of Percentage On Time

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	132043.000	132043.000	33010.700	3412.670	0.000
RS	2	20660.000	20660.000	10330.000	1067.920	0.000
RL	2	39955.300	39955.300	19977.700	2065.300	0.000
DR*RS	8	11332.900	11332.900	1416.600	146.450	0.000
DR*RL	8	83048.200	83048.200	10381.000	1073.200	0.000
RS*RL	4	7971.100	7971.100	1992.800	206.020	0.000
DR*RS*RL	16	27972.700	27972.700	1748.300	180.740	0.000
Error	405	3917.600	3917.600	9.700		
Total	449	326900.800				

Table D.4. ANOVA Table of Percent Idle

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	3.715	3.715	0.929	1240.680	0.000
RS	2	121.942	121.942	60.971	81000.000	0.000
RL	2	461.849	461.849	230.925	310000.000	0.000
DR*RS	8	0.497	0.497	0.062	82.900	0.000
DR*RL	8	0.555	0.555	0.069	92.600	0.000
RS*RL	4	24.286	24.286	6.072	8110.150	0.000
DR*RS*RL	16	0.241	0.241	0.015	20.130	0.000
Error	405	0.303	0.303	0.001		
Total	449	613.388				

Table D.5. ANOVA Table of Average WIP

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	36013.700	36013.700	9003.400	2355.480	0.000
RS	2	12351.500	12351.500	6175.800	1615.710	0.000
RL	2	57908.500	57908.500	28954.300	7575.030	0.000
DR*RS	8	11859.900	11859.900	1482.500	387.850	0.000
DR*RL	8	16370.300	16370.300	2046.300	535.350	0.000
RS*RL	4	6573.800	6573.800	1643.500	429.960	0.000
DR*RS*RL	16	5359.200	5359.200	335.000	87.630	0.000
Error	405	1548.000	1548.000	3.800		
Total	449	147985.100				

Table D.6. ANOVA Table of Average XT

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	2.120	2.120	0.530	2440.960	0.000
RS	2	0.592	0.592	0.296	1362.720	0.000
RL	2	3.562	3.562	1.781	8203.140	0.000
DR*RS	8	0.698	0.698	0.087	402.040	0.000
DR*RL	8	0.960	0.960	0.120	552.880	0.000
RS*RL	4	0.333	0.333	0.083	383.790	0.000
DR*RS*RL	16	0.310	0.310	0.019	89.320	0.000
Error	405	0.088	0.088	0.000		
Total	449	8.665				

Appendix E. MTO Two Factor ANOVA and Tukey Pairwise Comparison Results

This Appendix shows the ANOVA and Tukey pairwise comparison tables for each of the performance measures at each rework level in the MTO fab. The ANOVA tests determine whether dispatching rules and rework strategies are significant independently, and also whether their interaction is significant. The pairwise comparisons are done for the dispatching rule and rework strategy independently and also for a combination of the two. These tests are done at a 95 percent confidence level. The vertical lines on the charts refer to rules or strategies that are statistically the same as the others that are connected by the same vertical line.

Table E.1. ANOVA and Tukey Tests for Average Cycle Time at One Percent Rework

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	11127.730	11127.730	2781.930	2093.760	0.000
RS	2	157.390	157.390	78.690	59.230	0.000
DR*RS	8	103.810	103.810	12.980	9.770	0.000
Error	135	179.370	179.370	1.330		
Total	149	11568.310				

DR	RS	Avg. CT	Significance
RWK	FBN	325.562	
FIFO	FBN	325.649	
FIFO	RV	326.826	
RWK	RV	326.838	
RWK	WAIT	327.826	
FIFO	WAIT	328.115	
CR	FBN	330.179	
CR	WAIT	331.295	
CR	RV	335.318	
EDD	FBN	335.957	
EDD	WAIT	337.769	
EDD	RV	338.190	
SPT	FBN	348.611	
SPT	RV	350.300	
SPT	WAIT	351.029	

DR	Avg. CT	Sig.
RWK	326.742	
FIFO	326.863	
CR	332.264	
EDD	337.305	
SPT	349.980	

RS	Avg. CT	Sig.
FBN	333.192	
WAIT	335.207	
RV	335.494	

Table E.2. ANOVA and Tukey Tests for St. Dev of Cycle Time at One Percent Rework

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	18135.400	18135.400	4533.800	7681.480	0.000
RS	2	48.000	48.000	24.000	40.700	0.000
DR*RS	8	22.700	22.700	2.800	4.810	0.000
Error	135	79.700	79.700	0.600		
Total	149	18285.800				

DR	RS	St. Dev. CT	Significance
CR	WAIT	77.783	
CR	FBN	77.849	
RWK	FBN	79.581	
RWK	WAIT	79.585	
FIFO	FBN	79.604	
FIFO	WAIT	79.648	
FIFO	RV	79.872	
RWK	RV	79.916	
CR	RV	80.189	
SPT	WAIT	99.727	
SPT	FBN	99.858	
SPT	RV	101.097	
EDD	WAIT	102.388	
EDD	FBN	102.751	
EDD	RV	104.301	

DR	St. Dev. CT	Sig.
CR	78.607	
RWK	79.694	
FIFO	79.708	
SPT	100.227	
EDD	103.147	

RS	St. Dev. CT	Sig.
WAIT	87.826	
FBN	87.929	
RV	89.075	

Table E.3. ANOVA and Tukey Tests for Percentage On Time at One Percent Rework

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	31004.300	31004.300	7751.100	1818.840	0.000
RS	2	193.900	193.900	97.000	22.750	0.000
DR*RS	8	223.900	223.900	28.000	6.570	0.000
Error	135	575.300	575.300	4.300		
Total	149	31997.400				

DR	RS	% On Time	Significance
CR	FBN	95.555	
CR	WAIT	94.843	
RWK	FBN	94.212	
FIFO	FBN	94.138	
RWK	RV	93.124	
FIFO	RV	93.097	
RWK	WAIT	92.748	
FIFO	WAIT	92.445	
CR	RV	88.723	
EDD	FBN	74.386	
EDD	WAIT	72.959	
EDD	RV	71.171	
SPT	FBN	59.733	
SPT	RV	58.140	
SPT	WAIT	56.340	

DR	% On Time	Sig.
RWK	93.361	
FIFO	93.227	
CR	93.040	
EDD	72.839	
SPT	58.071	

RS	% On Time	Sig.
FBN	83.605	
WAIT	81.867	
RV	80.851	

Table E.4. ANOVA and Tukey Tests for Percent Idle at One Percent Rework

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	1.350	1.350	0.338	891.800	0.000
RS	2	6.826	6.826	3.413	9018.330	0.000
DR*RS	8	0.005	0.005	0.001	1.570	0.140
Error	135	0.051	0.051	0.000		
Total	149	8.232				

DR	RS	% Idle	Significance
SPT	WAIT	59.471	
EDD	WAIT	59.348	
SPT	RV	59.314	
FIFO	WAIT	59.237	
RWK	WAIT	59.233	
CR	WAIT	59.214	
EDD	RV	59.205	
CR	RV	59.093	
FIFO	RV	59.085	
RWK	RV	59.082	
SPT	FBN	58.961	
EDD	FBN	58.842	
FIFO	FBN	58.727	
RWK	FBN	58.727	
CR	FBN	58.710	

DR	% Idle	Sig.
SPT	59.249	
EDD	59.132	
FIFO	59.016	
RWK	59.014	
CR	59.006	

RS	% Idle	Sig.
WAIT	59.301	
RV	59.156	
FBN	58.793	

Table E.5. ANOVA and Tukey Tests for Average WIP at One Percent Rework

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	3448.380	3448.380	862.100	2116.530	0.000
RS	2	48.640	48.640	24.320	59.710	0.000
DR*RS	8	32.160	32.160	4.020	9.870	0.000
Error	135	54.990	54.990	0.410		
Total	149	3584.170				

DR	RS	Avg. WIP	Significance
RWK	FBN	181.111	
FIFO	FBN	181.161	
FIFO	RV	181.815	
RWK	RV	181.822	
RWK	WAIT	182.372	
FIFO	WAIT	182.533	
CR	FBN	183.682	
CR	WAIT	184.302	
CR	RV	186.542	
EDD	FBN	186.898	
EDD	WAIT	187.904	
EDD	RV	188.139	
SPT	FBN	193.947	
SPT	RV	194.883	
SPT	WAIT	195.285	

DR	Avg. WIP	Sig.
RWK	181.768	
FIFO	181.836	
CR	184.842	
EDD	187.647	
SPT	194.705	

RS	Avg. WIP	Sig.
FBN	185.360	
WAIT	186.479	
RV	186.640	

Table E.6. ANOVA and Tukey Tests for Average XT at One Percent Rework

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	0.156	0.156	0.039	1384.940	0.000
RS	2	0.002	0.002	0.001	38.080	0.000
DR*RS	8	0.002	0.002	0.000	7.990	0.000
Error	135	0.004	0.004	0.000		
Total	149	0.164				

DR	RS	Avg. XT	Significance
RWK	FBN	1.439	
FIFO	FBN	1.441	
FIFO	RV	1.443	
RWK	RV	1.443	
RWK	WAIT	1.448	
FIFO	WAIT	1.451	
EDD	FBN	1.459	
CR	FBN	1.462	
EDD	RV	1.466	
EDD	WAIT	1.467	
CR	WAIT	1.469	
CR	RV	1.483	
SPT	FBN	1.528	
SPT	RV	1.532	
SPT	WAIT	1.536	

DR	Avg. CT	Sig.
RWK	1.443	
FIFO	1.445	
EDD	1.464	
CR	1.471	
SPT	1.532	

RS	Avg. CT	Sig.
FBN	1.466	
RV	1.473	
WAIT	1.474	

Table E.7. ANOVA and Tukey Tests for Average Cycle Time at Five Percent Rework

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	34090.300	34090.300	8522.600	1883.920	0.000
RS	2	15122.500	15122.500	7561.300	1671.430	0.000
DR*RS	8	30032.500	30032.500	3754.100	829.840	0.000
Error	135	610.700	610.700	4.500		
Total	149	79856.100				

DR	RS	Avg. CT	Significance
RWK	FBN	330.597	
FIFO	FBN	330.855	
RWK	RV	335.952	
FIFO	RV	336.727	
RWK	WAIT	337.315	
FIFO	WAIT	338.507	
EDD	FBN	342.757	
CR	FBN	346.111	
CR	WAIT	346.694	
EDD	WAIT	348.918	
EDD	RV	355.188	
SPT	FBN	355.574	
SPT	WAIT	362.435	
SPT	RV	369.109	
CR	RV	426.613	

DR	Avg. CT	Sig.
RWK	334.621	
FIFO	335.363	
EDD	348.954	
SPT	362.373	
CR	373.139	

RS	Avg. CT	Sig.
FBN	341.179	
WAIT	346.774	
RV	364.718	

Table E.8. ANOVA and Tukey Tests for St. Dev. Of Cycle Time at Five Percent Rework

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	19938.400	19938.400	4984.600	2267.390	0.000
RS	2	4104.200	4104.200	2052.100	933.470	0.000
DR*RS	8	4424.600	4424.600	553.100	251.580	0.000
Error	135	296.800	296.800	2.200		
Total	149	28764.000				

DR	RS	Avg. CT	Significance
RWK	FBN	81.510	
FIFO	FBN	81.611	
RWK	WAIT	81.940	
FIFO	WAIT	82.210	
CR	WAIT	82.823	
RWK	RV	83.320	
FIFO	RV	83.462	
CR	FBN	84.411	
SPT	WAIT	102.660	
SPT	FBN	103.617	
EDD	WAIT	106.476	
EDD	FBN	106.490	
EDD	RV	114.175	
SPT	RV	115.049	
CR	RV	116.333	

DR	Avg. CT	Sig.
RWK	82.257	
FIFO	82.428	
CR	94.522	
SPT	107.109	
EDD	109.047	

RS	Avg. CT	Sig.
WAIT	91.222	
FBN	91.528	
RV	102.468	

Table E.9. ANOVA and Tukey Tests for Percentage On Time at Five Percent Rework

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	39218.300	39218.300	9804.600	2234.650	0.000
RS	2	17647.600	17647.600	8823.800	2011.110	0.000
DR*RS	8	36420.100	36420.100	4552.500	1037.610	0.000
Error	135	592.300	592.300	4.400		
Total	149	93878.300				

DR	RS	Avg. CT	Significance
RWK	FBN	96.429	
FIFO	FBN	96.384	
RWK	WAIT	93.132	
RWK	RV	92.752	
FIFO	WAIT	92.432	
FIFO	RV	92.311	
CR	FBN	89.195	
CR	WAIT	88.304	
EDD	FBN	76.889	
EDD	WAIT	71.565	
SPT	FBN	63.810	
EDD	RV	60.184	
SPT	WAIT	55.271	
SPT	RV	52.319	
CR	RV	0.682	

DR	Avg. CT	Sig.
RWK	94.104	
FIFO	93.709	
EDD	69.546	
CR	59.394	
SPT	57.133	

RS	Avg. CT	Sig.
FBN	84.541	
WAIT	80.141	
RV	59.650	

Table E.10. ANOVA and Tukey Tests for Percent Idle at Five Percent Rework

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	1.235	1.235	0.309	416.080	0.000
RS	2	49.466	49.466	24.733	33000.000	0.000
DR*RS	8	0.555	0.555	0.069	93.540	0.000
Error	135	0.100	0.100	0.001		
Total	149	51.357				

DR	RS	Avg. CT	Significance
SPT	WAIT	58.408	
EDD	WAIT	58.269	
FIFO	WAIT	58.163	
RWK	WAIT	58.161	
CR	WAIT	58.157	
CR	RV	58.102	
SPT	RV	58.008	
EDD	RV	57.905	
FIFO	RV	57.764	
RWK	RV	57.763	
SPT	FBN	57.046	
EDD	FBN	56.925	
CR	FBN	56.834	
FIFO	FBN	56.809	
RWK	FBN	56.808	

DR	Avg. CT	Sig.
SPT	57.821	
EDD	57.700	
CR	57.698	
FIFO	57.579	
RWK	57.577	

RS	Avg. CT	Sig.
WAIT	58.232	
RV	57.908	
FBN	56.884	

Table E.11. ANOVA and Tukey Tests for Average WIP at Five Percent Rework

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	10551.200	10551.200	2637.800	1876.030	0.000
RS	2	4679.700	4679.700	2339.900	1664.130	0.000
DR*RS	8	9295.600	9295.600	1162.000	826.390	0.000
Error	135	189.800	189.800	1.400		
Total	149	24716.400				

DR	RS	Avg. CT	Significance
RWK	FBN	183.914	
FIFO	FBN	184.059	
RWK	RV	186.897	
FIFO	RV	187.323	
RWK	WAIT	187.649	
FIFO	WAIT	188.314	
EDD	FBN	190.682	
CR	FBN	192.545	
CR	WAIT	192.868	
EDD	WAIT	194.109	
EDD	RV	197.596	
SPT	FBN	197.812	
SPT	WAIT	201.630	
SPT	RV	205.335	
CR	RV	237.331	

DR	Avg. CT	Sig.
RWK	186.153	
FIFO	186.565	
EDD	194.129	
SPT	201.592	
CR	207.581	

RS	Avg. CT	Sig.
FBN	189.802	
WAIT	192.914	
RV	202.896	

Table E.12. ANOVA and Tukey Tests for Average XT at Five Percent Rework

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	0.631	0.631	0.158	1742.520	0.000
RS	2	0.226	0.226	0.113	1247.810	0.000
DR*RS	8	0.543	0.543	0.068	748.720	0.000
Error	135	0.012	0.012	0.000		
Total	149	1.412				

DR	RS	Avg. CT	Significance
RWK	FBN	1.467	
FIFO	FBN	1.470	
RWK	RV	1.482	
FIFO	RV	1.488	
RWK	WAIT	1.492	
EDD	FBN	1.495	
FIFO	WAIT	1.496	
EDD	WAIT	1.515	
EDD	RV	1.534	
CR	WAIT	1.535	
CR	FBN	1.539	
SPT	FBN	1.562	
SPT	WAIT	1.587	
SPT	RV	1.608	
CR	RV	1.871	

DR	Avg. CT	Sig.
RWK	1.480	
FIFO	1.485	
EDD	1.515	
SPT	1.586	
CR	1.648	

RS	Avg. CT	Sig.
FBN	1.507	
WAIT	1.525	
RV	1.597	

Table E.13. ANOVA and Tukey Tests for Average Cycle Time at Ten Percent Rework

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	123998.000	123998.000	30999.000	952.670	0.000
RS	2	45824.000	45824.000	22912.000	704.120	0.000
DR*RS	8	25488.000	25488.000	3186.000	97.910	0.000
Error	135	4393.000	4393.000	33.000		
Total	149	199702.000				

DR	RS	Avg. CT	Significance
RWK	FBN	344.247	
FIFO	FBN	347.660	
RWK	WAIT	353.473	
FIFO	WAIT	359.451	
RWK	RV	362.930	
EDD	FBN	363.743	
FIFO	RV	370.150	
EDD	WAIT	372.282	
SPT	FBN	380.429	
SPT	WAIT	386.310	
EDD	RV	391.888	
CR	WAIT	400.353	
CR	FBN	406.223	
SPT	RV	424.999	
CR	RV	490.730	

DR	Avg. CT	Sig.
RWK	353.550	
FIFO	359.087	
EDD	375.971	
SPT	397.246	
CR	432.435	

RS	Avg. CT	Sig.
FBN	368.461	
WAIT	374.374	
RV	408.139	

Table E.14. ANOVA and Tukey Tests for Std. Dev. Of Cycle Time at Ten Percent Rework

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	51258.100	51258.100	12814.500	189.830	0.000
RS	2	16706.700	16706.700	8353.300	123.750	0.000
DR*RS	8	10792.800	10792.800	1349.100	19.990	0.000
Error	135	9113.100	9113.100	67.500		
Total	149	87870.600				

DR	RS	Avg. CT	Significance
RWK	FBN	85.607	
RWK	WAIT	86.234	
FIFO	FBN	86.497	
FIFO	WAIT	87.855	
RWK	RV	92.183	
FIFO	RV	94.197	
CR	WAIT	104.217	
CR	FBN	106.532	
EDD	FBN	116.604	
SPT	WAIT	117.146	
SPT	FBN	118.121	
EDD	WAIT	118.321	
EDD	RV	130.013	
CR	RV	139.387	
SPT	RV	169.724	

DR	Avg. CT	Sig.
RWK	88.008	
FIFO	89.516	
CR	116.712	
EDD	121.646	
SPT	134.997	

RS	Avg. CT	Sig.
FBN	102.672	
WAIT	102.755	
RV	125.101	

Table E.15. ANOVA and Tukey Tests for Percentage On Time at Ten Percent Rework

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	144869.000	144869.000	36217.000	1777.970	0.000
RS	2	10790.000	10790.000	5395.000	264.840	0.000
DR*RS	8	2662.000	2662.000	333.000	16.330	0.000
Error	135	2750.000	2750.000	20.000		
Total	149	161070.000				

DR	RS	Avg. CT	Significance
RWK	FBN	98.010	
FIFO	FBN	97.061	
RWK	WAIT	95.356	
FIFO	WAIT	91.088	
RWK	RV	82.409	
EDD	FBN	73.857	
FIFO	RV	73.184	
EDD	WAIT	65.237	
SPT	FBN	61.901	
SPT	WAIT	57.386	
SPT	RV	43.592	
EDD	RV	38.735	
CR	WAIT	9.764	
CR	FBN	4.440	
CR	RV	0.307	

DR	Avg. CT	Sig.
RWK	91.925	
FIFO	87.111	
EDD	59.276	
SPT	54.293	
CR	4.837	

RS	Avg. CT	Sig.
FBN	67.054	
WAIT	63.766	
RV	47.645	

Table E.16. ANOVA and Tukey Tests for Percent Idle at Ten Percent Rework

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	1.685	1.685	0.421	374.290	0.000
RS	2	89.936	89.936	44.968	40000.000	0.000
DR*RS	8	0.178	0.178	0.022	19.730	0.000
Error	135	0.152	0.152	0.001		
Total	149	91.951				

DR	RS	Avg. CT	Significance
SPT	WAIT	57.531	
EDD	WAIT	57.406	
CR	WAIT	57.403	
FIFO	WAIT	57.292	
RWK	WAIT	57.278	
CR	RV	57.077	
SPT	RV	57.013	
EDD	RV	56.910	
FIFO	RV	56.747	
RWK	RV	56.732	
SPT	FBN	55.686	
CR	FBN	55.625	
EDD	FBN	55.564	
FIFO	FBN	55.448	
RWK	FBN	55.433	

DR	Avg. CT	Sig.
SPT	56.743	
CR	56.702	
EDD	56.627	
FIFO	56.496	
RWK	56.481	

RS	Avg. CT	Sig.
WAIT	57.382	
RV	56.896	
FBN	55.551	

Table E.17. ANOVA and Tukey Tests for Average WIP at Ten Percent Rework

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	38384.500	38384.500	9596.100	994.040	0.000
RS	2	14197.000	14197.000	7098.500	735.320	0.000
DR*RS	8	7891.400	7891.400	986.400	102.180	0.000
Error	135	1303.200	1303.200	9.700		
Total	149	61776.100				

DR	RS	Avg. CT	Significance
RWK	FBN	191.506	
FIFO	FBN	193.406	
RWK	WAIT	196.639	
FIFO	WAIT	199.962	
RWK	RV	201.900	
EDD	FBN	202.353	
FIFO	RV	205.919	
EDD	WAIT	207.105	
SPT	FBN	211.639	
SPT	WAIT	214.912	
EDD	RV	218.016	
CR	WAIT	222.718	
CR	FBN	225.984	
SPT	RV	236.474	
CR	RV	273.003	

DR	Avg. CT	Sig.
RWK	196.682	
FIFO	199.762	
EDD	209.158	
SPT	221.008	
CR	240.568	

RS	Avg. CT	Sig.
FBN	204.978	
WAIT	208.267	
RV	227.062	

Table E.18. ANOVA and Tukey Tests for Average XT at Ten Percent Rework

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	2.293	2.293	0.573	1076.200	0.000
RS	2	0.697	0.697	0.348	654.240	0.000
DR*RS	8	0.464	0.464	0.058	108.960	0.000
Error	135	0.072	0.072	0.001		
Total	149	3.526				

DR	RS	Avg. CT	Significance
RWK	FBN	1.538	
FIFO	FBN	1.553	
RWK	WAIT	1.562	
EDD	FBN	1.588	
FIFO	WAIT	1.589	
RWK	RV	1.603	
EDD	WAIT	1.611	
FIFO	RV	1.634	
SPT	FBN	1.675	
SPT	WAIT	1.687	
EDD	RV	1.688	
CR	WAIT	1.763	
CR	FBN	1.805	
SPT	RV	1.833	
CR	RV	2.149	

DR	RS	Avg. CT	Significance
RWK	FBN	1.538	
FIFO	FBN	1.553	
RWK	WAIT	1.562	
EDD	FBN	1.588	
FIFO	WAIT	1.589	
RWK	RV	1.603	
EDD	WAIT	1.611	
FIFO	RV	1.634	
SPT	FBN	1.675	
SPT	WAIT	1.687	
EDD	RV	1.688	
CR	WAIT	1.763	
CR	FBN	1.805	
SPT	RV	1.833	
CR	RV	2.149	

Appendix F. MTS Three Factor ANOVA Tables

This appendix contains the ANOVA results from the make-to-stock fab. These tests used the dispatching rule, rework strategy, and rework level as the factors.

Table F.1. ANOVA Table of Average Cycle Time

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	115769.000	115769.000	28942.000	1872.140	0.000
RS	2	40289.000	40289.000	20145.000	1303.060	0.000
RL	2	346621.000	346621.000	173311.000	11000.000	0.000
DR*RS	8	39869.000	39869.000	4984.000	322.370	0.000
DR*RL	8	80856.000	80856.000	10107.000	653.780	0.000
RS*RL	4	28752.000	28752.000	7188.000	464.960	0.000
DR*RS*RL	16	22965.000	22965.000	1435.000	92.850	0.000
Error	405	6261.000	6261.000	15.000		
Total	449	681383.000				

Table F.2. ANOVA Table of Standard Deviation of Cycle Time

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	54735.500	54735.500	13683.900	810.870	0.000
RS	2	2901.100	2901.100	1450.500	85.950	0.000
RL	2	34986.700	34986.700	17493.400	1036.610	0.000
DR*RS	8	3746.900	3746.900	468.400	27.750	0.000
DR*RL	8	18221.500	18221.500	2277.700	134.970	0.000
RS*RL	4	2091.600	2091.600	522.900	30.990	0.000
DR*RS*RL	16	4137.800	4137.800	258.600	15.320	0.000
Error	405	6834.600	6834.600	16.900		
Total	449	127655.700				

Table F.3. ANOVA Table of Percentage On Time

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	98338.100	98338.100	24584.500	1699.720	0.000
RS	2	19559.900	19559.900	9779.900	676.160	0.000
RL	2	27904.900	27904.900	13952.500	964.640	0.000
DR*RS	8	13186.000	13186.000	1648.300	113.960	0.000
DR*RL	8	72774.500	72774.500	9096.800	628.930	0.000
RS*RL	4	6656.500	6656.500	1664.100	115.050	0.000
DR*RS*RL	16	18473.700	18473.700	1154.600	79.830	0.000
Error	405	5857.900	5857.900	14.500		
Total	449	262751.500				

Table F.4. ANOVA Table of Percent Idle

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	1.487	1.487	0.372	829.210	0.000
RS	2	51.472	51.472	25.736	57000.000	0.000
RL	2	217.486	217.486	108.743	240000.000	0.000
DR*RS	8	0.167	0.167	0.021	46.650	0.000
DR*RL	8	0.204	0.204	0.026	56.900	0.000
RS*RL	4	10.701	10.701	2.675	5966.110	0.000
DR*RS*RL	16	0.075	0.075	0.005	10.470	0.000
Error	405	0.182	0.182	0.000		
Total	449	281.775				

Table F.5. ANOVA Table of Average WIP

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	13045.500	13045.500	3261.400	1857.750	0.000
RS	2	4540.700	4540.700	2270.300	1293.240	0.000
RL	2	39058.500	39058.500	19529.300	11000.000	0.000
DR*RS	8	4491.600	4491.600	561.500	319.820	0.000
DR*RL	8	9111.100	9111.100	1138.900	648.740	0.000
RS*RL	4	3240.100	3240.100	810.000	461.400	0.000
DR*RS*RL	16	2587.600	2587.600	161.700	92.120	0.000
Error	405	711.000	711.000	1.800		
Total	449	76786.000				

Table F.6. ANOVA Table of Average XT

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	1.722	1.722	0.431	1737.590	0.000
RS	2	0.544	0.544	0.272	1097.170	0.000
RL	2	5.419	5.419	2.709	11000.000	0.000
DR*RS	8	0.610	0.610	0.076	307.690	0.000
DR*RL	8	1.207	1.207	0.151	608.700	0.000
RS*RL	4	0.412	0.412	0.103	415.510	0.000
DR*RS*RL	16	0.351	0.351	0.022	88.630	0.000
Error	405	0.100	0.100	0.000		
Total	449	10.365				

Appendix G. MTS Two Factor ANOVA and Tukey Pairwise Comparison Results

This Appendix shows the ANOVA and Tukey pairwise comparison tables for each of the performance measures at each rework level in the MTS fab. The ANOVA tests determine whether dispatching rules and rework strategies are significant independently, and also whether their interaction is significant. The pairwise comparisons are done for the dispatching rule and rework strategy independently and also for a combination of the two. These tests are done at a 95 percent confidence level. The vertical lines on the charts refer to rules or strategies that are statistically the same as the others that are connected by the same vertical line.

Table G.1. ANOVA and Tukey Tests for Average Cycle Time at One Percent Rework

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	8142.890	8142.890	2035.720	645.140	0.000
RS	2	234.730	234.730	117.370	37.190	0.000
DR*RS	8	124.260	124.260	15.530	4.920	0.000
Error	135	425.990	425.990	3.160		
Total	149	8927.870				

DR	RS	Avg. CT	Significance
RWK	FBN	370.492	
FIFO	FBN	370.643	
RWK	RV	372.163	
FIFO	RV	372.343	
RWK	WAIT	373.130	
FIFO	WAIT	373.343	
CR	FBN	374.391	
CR	WAIT	376.293	
EDD	FBN	377.904	
EDD	RV	379.456	
CR	RV	380.535	
EDD	WAIT	380.738	
SPT	FBN	390.341	
SPT	WAIT	392.634	
SPT	RV	393.287	

DR	Avg. CT	Sig.
RWK	371.928	
FIFO	372.109	
CR	377.073	
EDD	379.366	
SPT	392.087	

RS	Avg. CT	Sig.
FBN	376.754	
WAIT	379.227	
RV	379.557	

Table G.2. ANOVA and Tukey Tests for St. Dev of Cycle Time at One Percent Rework

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	9172.240	9172.240	2293.060	572.210	0.000
RS	2	19.380	19.380	9.690	2.420	0.093
DR*RS	8	24.510	24.510	3.060	0.760	0.635
Error	135	541.000	541.000	4.010		
Total	149	9757.120				

DR	RS	Avg. CT	Significance
RWK	FBN	41.046	
FIFO	FBN	41.137	
FIFO	RV	41.251	
RWK	RV	41.285	
FIFO	WAIT	41.612	
RWK	WAIT	41.752	
CR	FBN	42.603	
CR	WAIT	43.564	
CR	RV	43.956	
SPT	FBN	55.066	
SPT	WAIT	55.118	
SPT	RV	57.149	
EDD	FBN	59.273	
EDD	RV	59.830	
EDD	WAIT	59.859	

DR	Avg. CT	Sig.
FIFO	41.333	
RWK	41.361	
CR	43.374	
SPT	55.778	
EDD	59.654	

RS	Avg. CT	Sig.
FBN	47.825	
WAIT	48.381	
RV	48.694	

Table G.3. ANOVA and Tukey Tests for Percentage On Time at One Percent Rework

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	22174.100	22174.100	5543.500	949.730	0.000
RS	2	224.000	224.000	112.000	19.190	0.000
DR*RS	8	230.100	230.100	28.800	4.930	0.000
Error	135	788.000	788.000	5.800		
Total	149	23416.100				

DR	RS	Avg. CT	Significance
CR	FBN	96.261	
CR	WAIT	95.313	
FIFO	FBN	93.243	
RWK	FBN	93.180	
RWK	RV	92.343	
FIFO	RV	91.977	
RWK	WAIT	91.825	
FIFO	WAIT	91.686	
CR	RV	88.925	
EDD	FBN	79.199	
EDD	RV	77.561	
EDD	WAIT	76.617	
SPT	FBN	64.572	
SPT	WAIT	61.453	
SPT	RV	60.896	

DR	Avg. CT	Sig.
CR	93.500	
RWK	92.449	
FIFO	92.302	
EDD	77.792	
SPT	62.307	

RS	Avg. CT	Sig.
FBN	85.291	
WAIT	83.379	
RV	82.340	

Table G.4. ANOVA and Tukey Tests for Percent Idle at One Percent Rework

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	0.519	0.519	0.130	550.070	0.000
RS	2	2.703	2.703	1.352	5725.840	0.000
DR*RS	8	0.001	0.001	0.000	0.470	0.878
Error	135	0.032	0.032	0.000		
Total	149	3.256				

DR	RS	Avg. CT	Significance
SPT	WAIT	71.549	
EDD	WAIT	71.474	
SPT	RV	71.450	
FIFO	WAIT	71.406	
RWK	WAIT	71.406	
CR	WAIT	71.388	
EDD	RV	71.378	
RWK	RV	71.310	
FIFO	RV	71.309	
CR	RV	71.304	
SPT	FBN	71.230	
EDD	FBN	71.152	
RWK	FBN	71.087	
FIFO	FBN	71.084	
CR	FBN	71.070	

DR	Avg. CT	Sig.
SPT	71.410	
EDD	71.335	
RWK	71.268	
FIFO	71.266	
CR	71.254	

RS	Avg. CT	Sig.
WAIT	71.445	
RV	71.350	
FBN	71.125	

Table G.5. ANOVA and Tukey Tests for Average WIP at One Percent Rework

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	917.474	917.474	229.369	648.850	0.000
RS	2	26.480	26.480	13.240	37.450	0.000
DR*RS	8	13.991	13.991	1.749	4.950	0.000
Error	135	47.723	47.723	0.354		
Total	149	1005.668				

DR	RS	Avg. CT	Significance
RWK	FBN	124.363	
FIFO	FBN	124.413	
RWK	RV	124.925	
FIFO	RV	124.984	
RWK	WAIT	125.248	
FIFO	WAIT	125.321	
CR	FBN	125.672	
CR	WAIT	126.311	
EDD	FBN	126.851	
EDD	RV	127.374	
CR	RV	127.735	
EDD	WAIT	127.803	
SPT	FBN	131.026	
SPT	WAIT	131.795	
SPT	RV	132.015	

DR	Avg. CT	Sig.
RWK	124.845	
FIFO	124.906	
CR	126.573	
EDD	127.343	
SPT	131.612	

RS	Avg. CT	Sig.
FBN	126.465	
WAIT	127.296	
RV	127.407	

Table G.6. ANOVA and Tukey Tests for Average XT at One Percent Rework

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	0.117	0.117	0.029	502.830	0.000
RS	2	0.003	0.003	0.001	25.430	0.000
DR*RS	8	0.002	0.002	0.000	4.380	0.000
Error	135	0.008	0.008	0.000		
Total	149	0.129				

DR	RS	Avg. CT	Significance
FIFO	FBN	1.452	
RWK	FBN	1.453	
RWK	RV	1.456	
FIFO	RV	1.458	
RWK	WAIT	1.462	
FIFO	WAIT	1.463	
CR	FBN	1.466	
EDD	FBN	1.472	
CR	WAIT	1.474	
EDD	RV	1.478	
EDD	WAIT	1.484	
CR	RV	1.489	
SPT	FBN	1.528	
SPT	WAIT	1.534	
SPT	RV	1.538	

DR	Avg. CT	Sig.
RWK	1.457	
FIFO	1.458	
CR	1.476	
EDD	1.478	
SPT	1.533	

RS	Avg. CT	Sig.
FBN	1.474	
WAIT	1.483	
RV	1.484	

Table G.7. ANOVA and Tukey Tests for Average Cycle Time at Five Percent Rework

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	23109.300	23109.300	5777.300	482.200	0.000
RS	2	8455.000	8455.000	4227.500	352.840	0.000
DR*RS	8	12254.900	12254.900	1531.900	127.850	0.000
Error	135	1617.500	1617.500	12.000		
Total	149	45436.600				

DR	RS	Avg. CT	Significance
RWK	FBN	377.231	
FIFO	FBN	378.508	
RWK	RV	384.084	
RWK	WAIT	385.701	
FIFO	RV	386.135	
FIFO	WAIT	388.310	
EDD	FBN	388.579	
CR	FBN	391.105	
EDD	RV	394.714	
EDD	WAIT	396.653	
SPT	FBN	399.224	
CR	WAIT	402.668	
SPT	WAIT	407.465	
SPT	RV	413.148	
CR	RV	448.519	

DR	Avg. CT	Sig.
RWK	382.339	
FIFO	384.318	
EDD	393.315	
SPT	406.612	
CR	414.097	

RS	Avg. CT	Sig.
FBN	386.929	
WAIT	396.159	
RV	405.320	

Table G.8. ANOVA and Tukey Tests for St. Dev. Of Cycle Time at Five Percent Rework

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	11525.160	11525.160	2881.290	586.440	0.000
RS	2	602.040	602.040	301.020	61.270	0.000
DR*RS	8	634.020	634.020	79.250	16.130	0.000
Error	135	663.280	663.280	4.910		
Total	149	13424.500				

DR	RS	Avg. CT	Significance
RWK	FBN	42.150	
FIFO	FBN	42.252	
RWK	RV	43.034	
FIFO	RV	43.253	
RWK	WAIT	44.156	
FIFO	WAIT	44.780	
CR	FBN	47.580	
CR	WAIT	53.111	
SPT	FBN	58.308	
SPT	WAIT	60.017	
CR	RV	60.566	
EDD	FBN	62.916	
EDD	WAIT	64.468	
EDD	RV	65.039	
SPT	RV	65.820	

DR	Avg. CT	Sig.
RWK	43.113	
FIFO	43.429	
CR	53.752	
SPT	61.381	
EDD	64.141	

RS	Avg. CT	Sig.
FBN	50.641	
WAIT	53.306	
RV	55.542	

Table G.9. ANOVA and Tukey Tests for Percentage On Time at Five Percent Rework

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	31923.500	31923.500	7980.900	844.110	0.000
RS	2	13679.000	13679.000	6839.500	723.390	0.000
DR*RS	8	30154.200	30154.200	3769.300	398.660	0.000
Error	135	1276.400	1276.400	9.500		
Total	149	77033.100				

DR	RS	Avg. CT	Significance
RWK	FBN	96.415	
FIFO	FBN	95.918	
CR	FBN	94.283	
RWK	WAIT	93.069	
RWK	RV	92.949	
FIFO	RV	91.693	
FIFO	WAIT	91.244	
EDD	FBN	81.958	
EDD	RV	75.779	
CR	WAIT	75.316	
EDD	WAIT	74.585	
SPT	FBN	71.268	
SPT	WAIT	62.059	
SPT	RV	56.711	
CR	RV	6.928	

DR	Avg. CT	Sig.
RWK	94.144	
FIFO	92.952	
EDD	77.441	
SPT	63.346	
CR	58.842	

RS	Avg. CT	Sig.
FBN	87.968	
WAIT	79.255	
RV	64.812	

Table G.10. ANOVA and Tukey Tests for Percent Idle at Five Percent Rework

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	0.460	0.460	0.115	242.770	0.000
RS	2	20.953	20.953	10.477	22000.000	0.000
DR*RS	8	0.162	0.162	0.020	42.580	0.000
Error	135	0.064	0.064	0.001		
Total	149	21.639				

DR	RS	Avg. CT	Significance
SPT	WAIT	70.815	
EDD	WAIT	70.733	
FIFO	WAIT	70.672	
RWK	WAIT	70.668	
CR	WAIT	70.661	
CR	RV	70.567	
SPT	RV	70.551	
EDD	RV	70.471	
FIFO	RV	70.397	
RWK	RV	70.395	
SPT	FBN	69.933	
EDD	FBN	69.855	
FIFO	FBN	69.784	
RWK	FBN	69.781	
CR	FBN	69.779	

DR	Avg. CT	Sig.
SPT	70.433	
EDD	70.353	
CR	70.336	
FIFO	70.284	
RWK	70.281	

RS	Avg. CT	Sig.
WAIT	70.710	
RV	70.476	
FBN	69.826	

Table G.11. ANOVA and Tukey Tests for Average WIP at Five Percent Rework

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	2604.180	2604.180	651.050	485.080	0.000
RS	2	952.780	952.780	476.390	354.950	0.000
DR*RS	8	1380.360	1380.360	172.540	128.560	0.000
Error	135	181.190	181.190	1.340		
Total	149	5118.510				

DR	RS	Avg. CT	Significance
RWK	FBN	126.625	
FIFO	FBN	127.053	
RWK	RV	128.926	
RWK	WAIT	129.470	
FIFO	RV	129.615	
FIFO	WAIT	130.344	
EDD	FBN	130.434	
CR	FBN	131.284	
EDD	RV	132.494	
EDD	WAIT	133.144	
SPT	FBN	134.009	
CR	WAIT	135.164	
SPT	WAIT	136.774	
SPT	RV	138.684	
CR	RV	150.553	

DR	Avg. CT	Sig.
RWK	128.340	
FIFO	129.004	
EDD	132.024	
SPT	136.489	
CR	139.000	

RS	Avg. CT	Sig.
FBN	129.881	
WAIT	132.979	
RV	136.054	

Table G.12. ANOVA and Tukey Tests for Average XT at Five Percent Rework

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	0.337	0.337	0.084	421.970	0.000
RS	2	0.107	0.107	0.054	268.990	0.000
DR*RS	8	0.187	0.187	0.023	116.990	0.000
Error	135	0.027	0.027	0.000		
Total	149	0.658				

DR	RS	Avg. CT	Significance
RWK	FBN	1.483	
FIFO	FBN	1.489	
RWK	RV	1.505	
RWK	WAIT	1.510	
FIFO	RV	1.513	
EDD	FBN	1.520	
FIFO	WAIT	1.522	
CR	FBN	1.536	
EDD	RV	1.537	
EDD	WAIT	1.543	
SPT	FBN	1.567	
CR	WAIT	1.572	
SPT	WAIT	1.592	
SPT	RV	1.614	
CR	RV	1.753	

DR	Avg. CT	Sig.
RWK	1.499	
FIFO	1.508	
EDD	1.533	
SPT	1.591	
CR	1.620	

RS	Avg. CT	Sig.
FBN	1.519	
WAIT	1.548	
RV	1.584	

Table G.13. ANOVA and Tukey Tests for Average Cycle Time at Ten Percent Rework

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	165373.000	165373.000	41343.000	1323.350	0.000
RS	2	60351.000	60351.000	30176.000	965.880	0.000
DR*RS	8	50455.000	50455.000	6307.000	201.880	0.000
Error	135	4218.000	4218.000	31.000		
Total	149	280397.000				

DR	RS	Avg. CT	Significance
RWK	FBN	401.008	
FIFO	FBN	407.090	
RWK	WAIT	413.099	
EDD	FBN	421.471	
FIFO	WAIT	422.425	
RWK	RV	423.683	
EDD	WAIT	432.627	
SPT	FBN	432.665	
FIFO	RV	434.778	
SPT	WAIT	440.042	
EDD	RV	440.402	
CR	FBN	459.787	
CR	WAIT	474.159	
SPT	RV	475.829	
CR	RV	583.728	

DR	Avg. CT	Sig.
RWK	412.597	
FIFO	421.431	
EDD	431.500	
SPT	449.512	
CR	505.891	

RS	Avg. CT	Sig.
FBN	424.404	
WAIT	436.470	
RV	471.684	

Table G.14. ANOVA and Tukey Tests for Std. Dev. Of Cycle Time at Ten Percent Rework

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	52259.600	52259.600	13064.900	313.260	0.000
RS	2	4371.300	4371.300	2185.600	52.410	0.000
DR*RS	8	7226.200	7226.200	903.300	21.660	0.000
Error	135	5630.300	5630.300	41.700		
Total	149	69487.400				

DR	RS	Avg. CT	Significance
RWK	FBN	45.904	
FIFO	FBN	46.859	
RWK	WAIT	48.965	
RWK	RV	49.175	
FIFO	WAIT	51.016	
FIFO	RV	51.461	
CR	FBN	69.452	
EDD	FBN	70.816	
EDD	WAIT	73.291	
EDD	RV	74.552	
CR	WAIT	74.894	
CR	RV	82.243	
SPT	WAIT	83.523	
SPT	FBN	87.241	
SPT	RV	124.948	

DR	Avg. CT	Sig.
RWK	48.015	
FIFO	49.779	
EDD	72.886	
CR	75.530	
SPT	98.571	

RS	Avg. CT	Sig.
FBN	64.055	
WAIT	66.338	
RV	76.476	

Table G.15. ANOVA and Tukey Tests for Percentage On Time at Ten Percent Rework

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	117015.100	117015.100	29253.800	1041.070	0.000
RS	2	12313.400	12313.400	6156.700	219.100	0.000
DR*RS	8	1275.400	1275.400	159.400	5.670	0.000
Error	135	3793.500	3793.500	28.100		
Total	149	134397.400				

DR	RS	Avg. CT	Significance
RWK	FBN	97.868	
FIFO	FBN	96.280	
RWK	WAIT	94.961	
FIFO	WAIT	88.507	
RWK	RV	83.760	
EDD	FBN	80.476	
SPT	FBN	72.280	
EDD	WAIT	70.636	
FIFO	RV	68.874	
SPT	WAIT	67.166	
EDD	RV	63.173	
SPT	RV	48.732	
CR	FBN	27.707	
CR	WAIT	10.476	
CR	RV	0.000	

DR	Avg. CT	Sig.
RWK	92.196	
FIFO	84.554	
EDD	71.428	
SPT	62.726	
CR	12.728	

RS	Avg. CT	Sig.
FBN	74.922	
WAIT	66.349	
RV	52.908	

Table G.16. ANOVA and Tukey Tests for Percent Idle at Ten Percent Rework

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	0.712	0.712	0.178	280.130	0.000
RS	2	38.516	38.516	19.258	30000.000	0.000
DR*RS	8	0.080	0.080	0.010	15.760	0.000
Error	135	0.086	0.086	0.001		
Total	149	39.394				

DR	RS	Avg. CT	Significance
SPT	WAIT	70.224	
CR	WAIT	70.154	
EDD	WAIT	70.142	
FIFO	WAIT	70.067	
RWK	WAIT	70.059	
CR	RV	69.889	
SPT	RV	69.860	
EDD	RV	69.773	
FIFO	RV	69.681	
RWK	RV	69.679	
SPT	FBN	69.033	
EDD	FBN	68.941	
CR	FBN	68.931	
FIFO	FBN	68.858	
RWK	FBN	68.848	

DR	Avg. CT	Sig.
SPT	69.706	
CR	69.658	
EDD	69.619	
FIFO	69.535	
RWK	69.529	

RS	Avg. CT	Sig.
WAIT	70.129	
RV	69.776	
FBN	68.922	

Table G.17. ANOVA and Tukey Tests for Average WIP at Ten Percent Rework

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	18634.900	18634.900	4658.700	1304.600	0.000
RS	2	6801.500	6801.500	3400.700	952.320	0.000
DR*RS	8	5684.900	5684.900	710.600	198.990	0.000
Error	135	482.100	482.100	3.600		
Total	149	31603.300				

DR	RS	Avg. CT	Significance
RWK	FBN	134.607	
FIFO	FBN	136.649	
RWK	WAIT	138.666	
EDD	FBN	141.474	
FIFO	WAIT	141.796	
RWK	RV	142.220	
EDD	WAIT	145.220	
SPT	FBN	145.233	
FIFO	RV	145.944	
SPT	WAIT	147.710	
EDD	RV	147.832	
CR	FBN	154.339	
CR	WAIT	159.162	
SPT	RV	159.724	
CR	RV	195.943	

DR	Avg. CT	Sig.
RWK	138.498	
FIFO	141.463	
EDD	144.842	
SPT	150.889	
CR	169.815	

RS	Avg. CT	Sig.
FBN	142.460	
WAIT	146.511	
RV	158.333	

Table G.18. ANOVA and Tukey Tests for Average XT at Ten Percent Rework

Source	DF	Seq SS	Adj SS	Adj MS	F	P
DR	4	2.475	2.475	0.619	1274.070	0.000
RS	2	0.845	0.845	0.423	870.110	0.000
DR*RS	8	0.772	0.772	0.097	198.790	0.000
Error	135	0.066	0.066	0.000		
Total	149	4.158				

DR	RS	Avg. CT	Significance
RWK	FBN	1.585	
FIFO	FBN	1.607	
RWK	WAIT	1.617	
FIFO	WAIT	1.652	
EDD	FBN	1.654	
RWK	RV	1.662	
EDD	WAIT	1.683	
FIFO	RV	1.704	
SPT	FBN	1.704	
EDD	RV	1.717	
SPT	WAIT	1.719	
CR	FBN	1.811	
CR	WAIT	1.847	
SPT	RV	1.859	
CR	RV	2.282	

DR	Avg. CT	Sig.
RWK	1.621	
FIFO	1.654	
EDD	1.685	
SPT	1.761	
CR	1.980	

RS	Avg. CT	Sig.
FBN	1.672	
WAIT	1.704	
RV	1.845	

Appendix H. Two Factor MTO ANOVA Tables: Determination of Robust Strategies

The following tables show the ANOVA and Tukey multiple comparison test results for the tests of the six strategies found to perform well across performance measures, rework level in the MTO fab. Tukey multiple comparison tests are done for the factors that were considered significant.

Table H.1. Average Cycle Time ANOVA Table and Tukey Multiple Comparison Test

Source	DF	Seq SS	Adj SS	Adj MS	F	P	DR	Avg. CT	Sig.
DR	1	204.800	204.800	204.800	43.370	0.000	RWK	338.304	
RS	2	2685.900	2685.900	1342.900	284.340	0.000	FIFO	340.438	
DR*RS	2	17.700	17.700	8.800	1.870	0.157	RS	Avg. CT	Sig.
RL	2	27860.800	27860.800	13930.400	2949.490	0.000	FBN	334.095	
DR*RL	2	263.600	263.600	131.800	27.910	0.000	WAIT	340.781	
RS*RL	4	2179.100	2179.100	544.800	115.350	0.000	RV	343.237	
Error	166	784.000	784.000	4.700					
Total	179	33996.000							

Table H.2. Standard Deviation of Cycle Time ANOVA Table and Tukey Multiple Comparison Test

Source	DF	Seq SS	Adj SS	Adj MS	F	P	DR	Std. Dev CT	Sig.
DR	1	14.310	14.310	14.310	20.480	0.000	RWK	83.320	
RS	2	329.220	329.220	164.610	235.560	0.000	FIFO	83.884	
DR*RS	2	1.180	1.180	0.590	0.850	0.431	RS	Std. Dev CT	Sig.
RL	2	2605.730	2605.730	1302.860	1864.470	0.000	FBN	82.402	
DR*RL	2	20.250	20.250	10.120	14.490	0.000	WAIT	82.912	
RS*RL	4	305.590	305.590	76.400	109.330	0.000	RV	85.492	
Error	166	116.000	116.000	0.700					
Total	179	3392.280							

Table H.3. Percentage On Time ANOVA Table and Tukey Multiple Comparison Test

Source	DF	Seq SS	Adj SS	Adj MS	F	P	DR	% On Time	Sig.
DR	1	142.790	142.790	142.790	9.810	0.002	RWK	93.130	
RS	2	2065.510	2065.510	1032.750	70.950	0.000	FIFO	91.349	
DR*RS	2	62.010	62.010	31.000	2.130	0.122	RS	% On Time	Sig.
RL	2	677.880	677.880	338.940	23.290	0.000	FBN	96.039	
DR*RL	2	207.440	207.440	103.720	7.130	0.001	WAIT	92.867	
RS*RL	4	2456.390	2456.390	614.100	42.190	0.000	RV	87.813	
Error	166	2416.170	2416.170	14.560					
Total	179	8028.190							

Table H.4. Average WIP ANOVA Table and Tukey Multiple Comparison Test

Source	DF	Seq SS	Adj SS	Adj MS	F	P	DR	Avg. WIP	Sig.
DR	1	63.390	63.390	63.390	43.570	0.000	RWK	188.201	
RS	2	831.440	831.440	415.720	285.700	0.000	FIFO	189.388	
DR*RS	2	5.440	5.440	2.720	1.870	0.157	RS	Avg. WIP	Sig.
RL	2	8621.890	8621.890	4310.950	2962.670	0.000	FBN	185.860	
DR*RL	2	81.580	81.580	40.790	28.030	0.000	WAIT	189.578	
RS*RL	4	674.420	674.420	168.600	115.870	0.000	RV	190.946	
Error	166	241.540	241.540	1.460					
Total	179	10519.710							

Table H.5. Average XT ANOVA Table and Tukey Multiple Comparison Test

Source	DF	Seq SS	Adj SS	Adj MS	F	P	DR	Avg. XT	Sig.
DR	1	0.005	0.005	0.005	48.590	0.000	RWK	1.497	
RS	2	0.030	0.030	0.015	158.880	0.000	FIFO	1.507	
DR*RS	2	0.000	0.000	0.000	1.450	0.238	RS	Avg. XT	Sig.
RL	2	0.587	0.587	0.293	3100.040	0.000	FBN	1.485	
DR*RL	2	0.005	0.005	0.002	24.320	0.000	WAIT	1.506	
RS*RL	4	0.031	0.031	0.008	82.930	0.000	RV	1.516	
Error	166	0.016	0.016	0.000					
Total	179	0.674							

Appendix I. Two Factor MTS ANOVA Tables: Determination of Robust Strategies

The following tables show the ANOVA and Tukey multiple comparison test results for the tests of the six strategies found to perform well across performance measures, rework level in the MTS fab. Tukey multiple comparison tests are done for the factors that were considered significant.

Table I.1. Average Cycle Time ANOVA Table and Tukey Multiple Comparison Test

Source	DF	Seq SS	Adj SS	Adj MS	F	P	DR	Avg. CT	Sig.
DR	1	604.500	604.500	604.500	52.590	0.000	RWK	388.955	
RS	2	4196.700	4196.700	2098.400	182.560	0.000	FIFO	392.620	
DR*RS	2	31.500	31.500	15.700	1.370	0.257	RS	Avg. CT	Sig.
RL	2	65743.900	65743.900	32871.900	2859.890	0.000	FBN	384.162	
DR*RL	2	625.400	625.400	312.700	27.200	0.000	WAIT	392.668	
RS*RL	4	3164.900	3164.900	791.200	68.840	0.000	RV	395.531	
Error	166	1908.000	1908.000	11.500					
Total	179	76274.800							

Table I.2. Standard Deviation of Cycle Time ANOVA Table and Tukey Multiple Comparison Test

Source	DF	Seq SS	Adj SS	Adj MS	F	P	DR	Std. Dev CT	Sig.
DR	1	21.060	21.060	21.060	15.060	0.000	RWK	44.163	
RS	2	154.150	154.150	77.080	55.130	0.000	FIFO	44.847	
DR*RS	2	2.030	2.030	1.010	0.720	0.486	RS	Std. Dev CT	Sig.
RL	2	1846.830	1846.830	923.420	660.540	0.000	FBN	43.225	
DR*RL	2	27.180	27.180	13.590	9.720	0.000	RV	45.380	
RS*RL	4	92.300	92.300	23.070	16.510	0.000	WAIT	44.910	
Error	166	232.060	232.060	1.400					
Total	179	2375.610							

Table I.3. Percentage On Time ANOVA Table and Tukey Multiple Comparison Test

Source	DF	Seq SS	Adj SS	Adj MS	F	P	DR	% On Time	Sig.
DR	1	403.440	403.440	403.440	20.990	0.000	RWK	92.930	
RS	2	2211.910	2211.910	1105.960	57.540	0.000	FIFO	89.936	
DR*RS	2	175.670	175.670	87.830	4.570	0.012	RS	% On Time	Sig.
RL	2	882.790	882.790	441.400	22.960	0.000	FBN	95.484	
DR*RL	2	494.380	494.380	247.190	12.860	0.000	WAIT	91.882	
RS*RL	4	2663.670	2663.670	665.920	34.650	0.000	RV	86.933	
Error	166	3190.620	3190.620	19.220					
Total	179	10022.480							

Table I.4. Average WIP ANOVA Table and Tukey Multiple Comparison Test

Source	DF	Seq SS	Adj SS	Adj MS	F	P	DR	Avg. WIP	Sig.
DR	1	68.070	68.070	68.070	52.540	0.000	RWK	130.561	
RS	2	473.050	473.050	236.520	182.550	0.000	FIFO	131.791	
DR*RS	2	3.550	3.550	1.780	1.370	0.257	RS	Avg. WIP	Sig.
RL	2	7408.780	7408.780	3704.390	2859.080	0.000	FBN	128.952	
DR*RL	2	70.490	70.490	35.250	27.200	0.000	WAIT	131.808	
RS*RL	4	356.630	356.630	89.160	68.810	0.000	RV	132.769	
Error	166	215.080	215.080	1.300					
Total	179	8595.650							

Table I.5. Average XT ANOVA Table and Tukey Multiple Comparison Test

Source	DF	Seq SS	Adj SS	Adj MS	F	P	DR	Avg. XT	Sig.
DR	1	0.009	0.009	0.009	48.550	0.000	RWK	1.526	
RS	2	0.046	0.046	0.023	123.830	0.000	FIFO	1.540	
DR*RS	2	0.001	0.001	0.000	1.630	0.199	RS	Avg. XT	Sig.
RL	2	1.055	1.055	0.527	2857.070	0.000	FBN	1.512	
DR*RL	2	0.009	0.009	0.004	23.050	0.000	WAIT	1.538	
RS*RL	4	0.041	0.041	0.010	55.770	0.000	RV	1.550	
Error	166	0.031	0.031	0.000					
Total	179	1.190							

Appendix J. Two Factor ANOVA and Tukey Analysis to Determine Robust Strategies Overall

This appendix contains the ANOVA and Tukey pairwise comparison tables for the two factor analysis of the strategies that perform well. These strategies are RWK/FBN, FIFO/FBN, RWK/WAIT, FIFO/WAIT, RWK/RV, and FIFO/RV. Based upon the ANOVA results for each performance measure, if the dispatching rule or rework strategy are shown to be significant factors (at a confidence level of 95 percent), the Tukey pairwise comparison test is done on those factors. If the interaction of dispatching rules and rework strategies is shown to be significant at a 95 percent confidence level, the Tukey pairwise comparison test will also be done for the interaction.

Figure J.1. ANOVA and Tukey Results for Average Cycle Time

Source	DF	Seq SS	Adj SS	Adj MS	F	P	DR	Avg. CT	Sig.
Fab	1	237925.000	237925.000	237925.000	29000.000	0.000	RWK	363.629	
DR	1	757.000	757.000	757.000	92.430	0.000	FIFO	366.529	
Fab*DR	1	53.000	53.000	53.000	6.450	0.012	RS	Avg. CT	Sig.
RS	2	6798.000	6798.000	3399.000	415.270	0.000	FBN	359.128	
Fab*RS	2	84.000	84.000	42.000	5.160	0.006	WAIT	366.725	
DR*RS	2	48.000	48.000	24.000	2.940	0.054	RV	369.384	
RL	2	89584.000	89584.000	44792.000	5472.290	0.000			
DR*RL	2	849.000	849.000	424.000	51.850	0.000			
RS*RL	4	5294.000	5294.000	1324.000	161.710	0.000			
Fab*RL	2	4021.000	4021.000	2011.000	245.630	0.000			
Error	340	2783.000	2783.000	8.000					
Total	359	348196.000							

Figure J.2. ANOVA and Tukey Results for St. Deviation of Cycle Time

Source	DF	Seq SS	Adj SS	Adj MS	F	P	DR	Std. Dev CT	Sig.
Fab	1	137568.300	137568.300	137568.300	110000.000	0.000	RWK	63.741	
DR	1	35.100	35.100	35.100	28.560	0.000	FIFO	64.365	
Fab*DR	1	0.300	0.300	0.300	0.260	0.607	RS	Std. Dev CT	Sig.
RS	2	343.500	343.500	171.800	139.940	0.000	FBN	62.813	
Fab*RS	2	139.900	139.900	69.900	56.980	0.000	WAIT	64.146	
DR*RS	2	3.100	3.100	1.600	1.270	0.281	RV	65.201	
RL	2	4418.300	4418.300	2209.100	1799.910	0.000			
DR*RL	2	47.100	47.100	23.500	19.180	0.000			
RS*RL	4	329.100	329.100	82.300	67.030	0.000			
Fab*RL	2	34.300	34.300	17.100	13.970	0.000			
Error	340	417.300	417.300	1.200					
Total	359	143336.200							

Figure J.3. ANOVA and Tukey Results for Percentage On Time

Source	DF	Seq SS	Adj SS	Adj MS	F	P
Fab	1	58.560	58.560	58.560	3.520	0.062
DR	1	513.130	513.130	513.130	30.830	0.000
Fab*DR	1	33.100	33.100	33.100	1.990	0.159
RS	2	4274.410	4274.410	2137.200	128.420	0.000
Fab*RS	2	3.010	3.010	1.510	0.090	0.913
DR*RS	2	223.060	223.060	111.530	6.700	0.001
RL	2	1550.880	1550.880	775.440	46.600	0.000
DR*RL	2	670.140	670.140	335.070	20.130	0.000
RS*RL	4	5114.940	5114.940	1278.740	76.840	0.000
Fab*RL	2	9.790	9.790	4.890	0.290	0.745
Error	340	5658.200	5658.200	16.640		
Total	359	18109.220				

DR	RS	% On Time	Sig.	DR	% On Time	Sig.
RWK	FBN	96.019		RWK	93.030	
FIFO	FBN	95.504		FIFO	90.642	
RWK	Wait	93.515		RS	% On Time	Sig.
FIFO	Wait	91.234		FBN	95.761	
RWK	RV	89.556		WAIT	92.374	
FIFO	RV	85.189		RV	87.373	

Figure J.4. ANOVA and Tukey Results for Average WIP

Source	DF	Seq SS	Adj SS	Adj MS	F	P
Fab	1	298790.000	298790.000	298790.000	210000.000	0.000
DR	1	131.000	131.000	131.000	92.490	0.000
Fab*DR	1	0.000	0.000	0.000	0.030	0.864
RS	2	1279.000	1279.000	640.000	450.190	0.000
Fab*RS	2	25.000	25.000	13.000	8.870	0.000
DR*RS	2	9.000	9.000	4.000	3.120	0.045
RL	2	16005.000	16005.000	8002.000	5632.100	0.000
DR*RL	2	152.000	152.000	76.000	53.330	0.000
RS*RL	4	1005.000	1005.000	251.000	176.870	0.000
Fab*RL	2	26.000	26.000	13.000	9.200	0.000
Error	340	483.000	483.000	1.000		
Total	359	317906.000				

DR	RS	Avg. WIP	Sig.	DR	Avg. WIP	Sig.
RWK	FBN	157.021		RWK	159.381	
FIFO	FBN	157.790		FIFO	160.590	
RWK	Wait	160.007		RS	Avg. WIP	Sig.
RWK	RV	161.115		FBN	157.406	
FIFO	Wait	161.378		WAIT	160.693	
FIFO	RV	162.600		RV	161.858	

Figure J.5. ANOVA and Tukey Results for Average XT

Source	DF	Seq SS	Adj SS	Adj MS	F	P
Fab	1	0.085	0.085	0.085	614.870	0.000
DR	1	0.013	0.013	0.013	95.210	0.000
Fab*DR	1	0.000	0.000	0.000	2.600	0.108
RS	2	0.075	0.075	0.037	270.350	0.000
Fab*RS	2	0.001	0.001	0.000	2.960	0.053
DR*RS	2	0.001	0.001	0.000	3.040	0.049
RL	2	1.607	1.607	0.804	5795.810	0.000
DR*RL	2	0.013	0.013	0.006	46.020	0.000
RS*RL	4	0.072	0.072	0.018	130.120	0.000
Fab*RL	2	0.034	0.034	0.017	123.720	0.000
Error	340	0.047	0.047	0.000		
Total	359	1.949				

DR	RS	Avg. XT	Sig.
RWK	FBN	1.494	
FIFO	FBN	1.502	
RWK	Wait	1.515	
RWK	RV	1.525	
FIFO	Wait	1.529	
FIFO	RV	1.540	

DR	Avg. XT	Sig.
RWK	1.512	
FIFO	1.524	
RS	Avg. XT	Sig.
FBN	1.498	
WAIT	1.522	
RV	1.533	

Appendix K. Fab Description

This appendix contains a description of the dataset used in this research. The dataset is publicly available on the Arizona State University website (Test Beds 2003). There are seven datasets in this test bed, and the dataset used in this research is dataset 3. There are eleven products in this dataset, and the routing for product 9 is on the following pages. The rest of the dataset is in an Excel workbook on a CD is attached to the back cover of the bound thesis. This workbook contains all of the data necessary to build the model used in this research. The database is divided into 14 worksheets. Below is a description of the contents of each worksheet.

Products: Contains arrival information for each of the eleven products. The C(?) at the top of the column headings indicates that the distribution used is constant.

Tools: Contains information about each of the tools, including the number of quantity of the tool, and the batching information,

Downtimes & Setups: Contains downtime data for each of the tool groups, including the mean time to failure and the mean time to repair. This also contains the necessary setup information for each tool. The E(?) at the top of the column headings indicates that the distribution used in exponential.

1-11: Contains the routing for each of the eleven products. This includes the load, unload, and processing time. The setup needed at the step is also given, and setups are only done when needed. This means that the setup time will not be incurred if the tool currently has the setup of the lot to be processed. Scrap and rework data is also given. The scrap and rework percentage refers to the percentage of wafers that will be scrapped from each lot. Throughout the data there are lines highlighted in black. These refer to steps that only wafers needing rework go through (rework loop). Wafers not needing rework skip these steps. After wafers needing rework have gone through all of the highlighted steps, they return to the step previous to the highlighting for inspection. It is possible for a reworked wafer to need rework multiple times. Once again, the C(?) in the column headings refers to the constant distribution.

It is important to note that there are some slight changes are made to this dataset. All of the routing information is the same for the MTO and MTS fabs, but the quantity of some of the tools are slightly changed (see table K.1). Also, only products one and five are used in the MTS fab and their changed from 20.81 to 4.16 hours and 17.47 to 10.48 hours, respectively.

Table K.1. Tool Quantity Changes between Fabs

	Initial Fab	MTO Fab	MTS Fab
Stepper	13	13	9
Furnace 3	8	12	8
Furnace 4	2	2	1
Furnace 5	2	4	2
High Implant	3	3	2
Med. Implant	4	4	3

Table K.2. Product 9 Routing

Step Num	Tool Group Used by Step	Load Time (Hours) C(?)	Processing Time			Batch ID	Unload Time (Hours) C(?)	Setup ID	% of Units Scrapped	% of Units Reworked
			Per-Unit (Hours) C(?)	Per-Lot (Hours) C(?)	Per-Batch (Hours) C(?)					
1	TERM_Computer_terminal			0.0125						
2	LIS_Laser_Scribe	0.0333		0.5000			0.0333			
3	PIRH1_Strip	0.0500		0.1167						
4	RINS1_Rinse			0.0833						
5	STI5_Dry_Rinse	0.0333		0.1333						
6	FURN5_Furnace_Tube	0.5833			4.4667	31	0.5833			
7	TERM_Computer_terminal			0.0125						
8	CVD5_CVD	0.0583			0.2333	2	0.0583			
9	AERO_Metrology	0.0167		0.2500			0.0167			
10	TERM_Computer_terminal			0.0125						
11	COAT3_Coater	0.0333	0.0250		0.0667		0.0333			
12	PAL_Photo_Aligner	0.0667	0.0182		0.4667		0.0667	gpsetup1		
13	DEV_Develop	0.0167	0.0250		0.0333		0.0167			
14	SCOP2_Metrology	0.0667	0.0020		0.1333		0.0667			10
15	COAT3_Coater	0.0333	0.0250				0.0333	gpsetup1		
16	PAL_Photo_Aligner	0.0667	0.0182				0.0667			
17	DEV_Develop	0.0167	0.0250				0.0167			
18	SCOP2_Metrology	0.0667	0.0020				0.0667			
19	SCOP2_Metrology	0.0667	0.0033				0.0667			
20	ITP_Metrology	0.0167	0.0017				0.0167			
21	TERM_Computer_terminal			0.0125						
22	TEG_Dry_Etch		0.0287				0.1667			
23	SCOP2_Metrology	0.0333	0.0017				0.0333			
24	TERM_Computer_terminal			0.0125						
25	MED_Med_Current_Implant	0.0333	0.0100				0.0333	jtsetup98		
26								gpsetup4		
27	STI2_Dry_Rinse	0.0833		0.1333			0.0833			
28	TERM_Computer_terminal			0.0125						
29	LFE_Asher	0.0333	0.0105				0.0833			
30	PIRH2_Strip	0.0333		0.1167			0.0333			
31	PIRH2_Strip	0.0333		0.1167			0.0333			
32	RINS2_Rinse	0.0333		0.1333			0.0333			
33	EST1_Dryer	0.0333		0.1333			0.0333			
34	SCOP2_Metrology	0.0667	0.0033				0.0667			
35	SCOP2_Metrology	0.0667		0.1667			0.0667			
36	VICK_Metrology	0.0167		0.1250			0.0167			
37	TERM_Computer_terminal			0.0125						
38	PIRH1_Strip	0.0500		0.1167						
39	RINS1_Rinse			0.0833						
40	STI5_Dry_Rinse	0.0333		0.1333						
41	PRPH_Wet_Etch			0.1000						
42	PRPH_Wet_Etch			0.1000						
43	STI5_Dry_Rinse	0.0333		0.1333						
44	FURN3_Furnace_Tube	0.5833			7.4667	7	0.5833			
45	TERM_Computer_terminal			0.0125						
46	OXIH_Wet_Etch	0.0333		0.0667			0.0333			
47	STI2_Dry_Rinse	0.0833		0.1333			0.0833			
48	NITH_Wet_Etch	0.0333		0.9167			0.0333			
49	NANO_Metrology	0.0167		0.0833			0.0333			
50	PIRH2_Strip	0.0333		0.1167			0.0333			
51	PIRH2_Strip	0.0333		0.1167			0.0333			
52	RINS2_Rinse	0.0333		0.1333			0.0333			
53	EST1_Dryer	0.0333		0.1333			0.0333			
54	SCOP2_Metrology	0.0333		0.0833			0.0333			
55	TERM_Computer_terminal			0.0125						
56	MED_Med_Current_Implant	0.0333	0.0100				0.0333	jtsetup99		
57								gpsetup4		
58	STI2_Dry_Rinse	0.0833		0.1333			0.0833			
59	TERM_Computer_terminal			0.0125						
60	COAT3_Coater	0.0333	0.0217		0.0667		0.0333			

61	PERK_Photo_Aligner	0.0167	0.0125		0.1000		0.0833	gpsetup18		
62	DEV_Develop	0.0167	0.0333		0.0333		0.0167			
63	SCOP2_Metrology	0.0667	0.0030		0.1333		0.0667			5.3
64	COAT3_Coater	0.0333	0.0217				0.0333	gpsetup18		
65	PERK_Photo_Aligner	0.0167	0.0125				0.0833			
66	DEV_Develop	0.0167	0.0333				0.0167			
67	SCOP2_Metrology	0.0667	0.0030				0.0667			
68	TERM_Computer_terminal			0.0125						
69	MTRX_Descum	0.0333	0.0208				0.0333			
70	OXIH_Wet_Etch	0.0333		0.0667			0.3333			
71	PIRH2_Strip	0.0333		0.1167			0.0333			
72	PIRH2_Strip	0.0333		0.1167			0.0333			
73	RINS2_Rinse	0.0333		0.1333			0.0333			
74	ESTI_Dryer	0.0333		0.1333			0.0333			
75	SCOP2_Metrology	0.0333		0.1667			0.0333			
76	TERM_Computer_terminal			0.0125						
77	PIRH1_Strip	0.0500		0.1167						
78	RINS1_Rinse			0.0833						
79	STI5_Dry_Rinse	0.0333		0.1333						
80	PRPH_Wet_Etch			0.1000						
81	PRPH_Wet_Etch			0.1000						
82	STI5_Dry_Rinse	0.0333		0.2000						
83	CVD4_CVD	0.0417			0.3333	32	0.0417			
84	SCOP1_Metrology			0.0083						
85	TERM_Computer_terminal			0.0125						
86	PHOS_Furnace_Tube	0.4167			2.8000	33	0.4167			
87	TERM_Computer_terminal			0.0125						
88	STI5_Dry_Rinse	0.0333		0.1333						
89	PIRH1_Strip	0.0500		0.1167						
90	RINS1_Rinse			0.0833						
91	STI5_Dry_Rinse	0.0333		0.1333						
92	CVD1_CVD	0.0417			0.3167	34	0.0417			
93	TERM_Computer_terminal			0.0125						
94	COAT3_Coater	0.0333	0.0217		0.0667		0.0333			
95	PAL_Photo_Aligner	0.0167	0.0333		0.4333		0.0833	gpsetup8		
96	DEV_Develop	0.0167	0.0250		0.0333		0.0167			
97	SCOP2_Metrology	0.0667	0.0012		0.1333		0.0667			6.8
98	COAT3_Coater	0.0333	0.0217				0.0333	gpsetup8		
99	PAL_Photo_Aligner	0.0167	0.0333				0.0833			
100	DEV_Develop	0.0167	0.0250				0.0167			
101	SCOP2_Metrology	0.0667	0.0012				0.0667			
102	ITP_Metrology	0.0167	0.0083				0.0167			
103	TERM_Computer_terminal			0.0125						
104	OLAM_Dry_Etch		0.0350				0.7500			
105	SCOP2_Metrology	0.0667	0.0033				0.0667			
106	LFE_Asher	0.0167	0.0070				0.0167			
107	PIRH2_Strip	0.0333		0.1167			0.0333			
108	PIRH2_Strip	0.0333		0.1167			0.0333			
109	RINS2_Rinse	0.0333		0.1333			0.0333			
110	ESTI_Dryer	0.0333		0.1333			0.0333			
111	VICK_Metrology	0.0167		0.0833			0.0167			
112	SCOP2_Metrology	0.0333		0.1667			0.0333			
113	TERM_Computer_terminal			0.0125						
114	XLAM_Dry_Etch		0.0333				0.1667		0.4	
115	PIRH2_Strip	0.0333		0.1167			0.0333			
116	PIRH2_Strip	0.0333		0.1167			0.0333			
117	RINS2_Rinse	0.0333		0.1333			0.0333			
118	ESTI_Dryer	0.0333		0.1333			0.0333			
119	SCOP2_Metrology	0.0333		0.1667			0.0333			
120	TERM_Computer_terminal			0.0125						
121	MED_Med_Current_Implant	0.0333	0.0100				0.0333	jtsetup100		
122								gpsetup4		
123	STI2_Dry_Rinse	0.0833		0.1333			0.0833			
124	TERM_Computer_terminal			0.0125						
125	PIRH1_Strip	0.0500		0.1167						

126	RINS1_Rinse			0.0833						
127	STI5_Dry_Rinse	0.0333		0.1333						
128	PRPH_Wet_Etch			0.1000						
129	PRPH_Wet_Etch			0.1000						
130	STI5_Dry_Rinse	0.0333		0.1333						
131	FURN3_Furnace_Tube	0.5833			3.7417	26	0.5833			
132	TERM_Computer_terminal			0.0125						
133	MED_Med_Current_Implant	0.0333	0.0100				0.0333	jtsetup101		
134								gpsetup2		
135	STI2_Dry_Rinse	0.0833		0.1333			0.0833			
136	TERM_Computer_terminal			0.0125						
137	PIRH1_Strip	0.0500		0.1167						
138	RINS1_Rinse			0.0833						
139	STI5_Dry_Rinse	0.0333		0.1333						
140	CVD1_CVD	0.0333			0.2917	35	0.0333			
141	TERM_Computer_terminal			0.0125						
142	FURN3_Furnace_Tube	0.5833			4.0833	13	0.5833			
143	TERM_Computer_terminal			0.0125						
144	OLAM_Dry_Etch		0.0283				0.2500			
145	LFE_Asher	0.0167	0.0053				0.0167			
146	TERM_Computer_terminal			0.0125						
147	PIRH2_Strip	0.0333		0.1167			0.0333			
148	PIRH2_Strip	0.0333		0.1167			0.0333			
149	RINS2_Rinse	0.0333		0.1333			0.0333			
150	ESTI_Dryer	0.0333		0.1333			0.0333			
151	OXIH_Wet_Etch	0.0333		0.0667			0.0333			
152	ESTI_Dryer	0.0333		0.1333			0.0333			
153	TERM_Computer_terminal			0.0125						
154	HIGH_High_Current_Implant	0.0667	0.0533				0.0667	jtsetup102		
155								gpsetup3		
156	TERM_Computer_terminal		0.0125							
157	PIRH1_Strip	0.0500		0.1167						
158	RINS1_Rinse			0.0833						
159	STI5_Dry_Rinse	0.0333		0.1333						
160	PRPH_Wet_Etch			0.1000						
161	PRPH_Wet_Etch			0.1000						
162	STI5_Dry_Rinse	0.0333		0.1333						
163	CVD5_CVD	0.0583			0.1950	36	0.0583			
164	TERM_Computer_terminal			0.0125						
165	FURN3_Furnace_Tube	0.5833			3.0833	37	0.5833			
166	TERM_Computer_terminal			0.0125						
167	CVD4_CVD	0.0583			0.2783	16	0.0583			
168	SCOP1_Metrology			0.0117						
169	TERM_Computer_terminal			0.0125					0.2	
170	PHOS_Furnace_Tube	0.4167			3.3067	17	0.4167			
171	FSI_Clean	0.0333		0.5833			0.0333			
172	TERM_Computer_terminal			0.0125						
173	PIRH2_Strip	0.0333		0.1167			0.0333			
174	PIRH2_Strip	0.0333		0.1167			0.0333			
175	RINS2_Rinse	0.0333		0.1333			0.0333			
176	ESTI_Dryer	0.0333		0.1333			0.0333			
177	COAT3_Coater	0.0167	0.0375		0.0333		0.0167			
178	PERK_Photo_Aligner	0.0167	0.0292		0.4333		0.0833	gpsetup10		
179	DEV_Develop	0.0167	0.0417		0.0333		0.0167			
180	SCOP2_Metrology	0.0667	0.0020		0.1333		0.0667			4.5
181	COAT3_Coater	0.0167	0.0375				0.0167	gpsetup10		
182	PERK_Photo_Aligner	0.0167	0.0292				0.0833			
183	DEV_Develop	0.0167	0.0417				0.0167			
184	SCOP2_Metrology	0.0667	0.0020				0.0667			
185	TERM_Computer_terminal			0.0125						
186	MTRX_Descum	0.0333	0.0208				0.0333			
187	POLH_Wet_Etch	0.0167		0.2500			0.3333			
188	SCOP2_Metrology	0.0333	0.0017				0.0333			
189	OXIH_Wet_Etch	0.0333		0.0667			0.0333			
190	PIRH2_Strip	0.0333		0.1167			0.0333			

191	PIRH2_Strip	0.0333		0.1167			0.0333			
192	RINS2_Rinse	0.0333		0.1333			0.0333			
193	ESTI_Dryer	0.0333		0.1333			0.0333			
194	NITH_Wet_Etch	0.0333		0.4167			0.0333			
195	SCOP2_Metrology	0.0667	0.0067				0.0667			
196	SCOP2_Metrology	0.0333		0.1667			0.0333			
197	TERM_Computer_terminal			0.0125						
198	PIRH1_Strip	0.0500		0.1167						
199	RINS1_Rinse			0.0833						
200	STI5_Dry_Rinse	0.0333		0.1333						
201	CVD1_CVD	0.0333			0.2217	18	0.0333			
202	TERM_Computer_terminal			0.0125						
203	WATJ_Metal_Dep			1.6667						
204	TERM_Computer_terminal			0.0125						
205	DEGH_Deglaze	0.0333		0.2700			0.0333			
206	DEGH_Deglaze			0.0833						
207	PIRH1_Strip	0.0500		0.1167						
208	RINS1_Rinse			0.0833						
209	STI5_Dry_Rinse	0.0333		0.1333						
210	FURN4_Furnace_Tube	0.5833			3.7667	38	0.5833			
211	TERM_Computer_terminal			0.0125						
212	COAT5_Coater	0.0333	0.0305				0.0333			
213	OLAM_Dry_Etch	0.0833	0.0383				0.2833			
214	NANO_Metrology	0.0083	0.0250				0.0083			
215	SCOP2_Metrology	0.0333	0.0017				0.0333			
216	LFE_Asher	0.0167	0.0053				0.0167			
217	PIRH2_Strip	0.0333		0.1167			0.0333			
218	PIRH2_Strip	0.0333		0.1167			0.0333			
219	RINS2_Rinse	0.0333		0.1333			0.0333			
220	ESTI_Dryer	0.0333		0.1333			0.0333			
221	SCOP2_Metrology	0.0333		0.0500			0.0333			
222	TERM_Computer_terminal			0.0125					0.2	
223	COAT3_Coater	0.0167	0.0250		0.0333		0.0167			
224	PERK_Photo_Aligner	0.0333	0.0333		0.4500		0.0833	gpsetup25		
225	DEV_Develop	0.0083	0.0333		0.0167		0.0083			
226	SCOP2_Metrology	0.0667	0.0020		0.1333		0.0667			8.3
227	COAT3_Coater	0.0167	0.0250				0.0167			
228	PERK_Photo_Aligner	0.0333	0.0333				0.0833	gpsetup25		
229	DEV_Develop	0.0083	0.0333				0.0083			
230	SCOP2_Metrology	0.0667	0.0020				0.0667			
231	ITP_Metrology	0.0167	0.0083				0.0167			
232	TERM_Computer_terminal			0.0125						
233	MTRX_Descum	0.0500	0.0192				0.0333			
234	OXIH_Wet_Etch	0.0333		0.0667			0.3333			
235	OLAM_Dry_Etch		0.0650				0.1667			
236	SCOP2_Metrology	0.0333	0.0017				0.0333			
237	LFE_Asher	0.0167	0.0053				0.0167			
238	PIRH2_Strip	0.0333		0.1167			0.0333			
239	PIRH2_Strip	0.0333		0.1167			0.0333			
240	RINS2_Rinse	0.0333		0.1333			0.0333			
241	ESTI_Dryer	0.0333		0.1333			0.0333			
242	VICK_Metrology	0.0167		0.0833			0.0167			
243	SCOP2_Metrology	0.0667		0.1667			0.0667			
244	SCOP2_Metrology	0.0333		0.0500			0.0333			
245	TERM_Computer_terminal			0.0125						
246	MED_Med_Current_Implant	0.0333	0.0100				0.0333	jtsetup103		
247								gpsetup2		
248	TERM_Computer_terminal			0.0125						
249	PIRH2_Strip	0.0333		0.1167			0.0333			
250	PIRH2_Strip	0.0333		0.1167			0.0333			
251	RINS2_Rinse	0.0333		0.1333			0.0333			
252	ESTI_Dryer	0.0333		0.1333			0.0333			
253	PRMH_Rinse	0.0833		0.1667			0.0833			
254	STI6_Dry_Rinse	0.0833		0.1667			0.0833			
255	METL_Metal_Dep	0.0167	0.0200				0.0167			

256	TERM_Computer_terminal			0.0125						
257	COAT3_Coater	0.0333	0.0350		0.0667		0.0333			
258	PERK_Photo_Aligner	0.0167	0.0417		0.4000		0.0500	gpsetup26		
259	DEV_Develop	0.0042	0.0525		0.0083		0.0042			
260	SCOP2_Metrology	0.0833	0.0180		0.1667		0.0833			16
261	COAT3_Coater	0.0333	0.0350				0.0333			
262	PERK_Photo_Aligner	0.0167	0.0417				0.0500	gpsetup26		
263	DEV_Develop	0.0042	0.0525				0.0042			
264	SCOP2_Metrology	0.0833	0.0180				0.0833			
265	TERM_Computer_terminal			0.0125						
266	MLAM_Dry_Etch		0.0867				0.2500			
267	SCOP2_Metrology	0.0333	0.0017				0.0333		1	
268	STRP_Strip			0.5833						
269	LFE_Asher	0.0167	0.0122				0.0167			
270	SCOP2_Metrology	0.0833		0.1667			0.0833			
271	VICK_Metrology	0.0167		0.1250			0.0167			
272	SCOP2_Metrology	0.0333		0.0500			0.0333			
273	TERM_Computer_terminal			0.0125						
274	STI4_Dry_Rinse			0.1667						
275	FURN2_Furnace_Tube	0.3333			2.3333	39	0.3333			
276	TERM_Computer_terminal			0.0125						
277	TERM_Computer_terminal			0.0125						
278	STI4_Dry_Rinse			0.1667						
279	CVD2_CVD	0.3333		1.1833			0.3333			
280	CVD2_CVD	0.3333		1.2333			0.3333			
281	TERM_Computer_terminal			0.0125						
282	COAT2_Coater	0.0333	0.0350		0.0667		0.0333			
283	PERK_Photo_Aligner	0.0167	0.0188		0.3667		0.0167	gpsetup15		
284	DEV_Develop	0.0167	0.0220		0.0333		0.0167			
285	SCOP2_Metrology	0.0667	0.0013		0.1333		0.0667			0.8
286	COAT2_Coater	0.0333	0.0350				0.0333			
287	PERK_Photo_Aligner	0.0167	0.0188				0.0167	gpsetup15		
288	DEV_Develop	0.0167	0.0220				0.0167			
289	SCOP2_Metrology	0.0667	0.0013				0.0667			
290	TERM_Computer_terminal			0.0125						
291	OLAM_Dry_Etch		0.0667				0.1667			
292	SCOP2_Metrology	0.0333	0.0017				0.0333			
293	LFE_Asher	0.0167	0.0070				0.0167			
294	TERM_Computer_terminal			0.0125						
295	COAT1_Coater	0.0333	0.0217				0.0333			
296	TERM_Computer_terminal			0.0125						
297	BAGR_Backgrind	0.0333		0.5333			0.0333			
298	HOOD_Rinse	0.0167		0.2500			0.0167			
299	HOOD_Rinse			0.3000						
300	STI3_Dry_Rinse	0.0833		0.2500			0.0833			
301	TUBE_Alloy	0.0167			0.8250	21	0.0167			
302	TERM_Computer_terminal			0.0125						
303	PR1_Probe	0.1167	0.1667				0.1167			
304	PR1_Probe	0.0833		0.6000			0.0833			

